

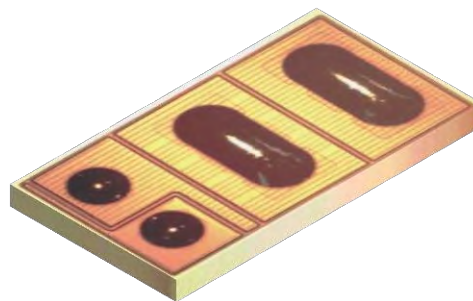
Enhancement Mode GaN on Silicon Enables Increased Performance and New Applications

David Reusch

Director of Applications Engineering
Efficient Power Conversion

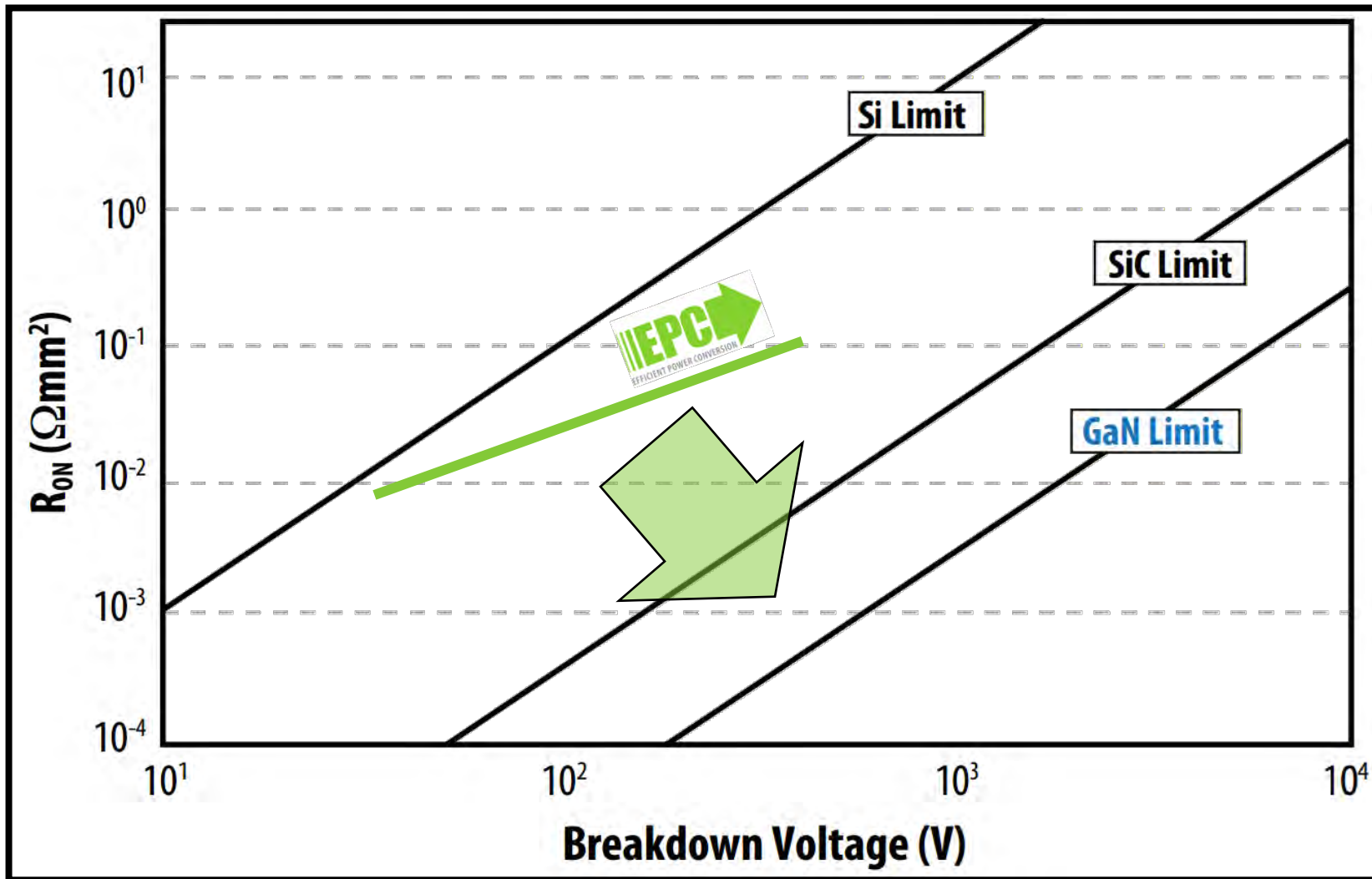
- How eGaN FETs work
- Design Basics
- Design Examples
- A Look into the Future
- Q & A

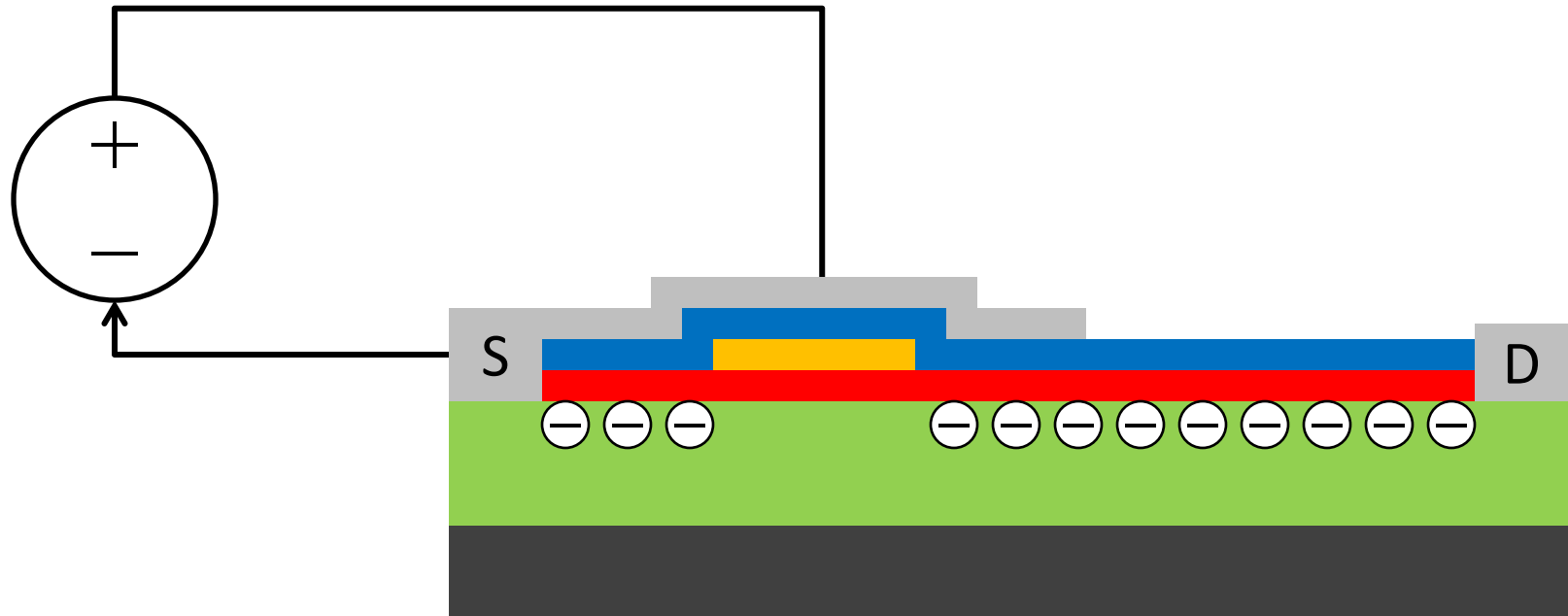
How eGaN FETs Work and State-of-the-Art Technology



- Lower On Resistance
- Faster
- Less Capacitance
- Smaller
- Lower Cost

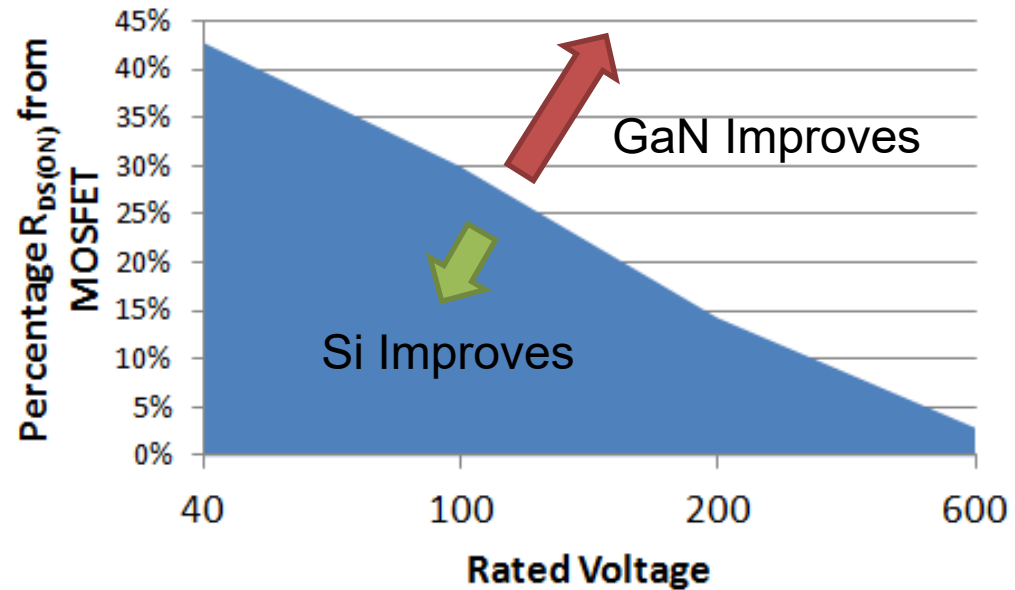
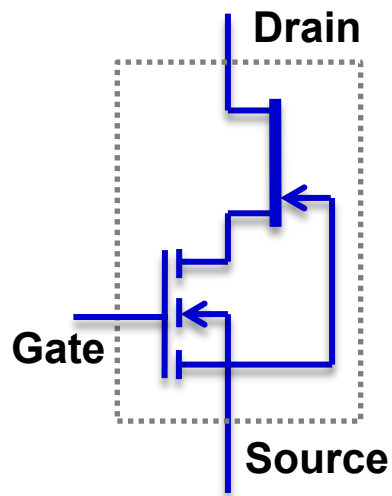
Why Gallium Nitride?

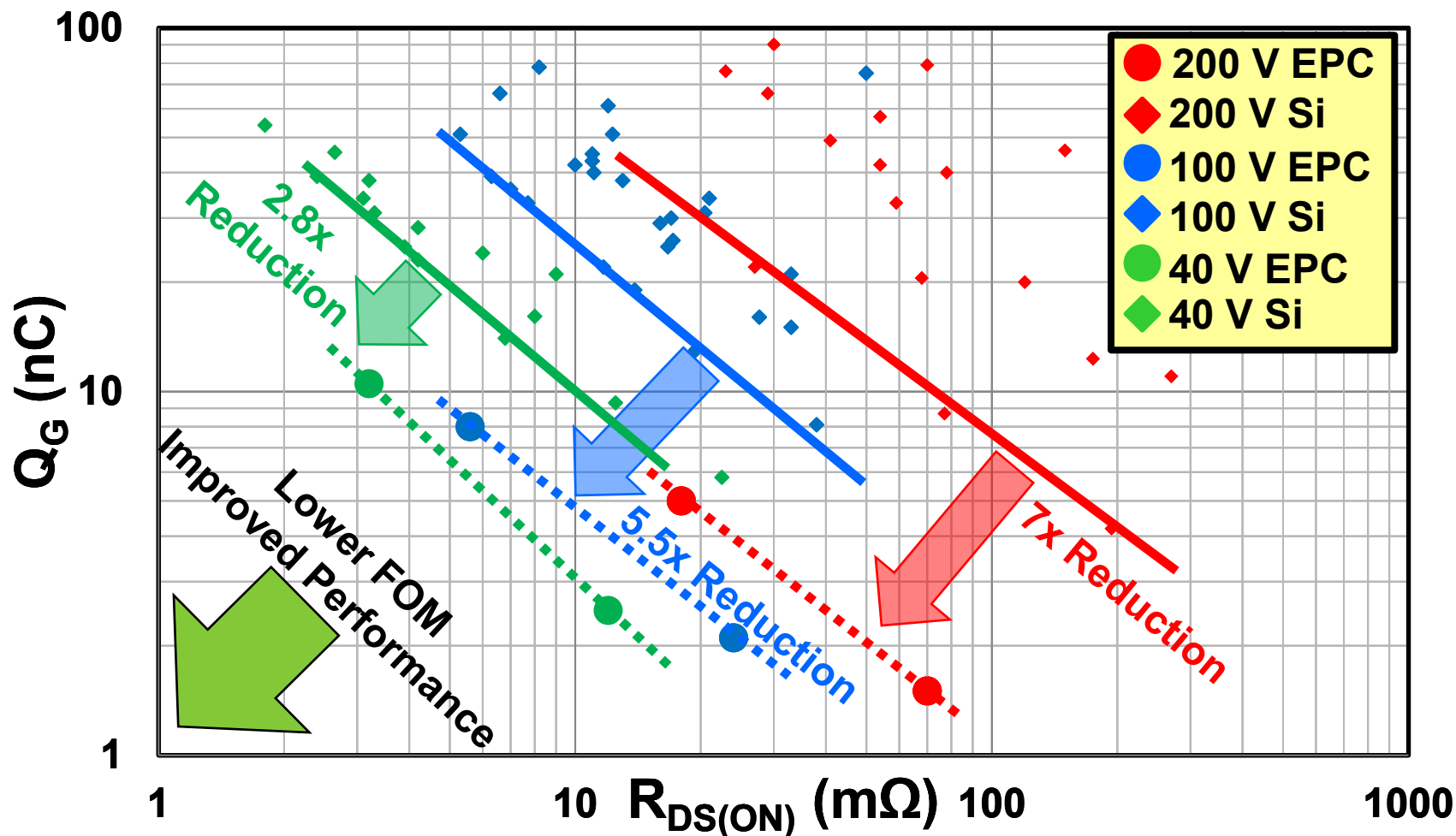


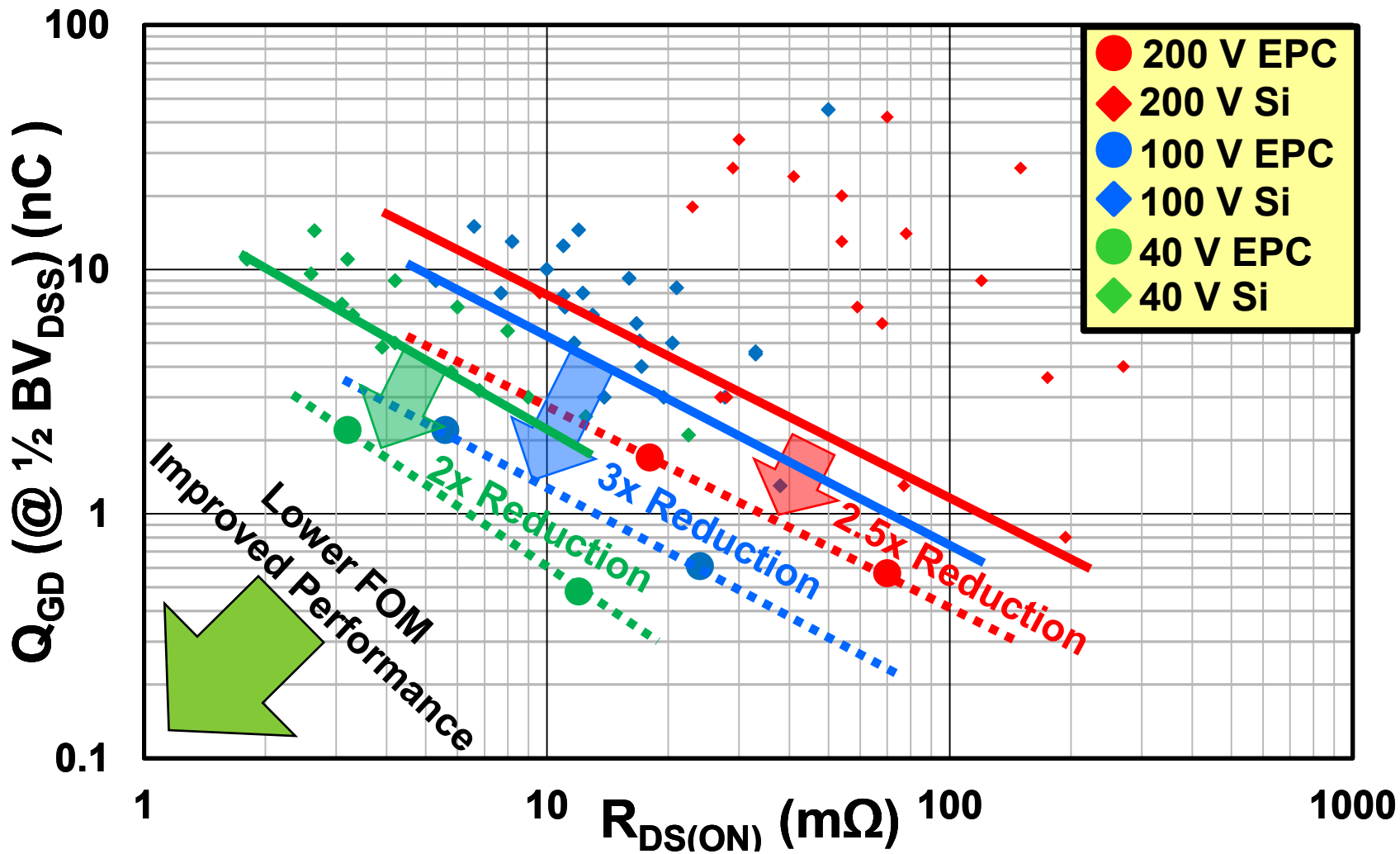


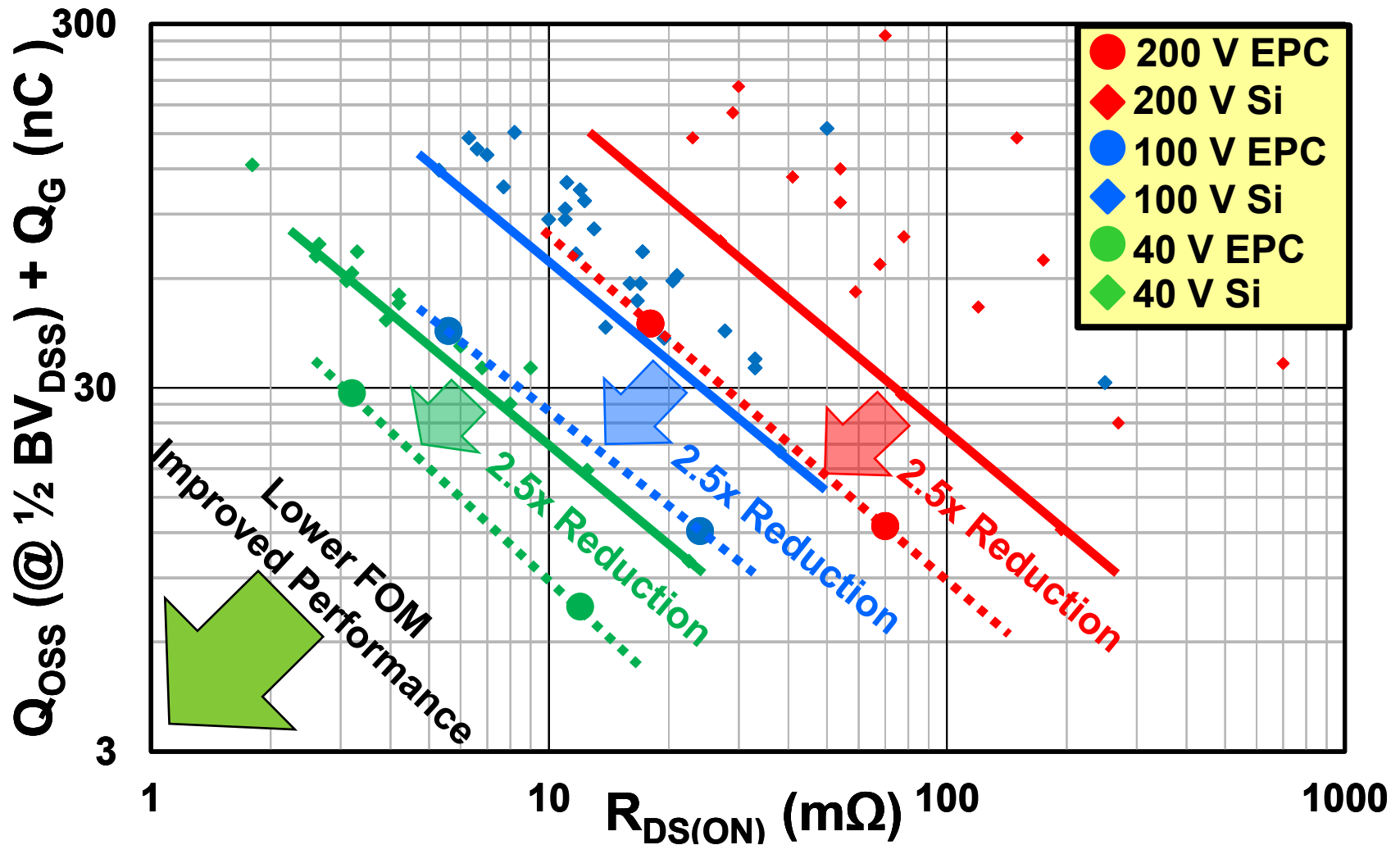
A positive voltage from Gate-To-Source establishes an electron gas under the gate

Cascode devices combine a depletion mode GaN transistor with a low voltage enhancement mode MOSFET









Like A MOSFET

- I^2R Conduction Loss
- Capacitive Switching Losses
- Gate Drive Losses
- $V \times I$ Switching Loss

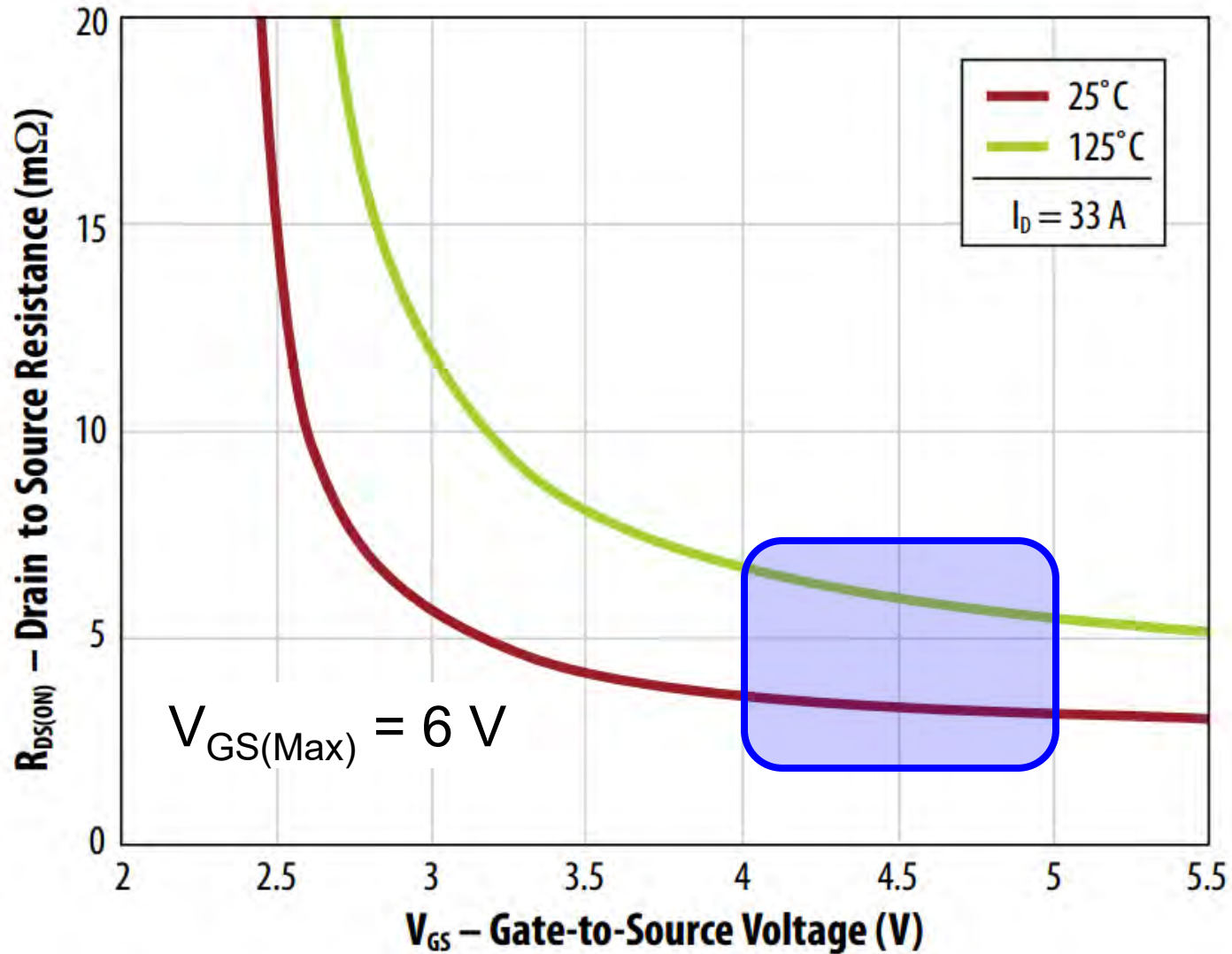
Not Like A MOSFET

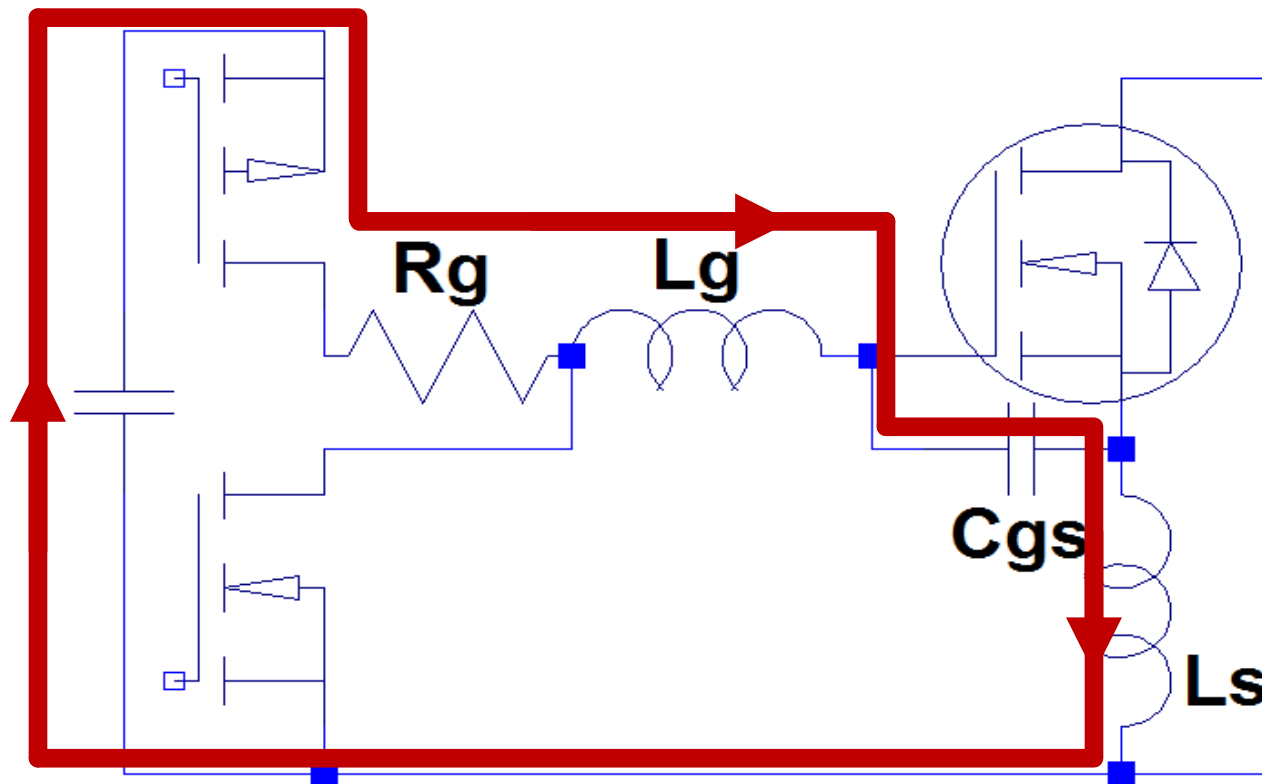
- High Reverse Conduction Loss
- No Body Diode Reverse Recovery Loss

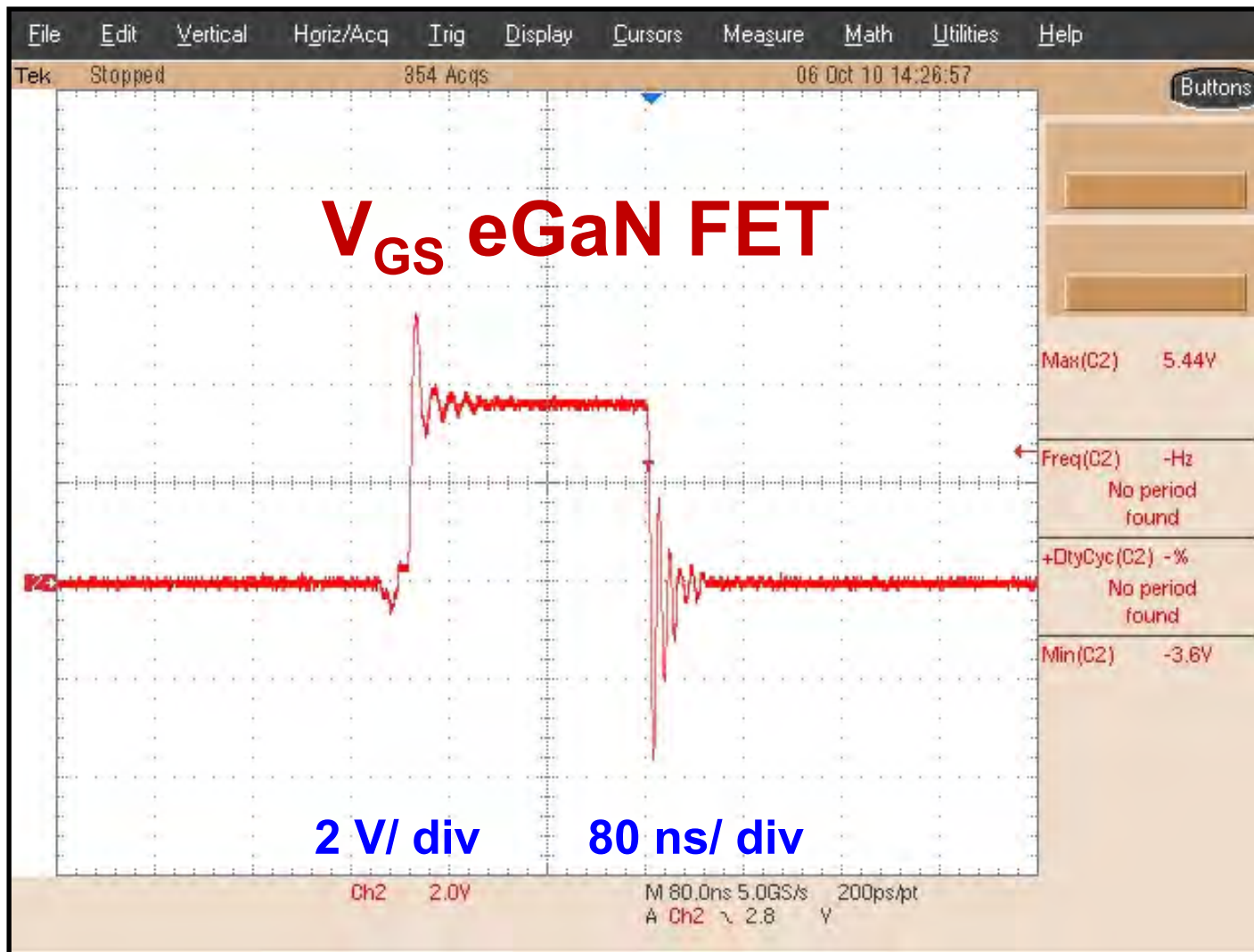
Can be much, much better than
comparable silicon MOSFET

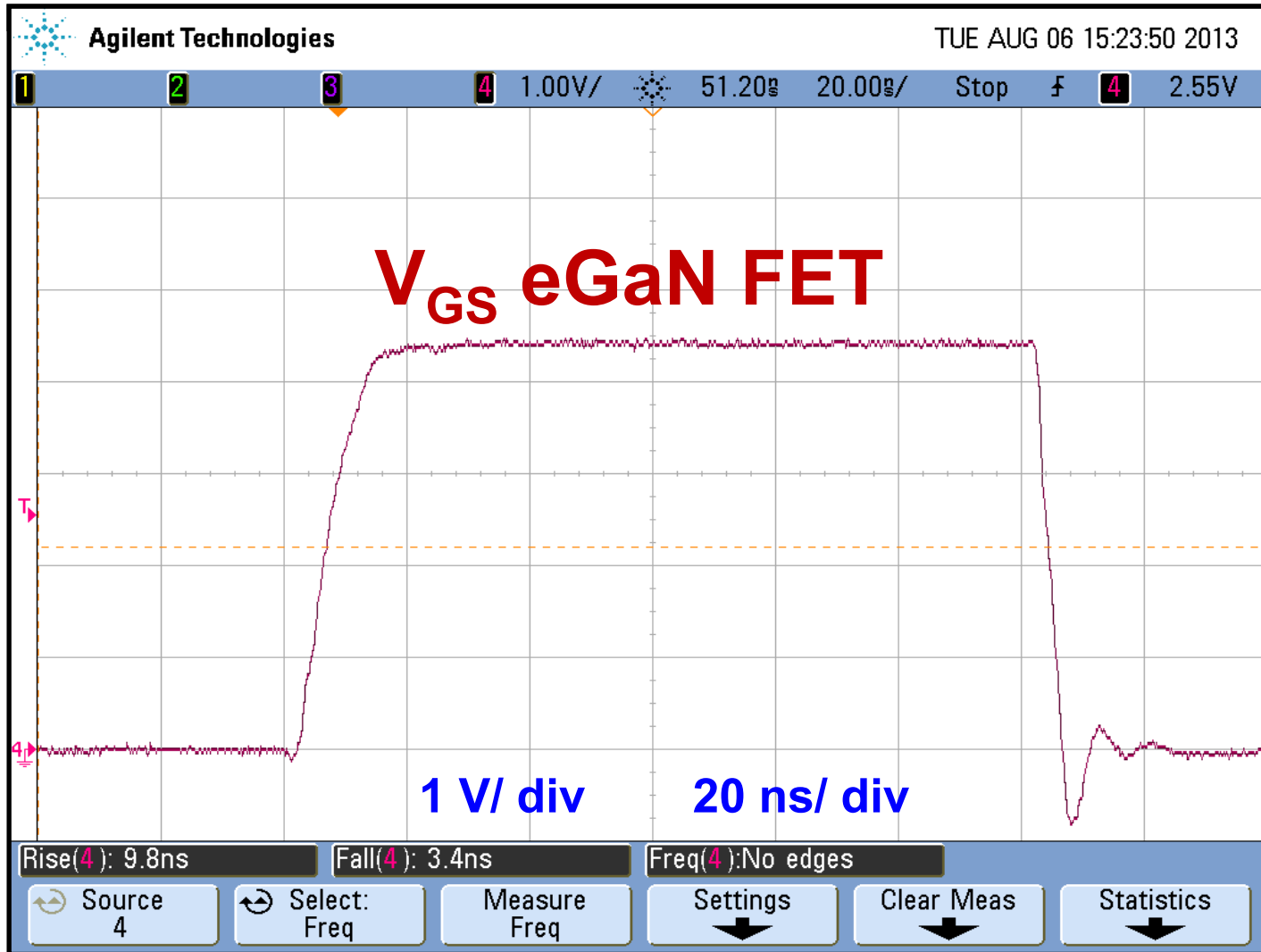
Design Basics

Gate Drive

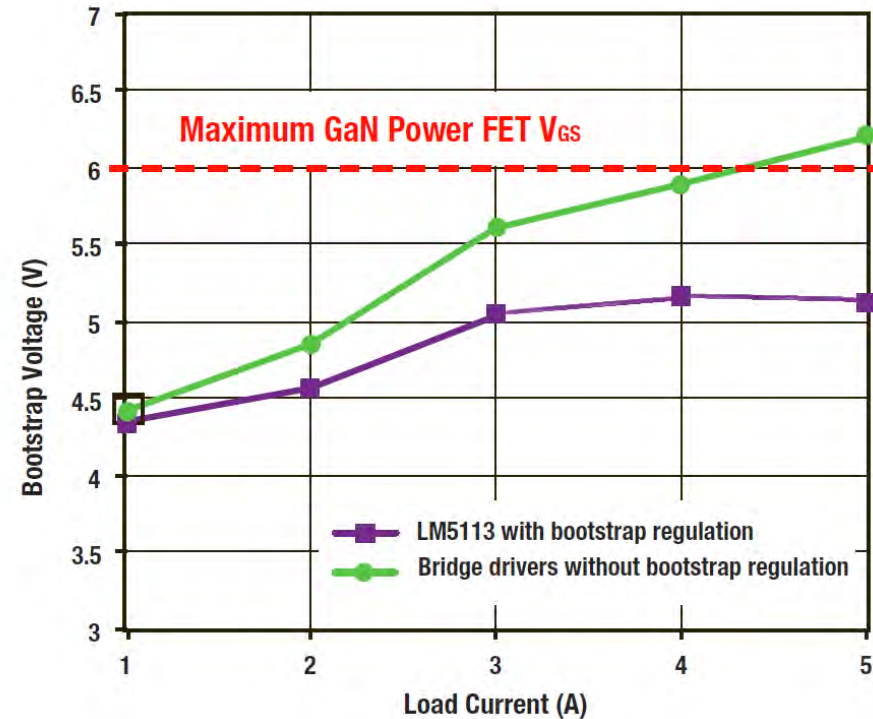
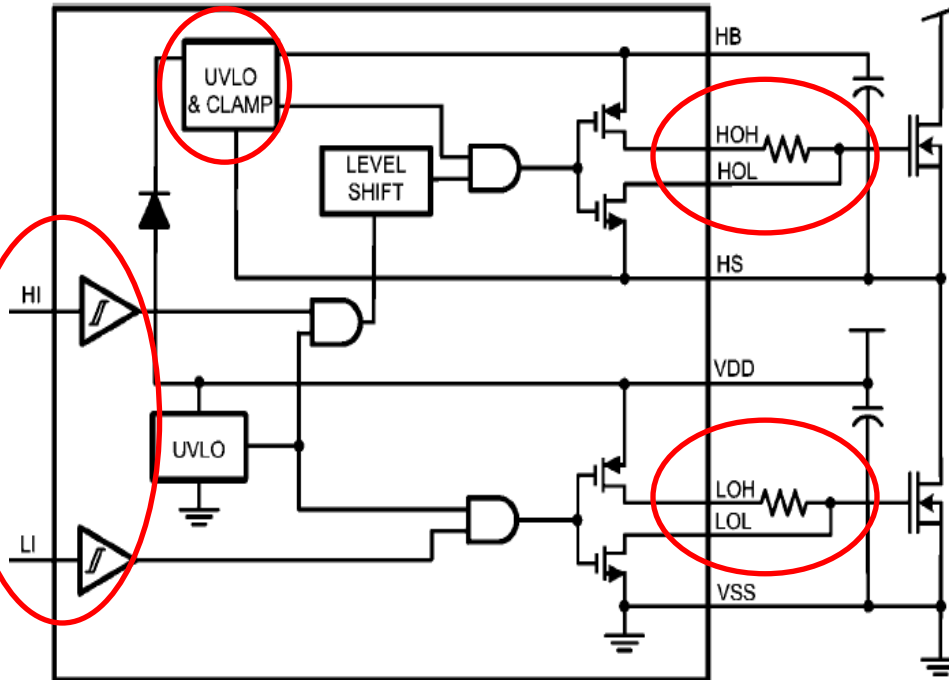






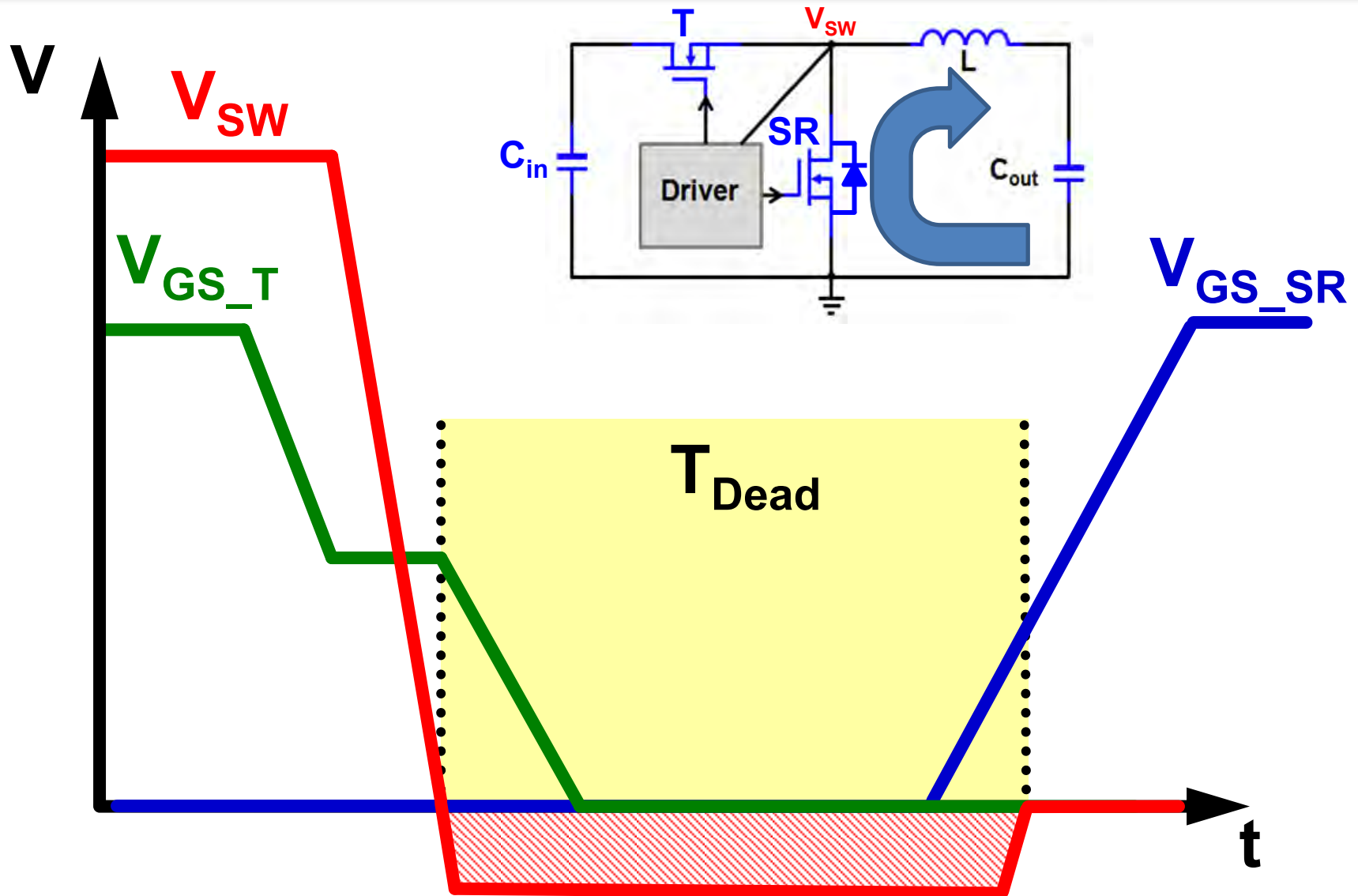


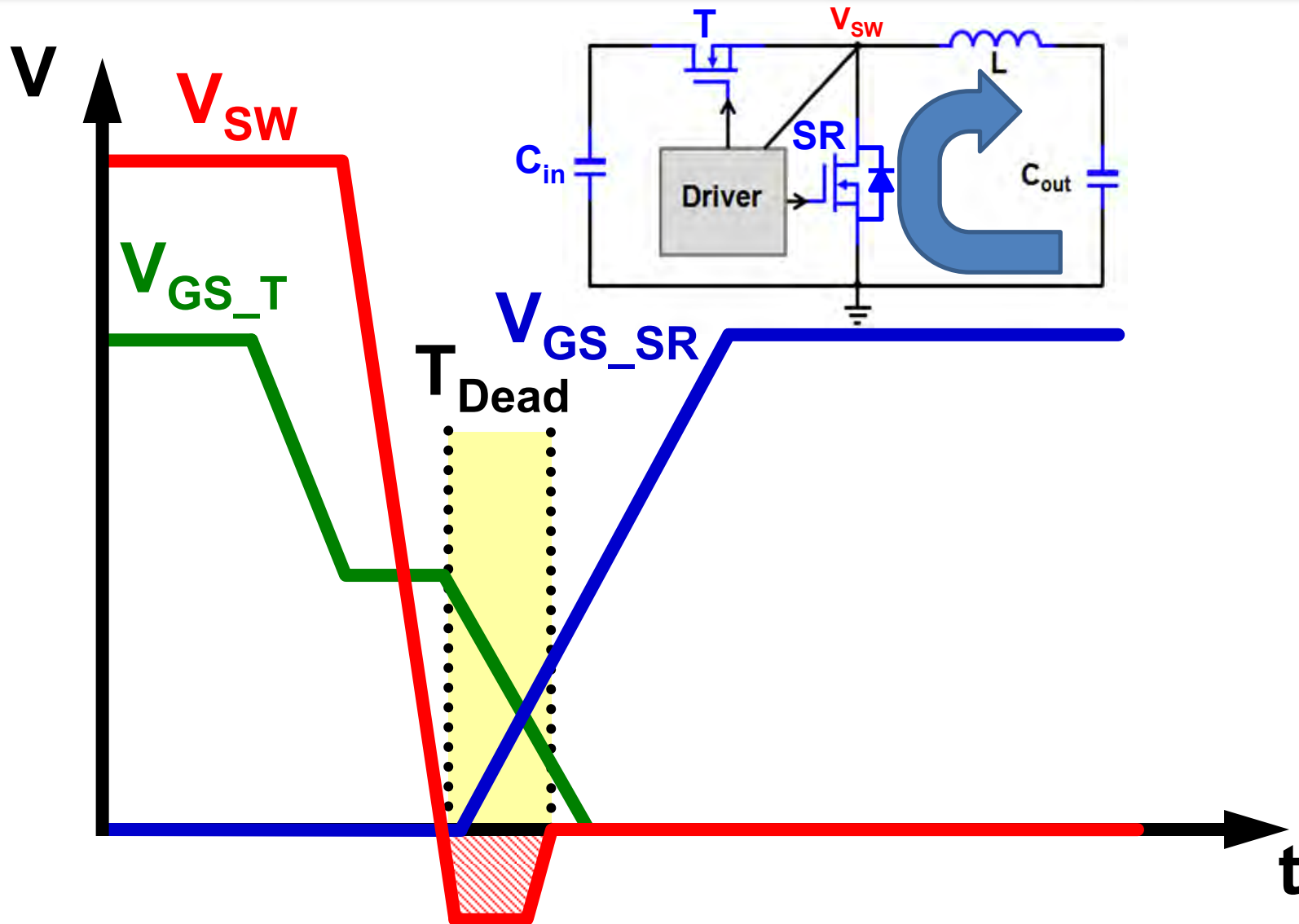
LM5113

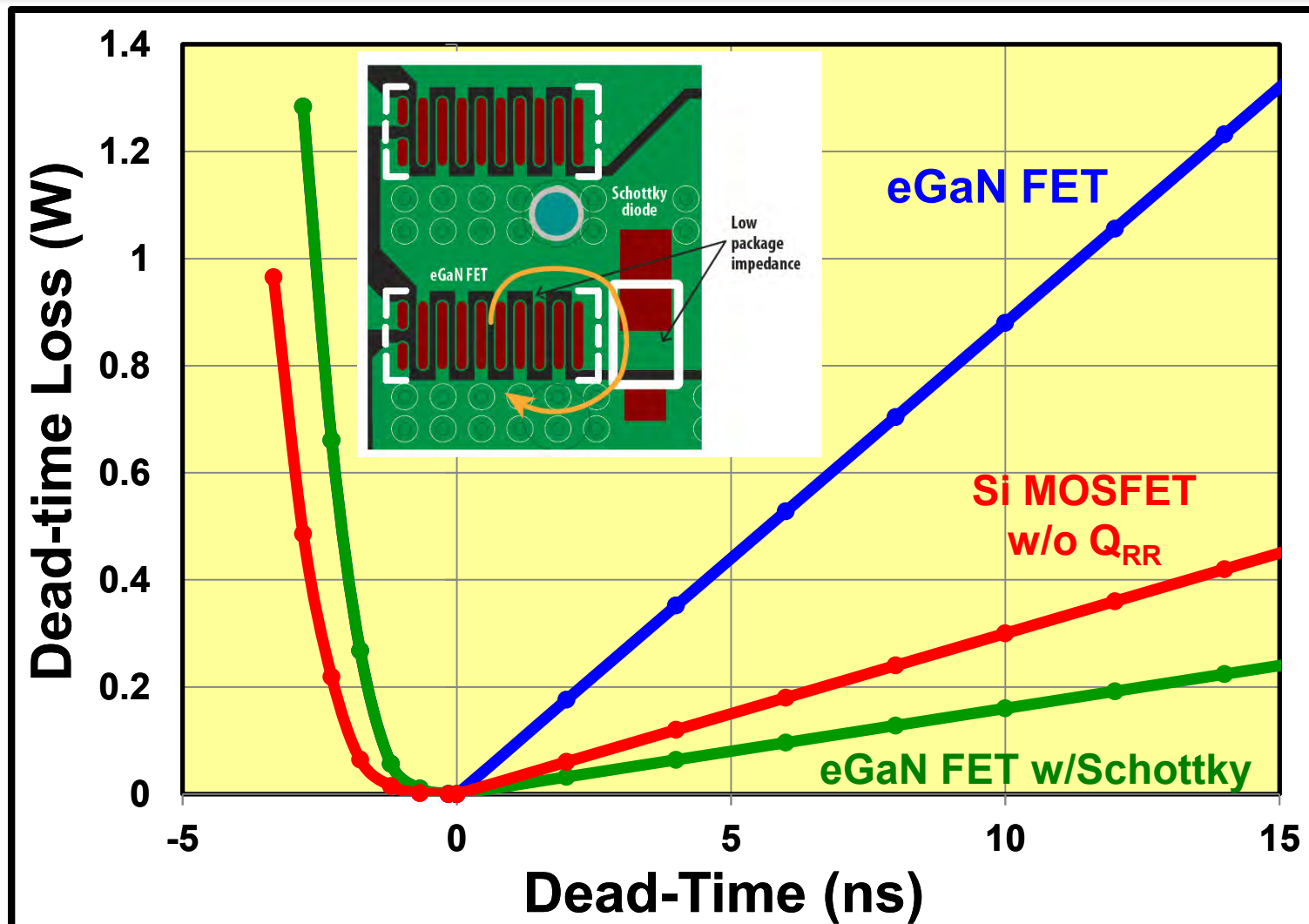


Reference: Texas Instruments, "Gate Drivers for Enhancement Mode GaN Power FETs 100V Half-Bridge and Low-Side Drivers Enable Greater Efficiency, Power Density, and Simplicity," SNVB001

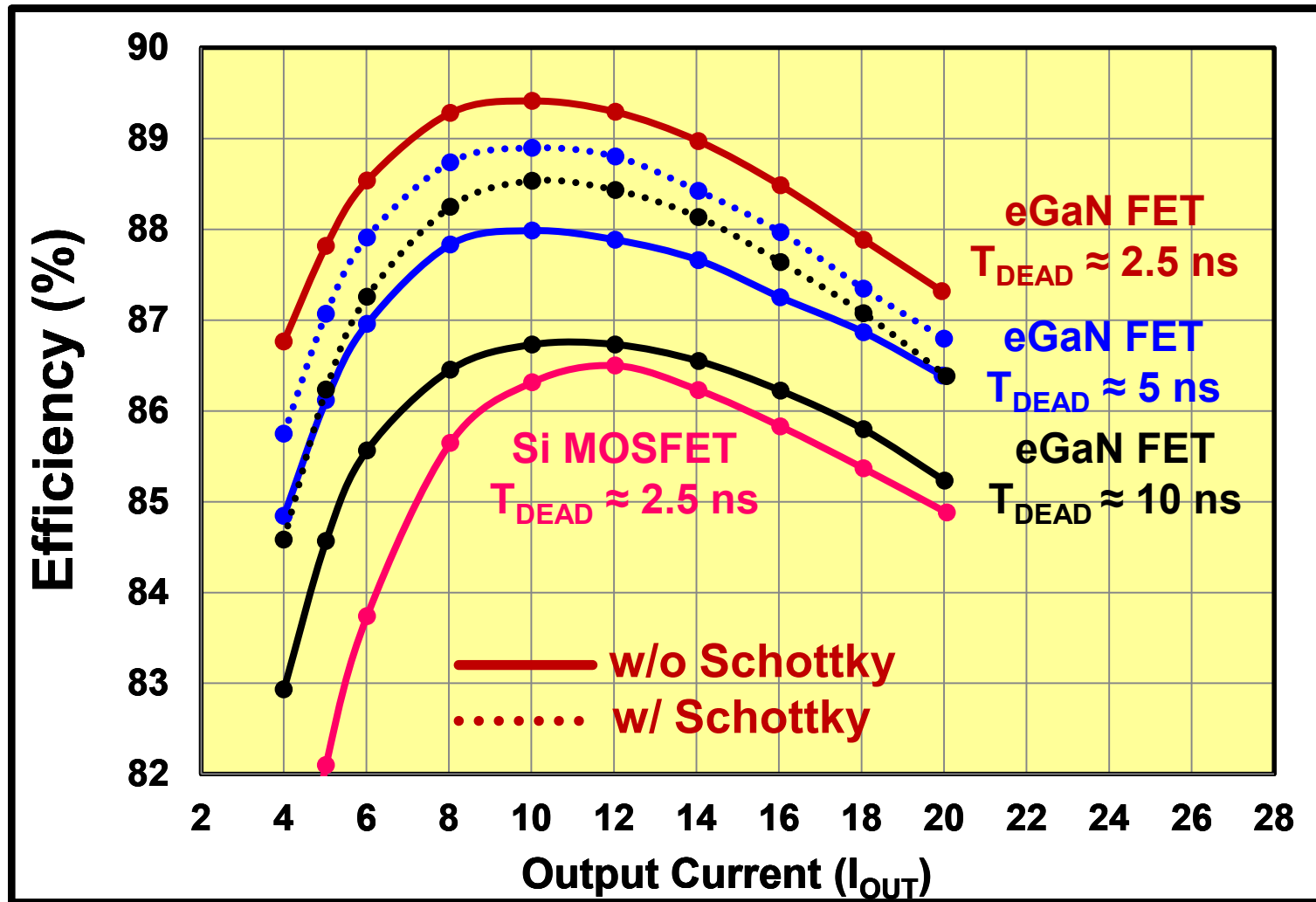
Dead-time Requirements





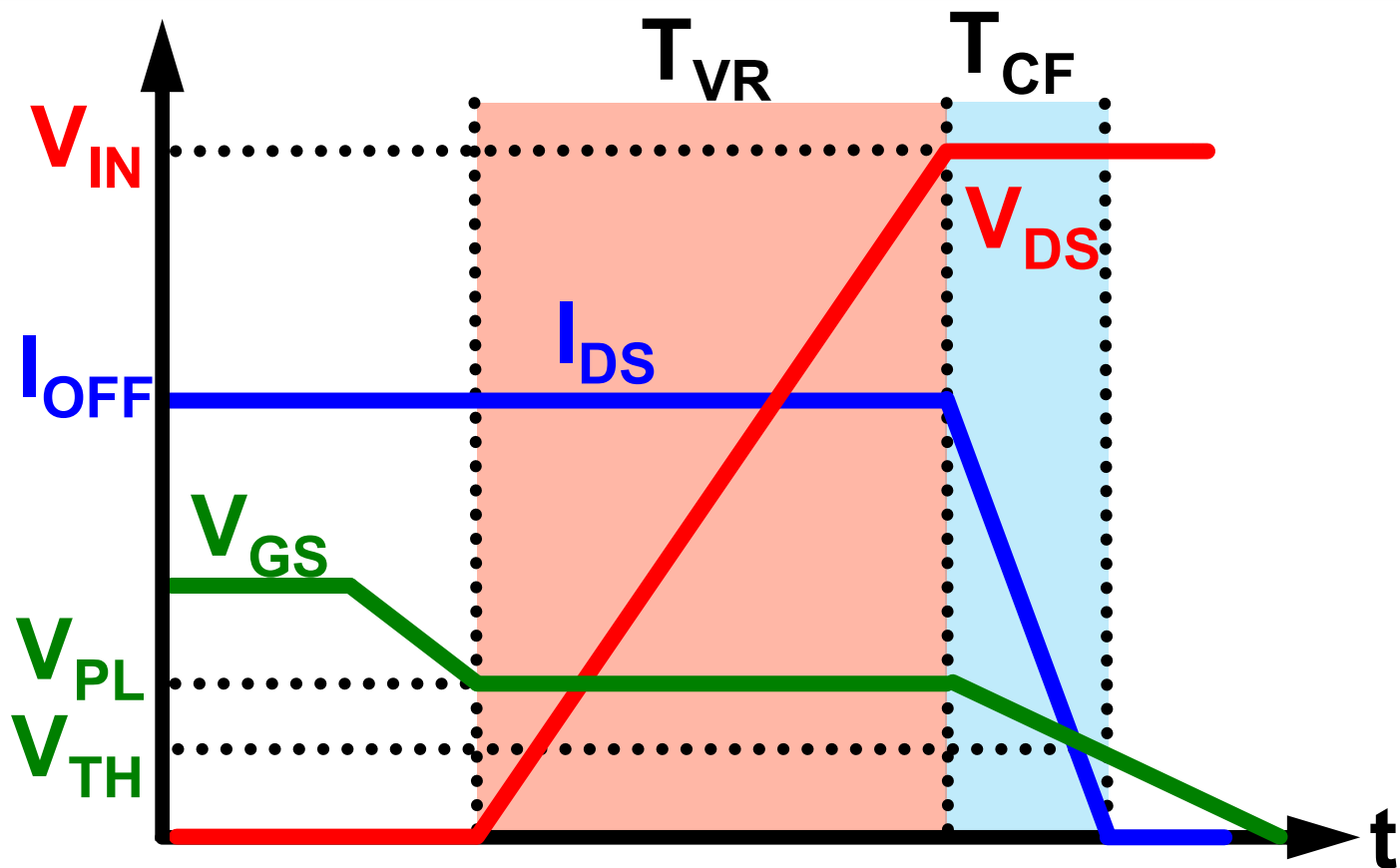


$V_{IN} = 12\text{ V}$, $V_{OUT} = 1.2\text{ V}$, $I_{OUT} = 20\text{ A}$, and $F_S = 1\text{ MHz}$



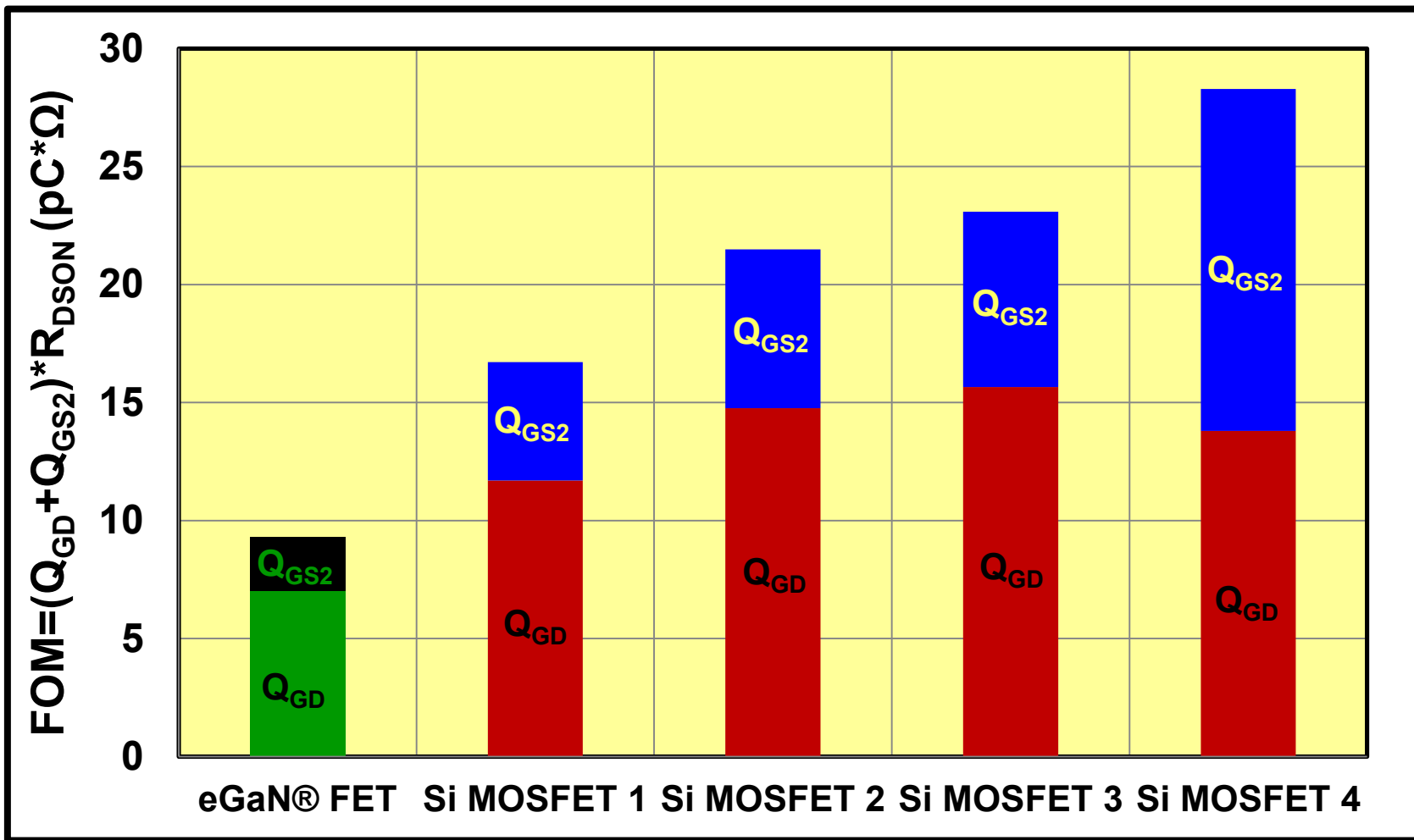
$V_{IN} = 12$ V, $V_{OUT} = 1.2$ V, and $F_S = 1$ MHz

PCB Layout

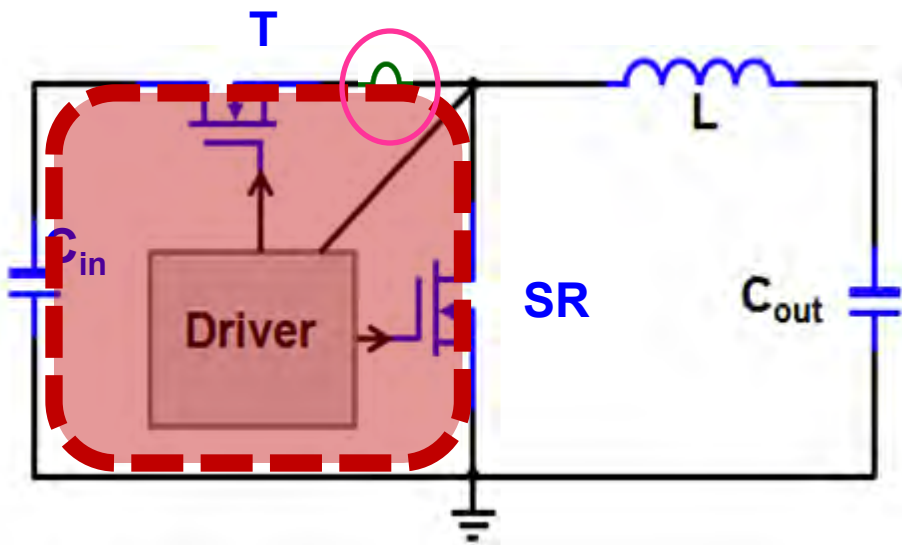


$$P_{T_{VR}} \approx \frac{V_{IN} * I_{OFF} * Q_{GD}}{2 * I_G}$$

$$P_{T_{CFB}} \approx \frac{V_{IN} * I_{OFF} * Q_{GS2}}{2 * I_G}$$

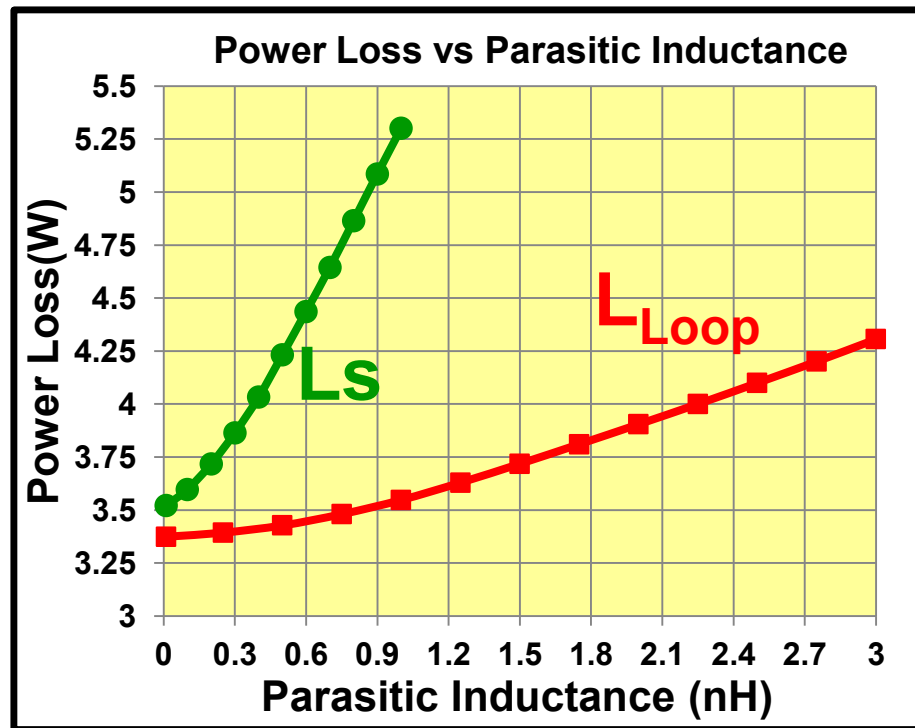


$V_{DS}=20\text{ V}, I_{DS}=20\text{ A}$

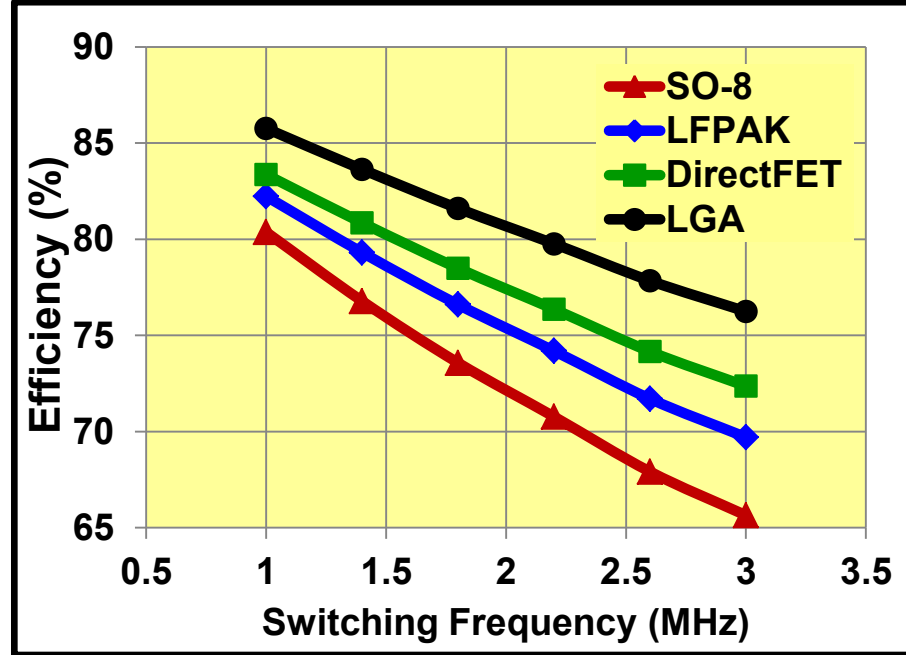
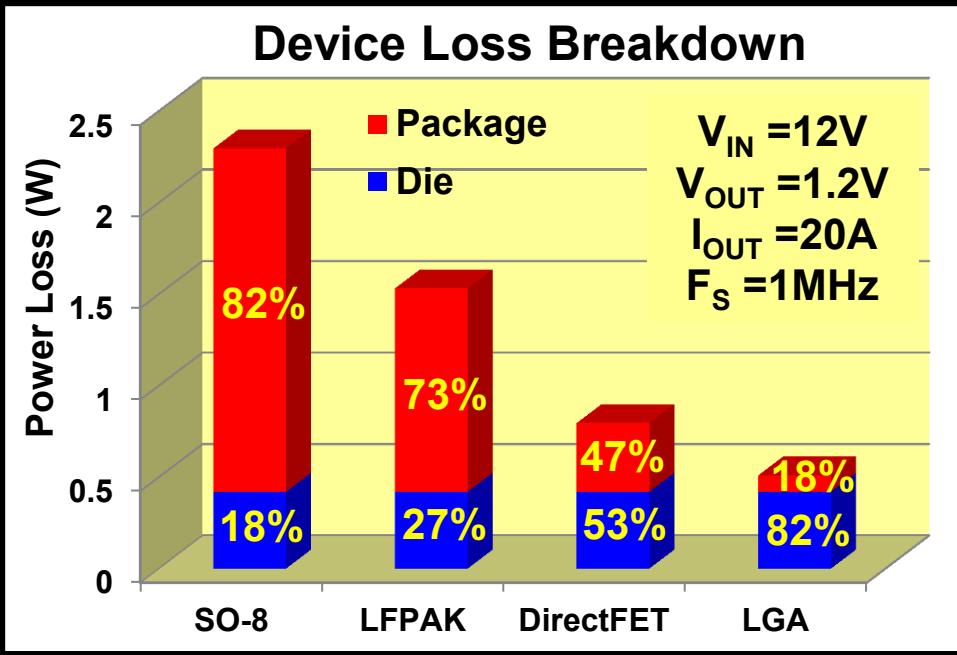
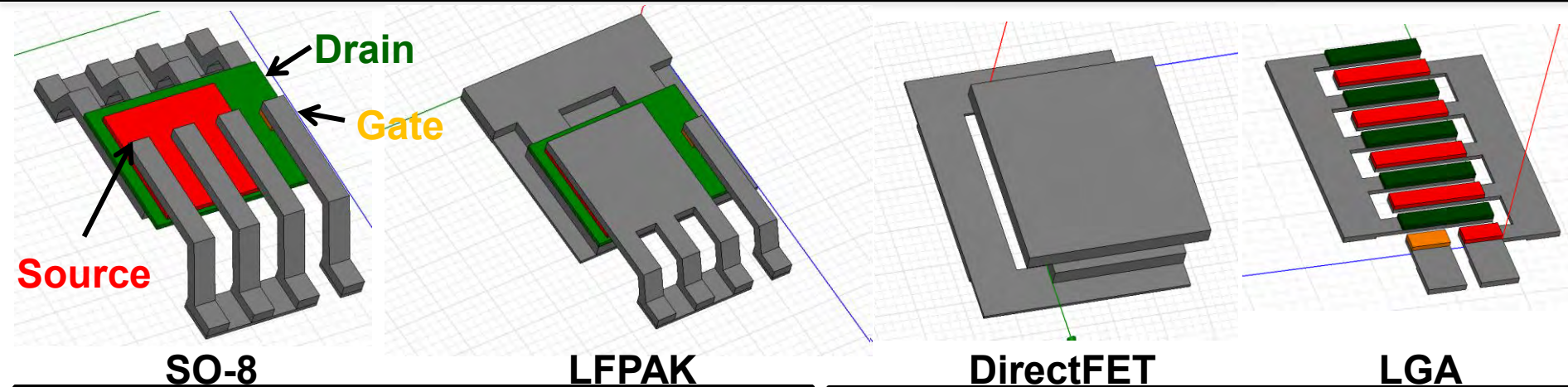


L_S : Common Source Inductance

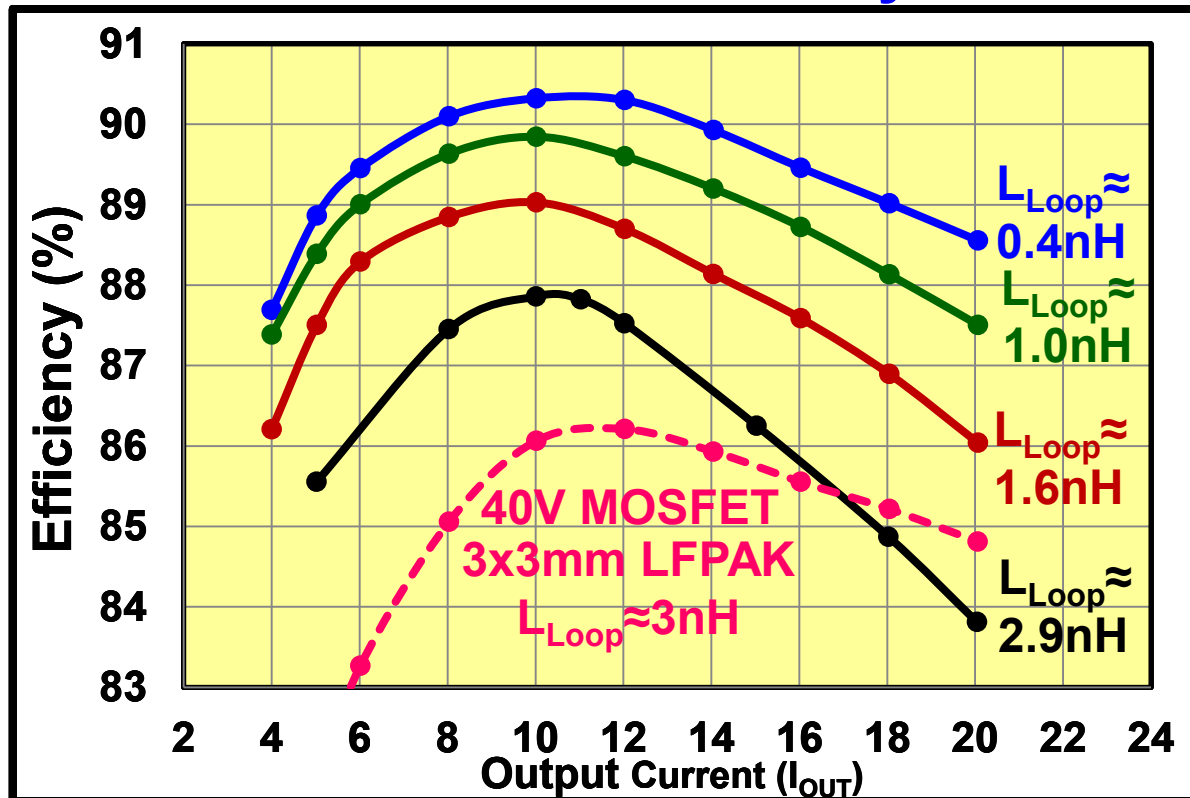
L_{Loop} : High Frequency Power Loop Inductance



$V_{IN}=12\text{ V}$, $V_{OUT}=1.2\text{ V}$,
 $F_S=1\text{ MHz}$, $I_{OUT}=20\text{ A}$



Measured Efficiency



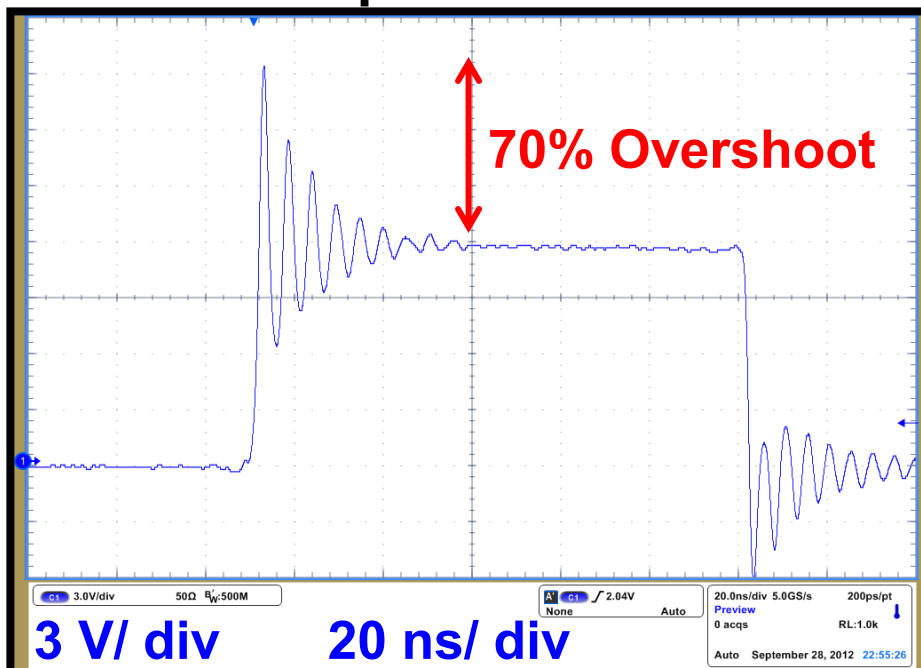
$V_{IN}=12\text{ V}$, $V_{OUT}=1.2\text{ V}$, $F_S=1\text{ MHz}$, $L=150\text{ nH}$

Experimental Prototype

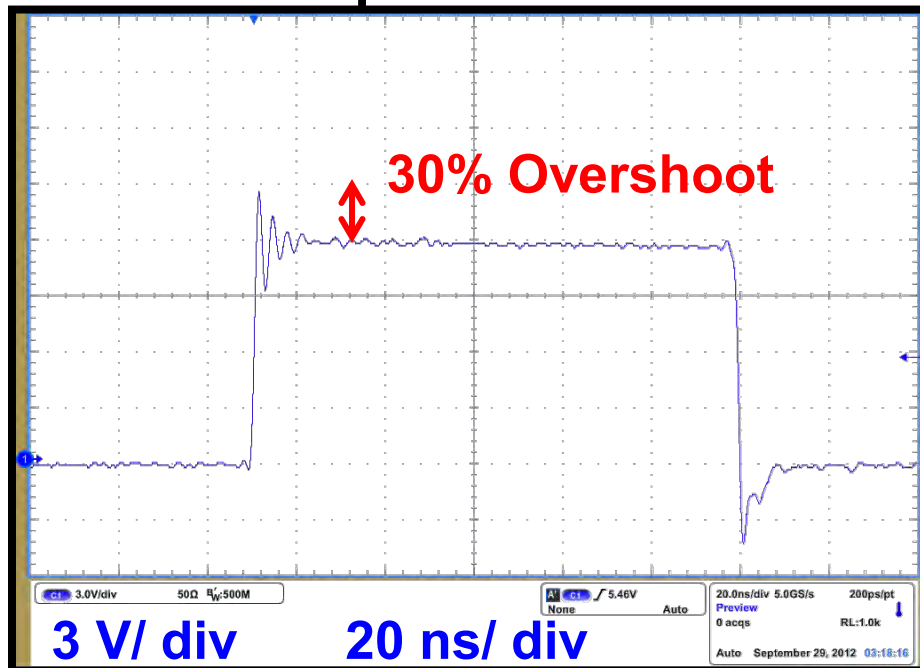
$L_{LOOP} \approx 0.4\text{ nH}$



$L_{Loop} \approx 1.0 \text{ nH}$



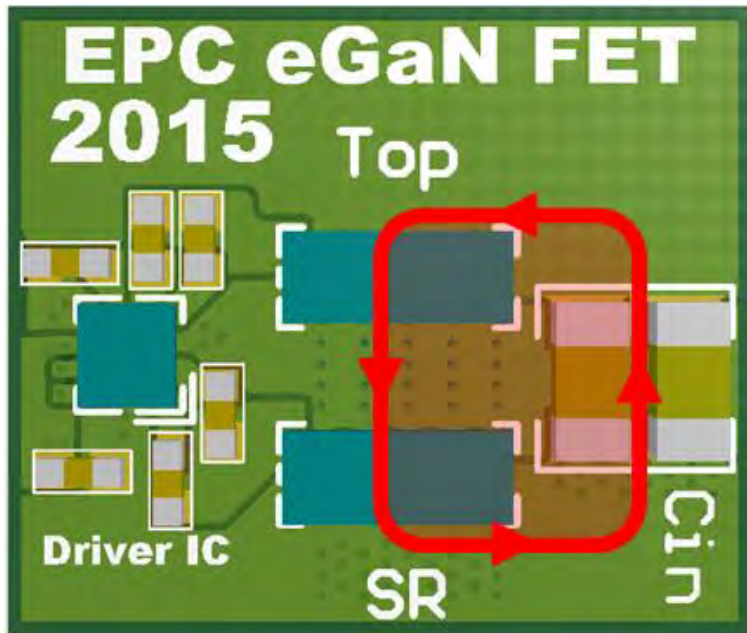
$L_{Loop} \approx 0.4 \text{ nH}$



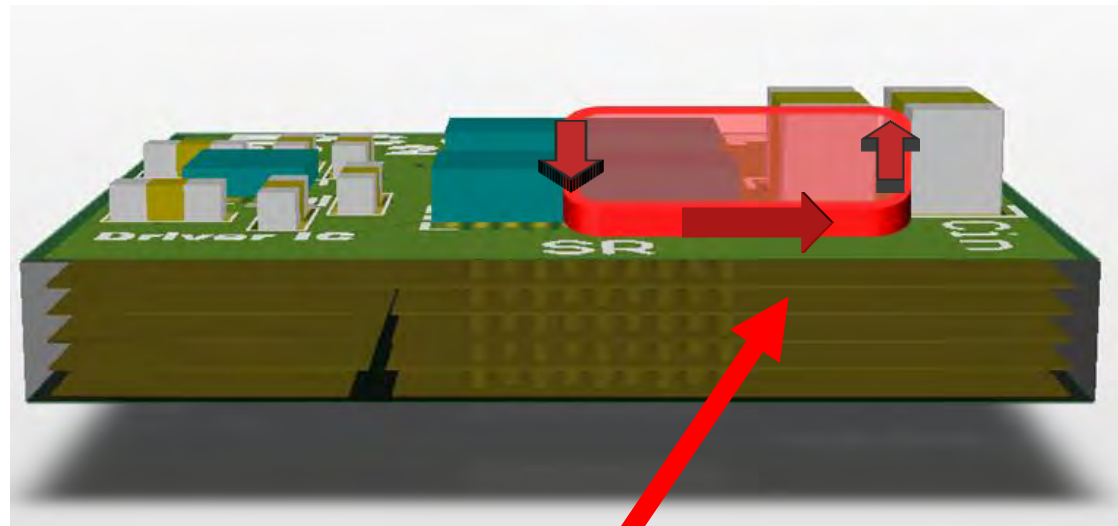
Switching Node Voltage

$V_{IN}=12 \text{ V } V_{OUT}=1.2 \text{ V } I_{OUT}=20 \text{ A } F_S=1 \text{ MHz } L=150 \text{ nH}$

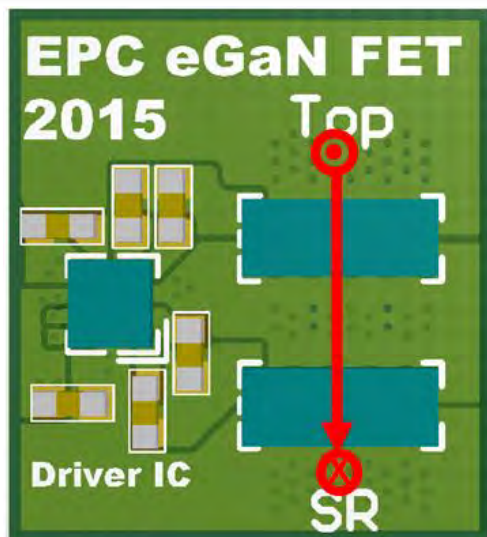
Top View



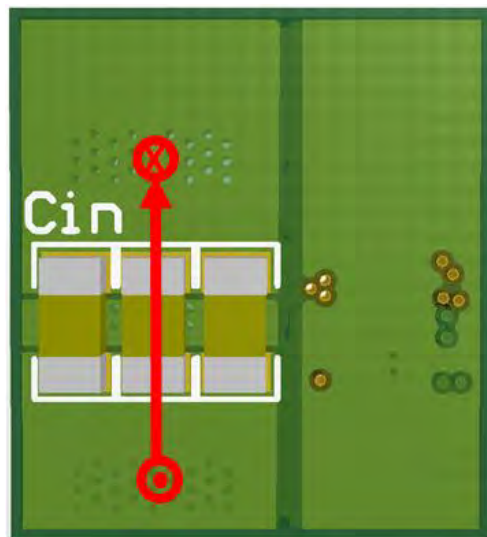
Side View



Shield Layer

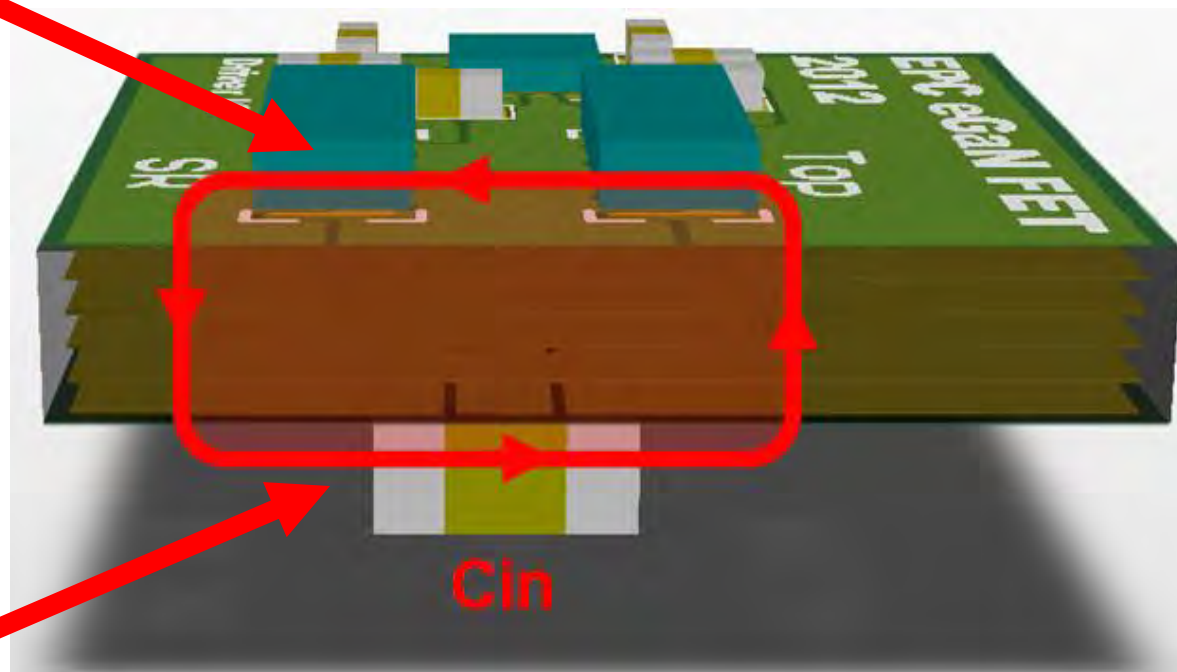


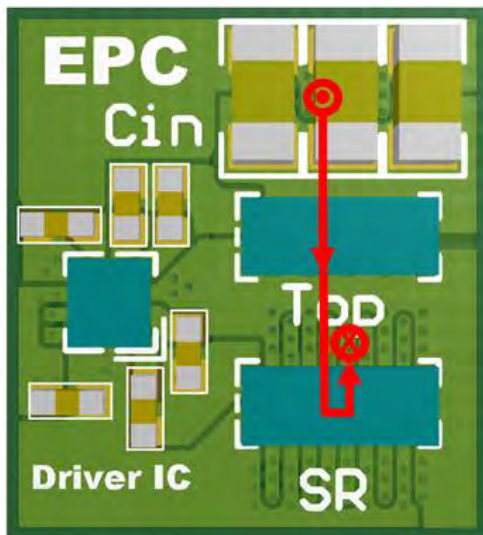
Top View



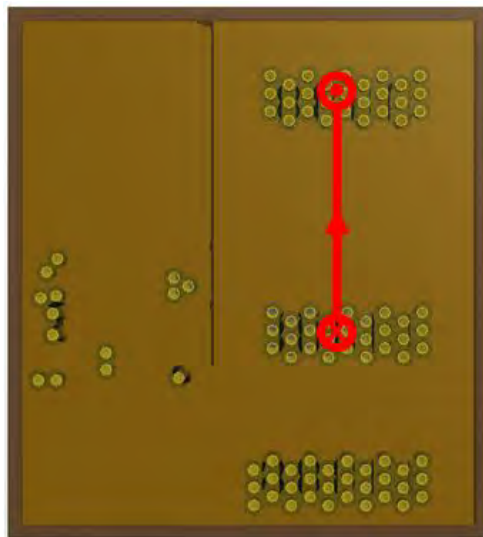
Bottom View

Side View



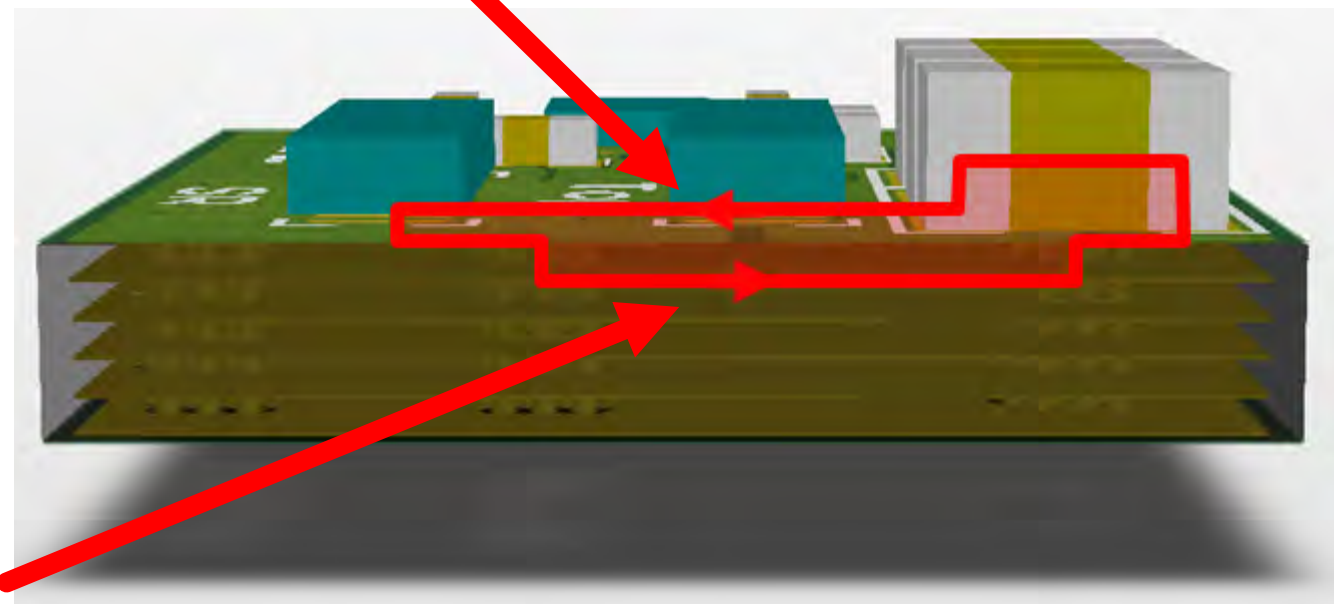


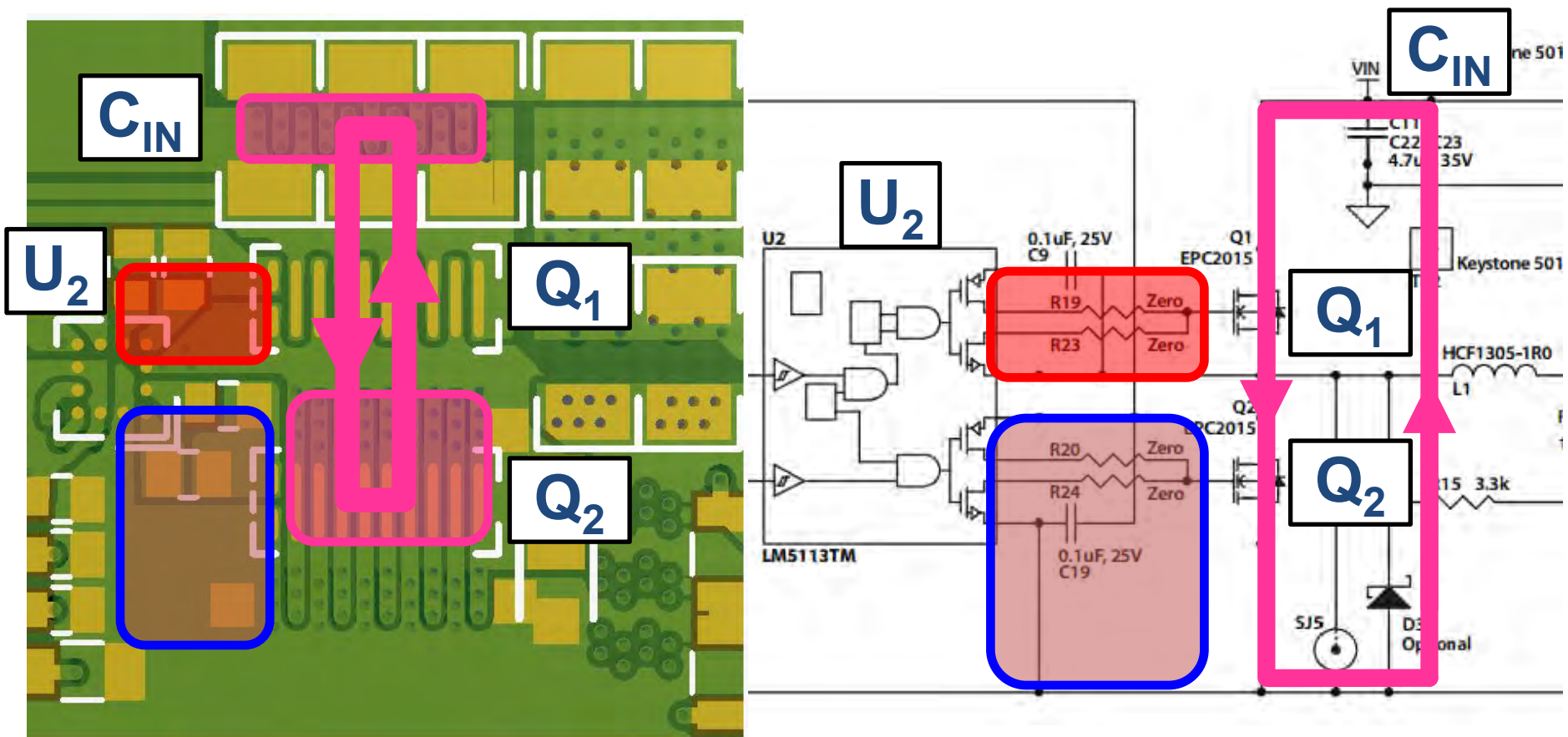
Top View



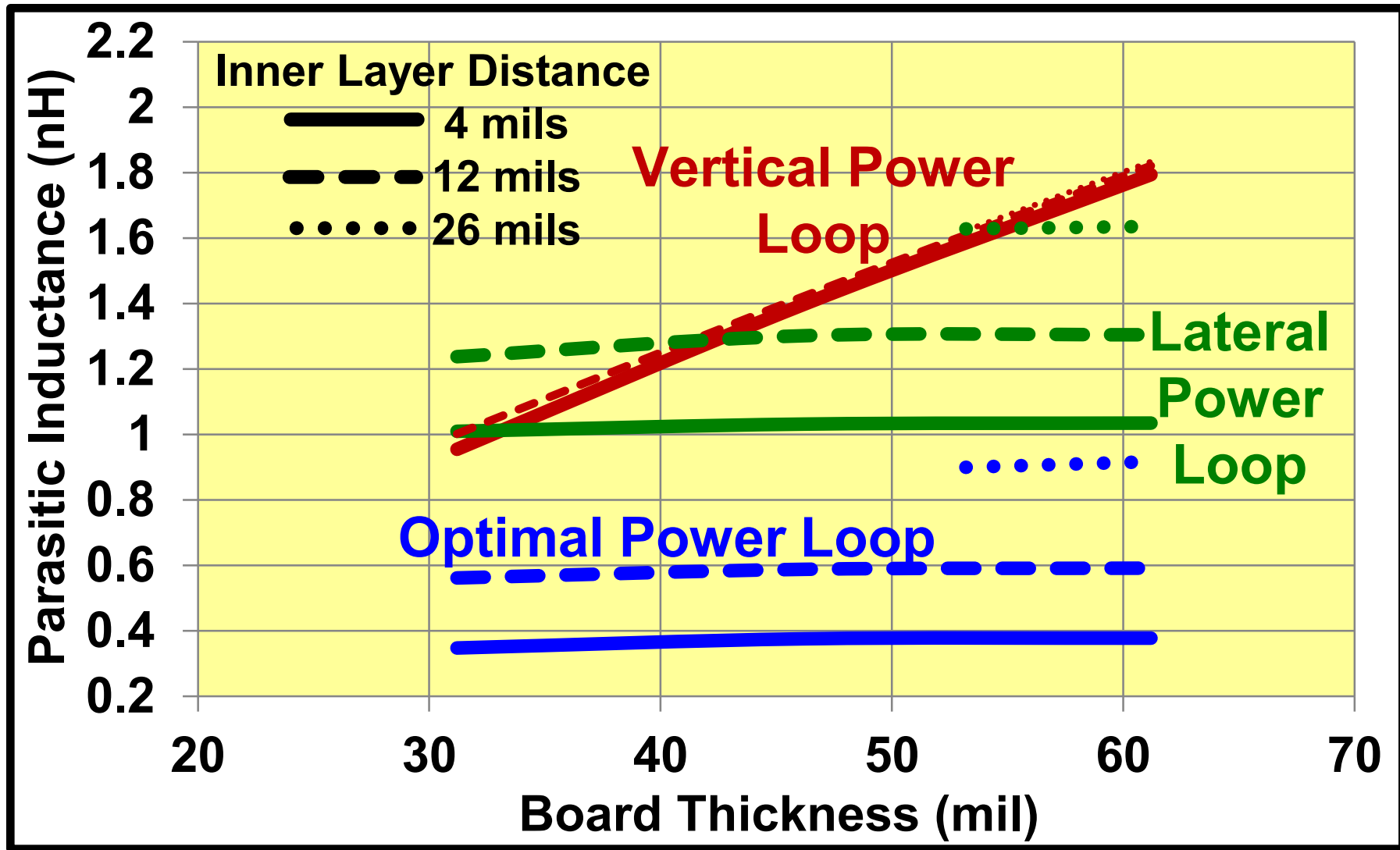
Top View Inner Layer 1

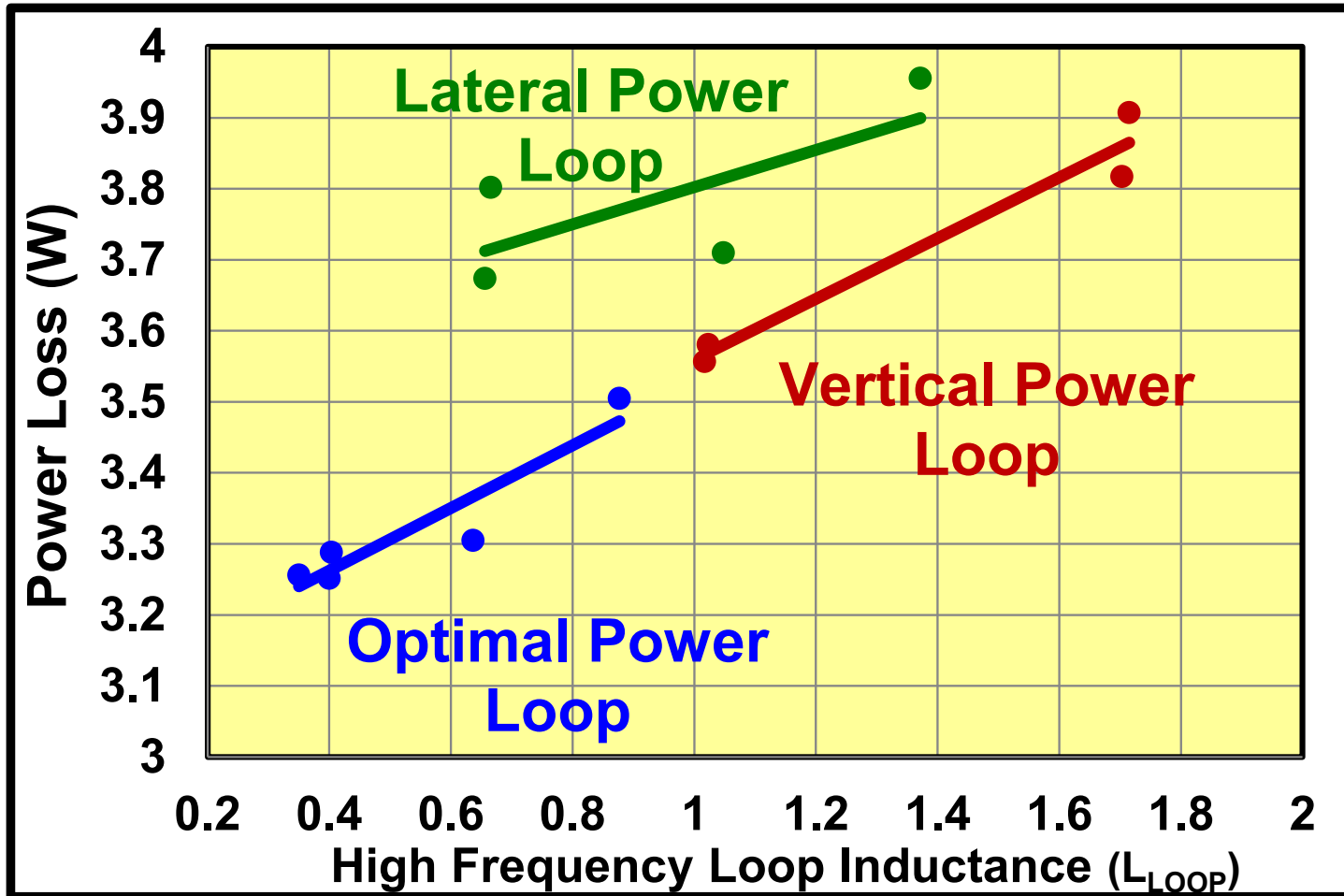
Side View



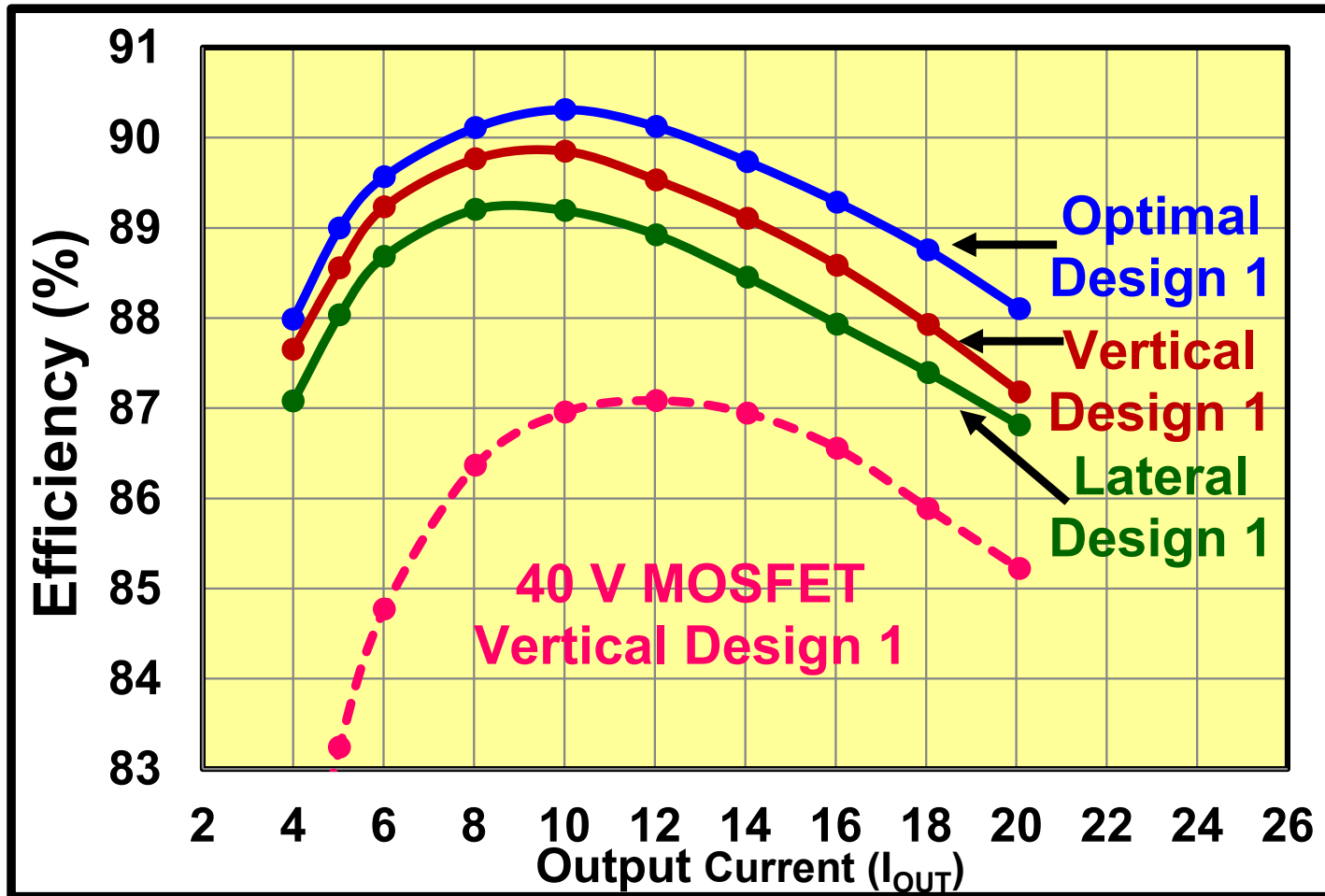


	Lateral Loop	Vertical Loop	Optimal Loop
Single Sided PCB Capability	Yes	No	Yes
Field Self Cancellation	No	Yes	Yes
Inductance Independent of Board Thickness	Yes	No	Yes
Shield Layer Required	Yes	No	No

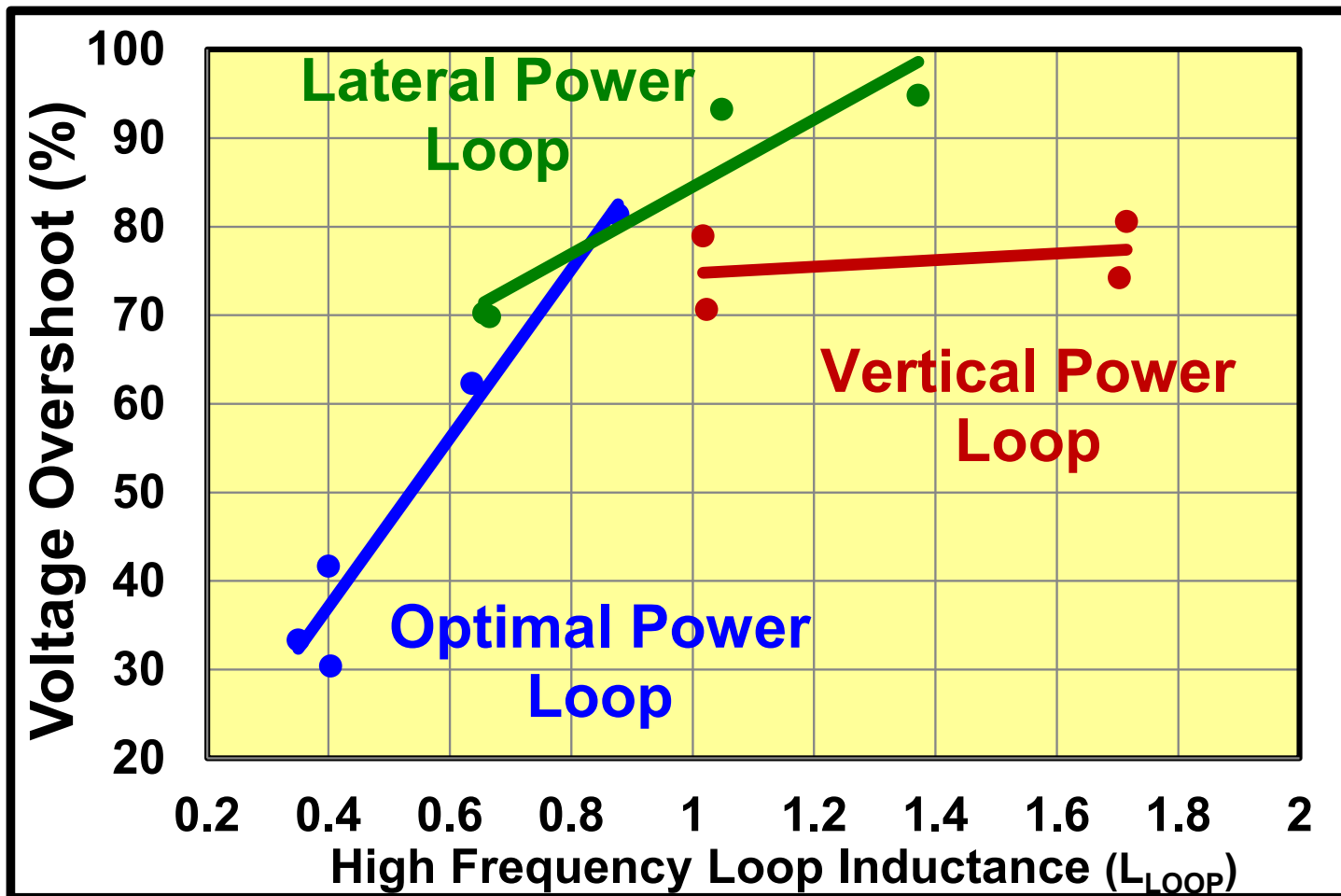




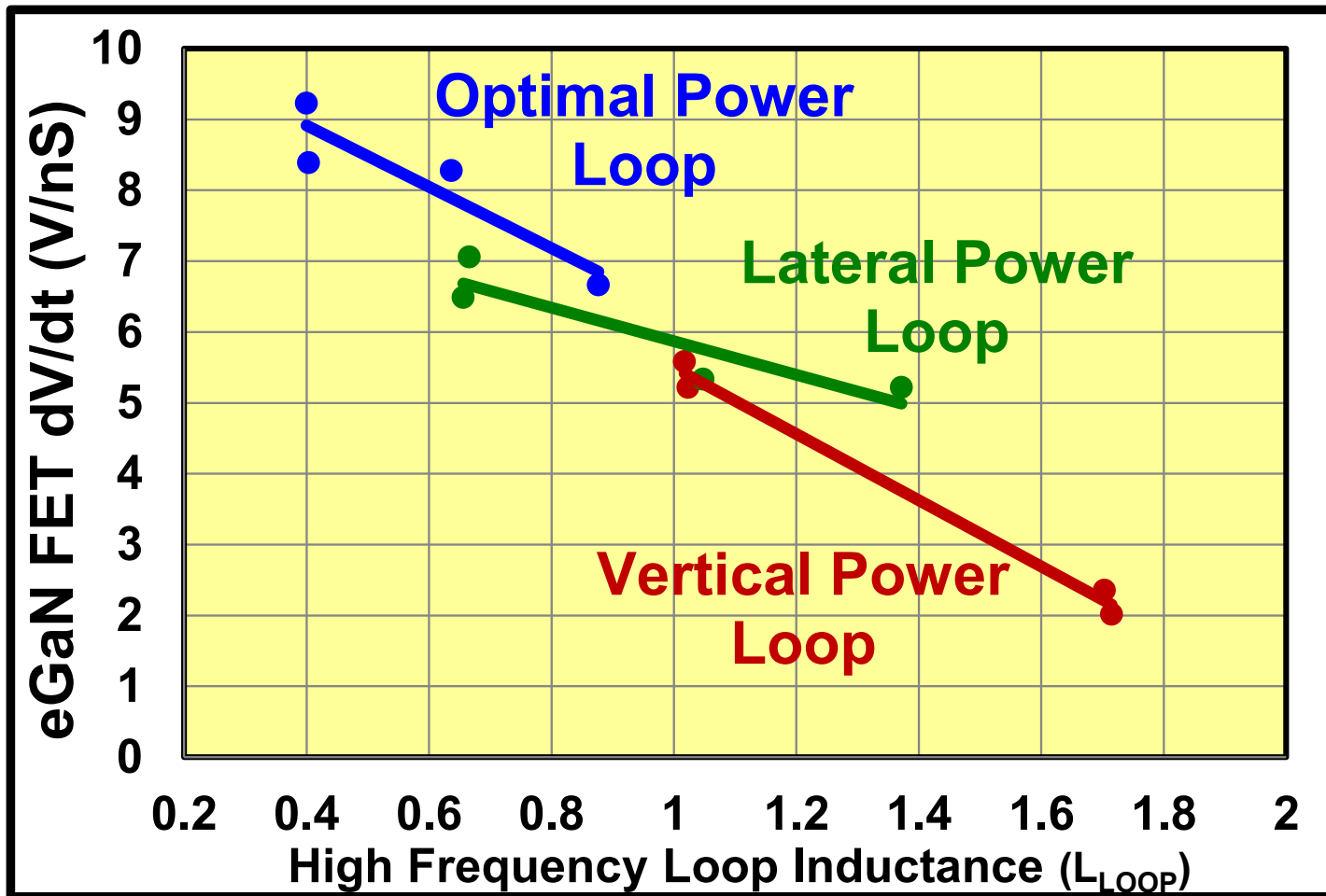
$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $I_{OUT}=20\text{ A}$ $F_S=1\text{ MHz}$ $L=300\text{ nH}$
 T/SR: EPC2015 Driver LM5113



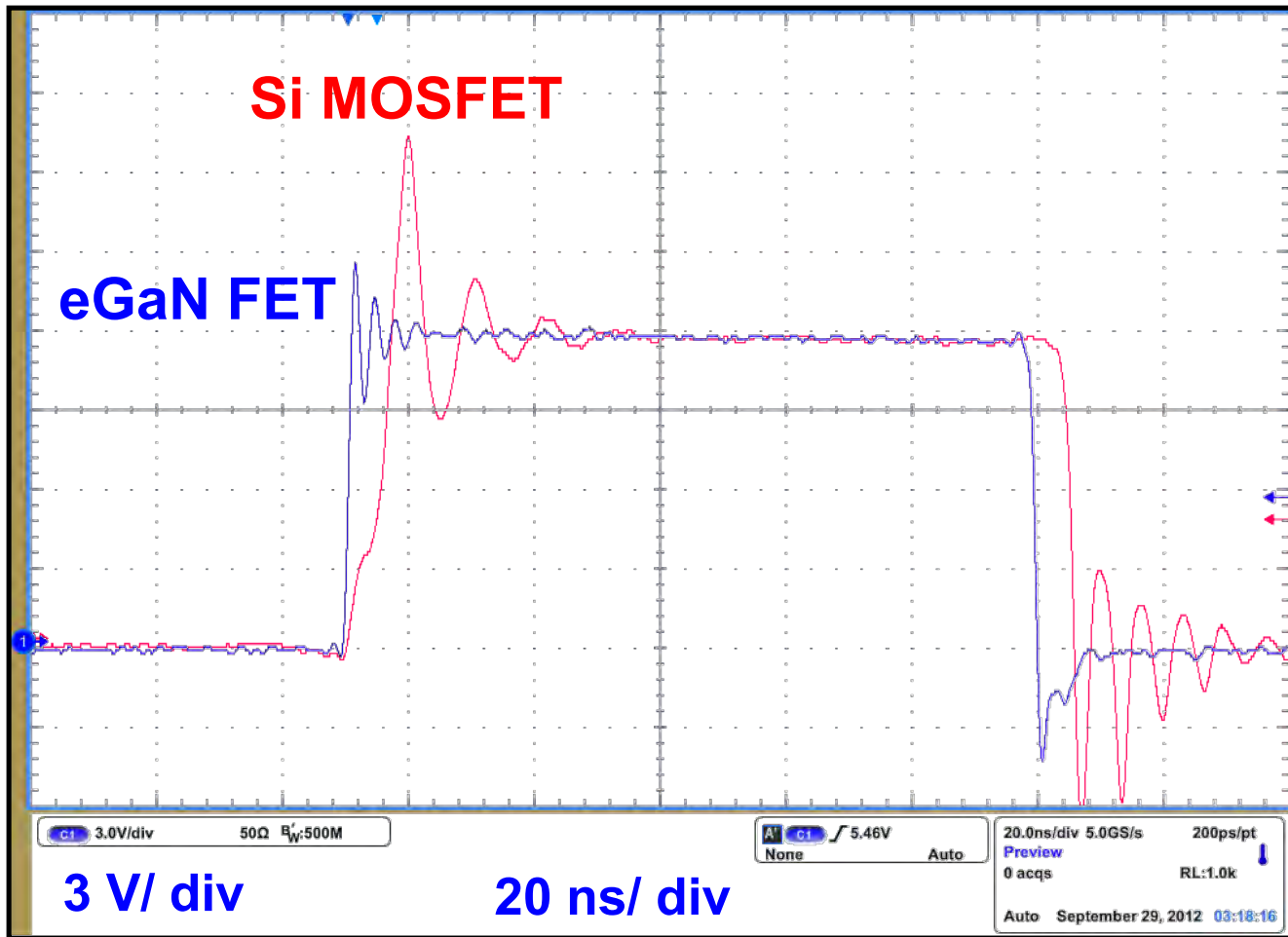
$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $F_s=1\text{ MHz}$ $L=300\text{ nH}$
 GaN T/SR: EPC2015 Driver LM5113



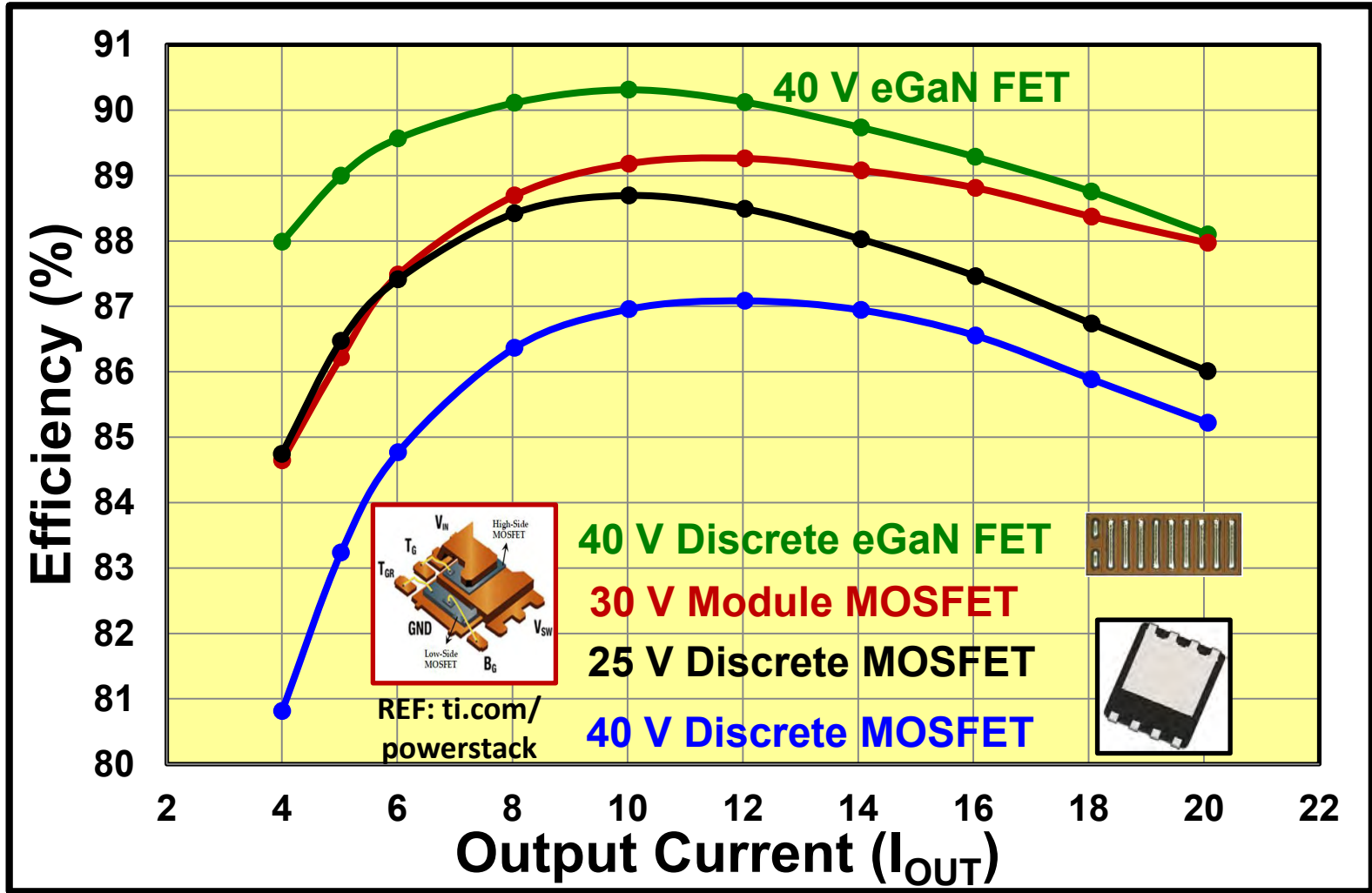
$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $I_{OUT}=20\text{ A}$ $F_S=1\text{ MHz}$ $L=300\text{ nH}$
 T/SR: EPC2015 Driver LM5113



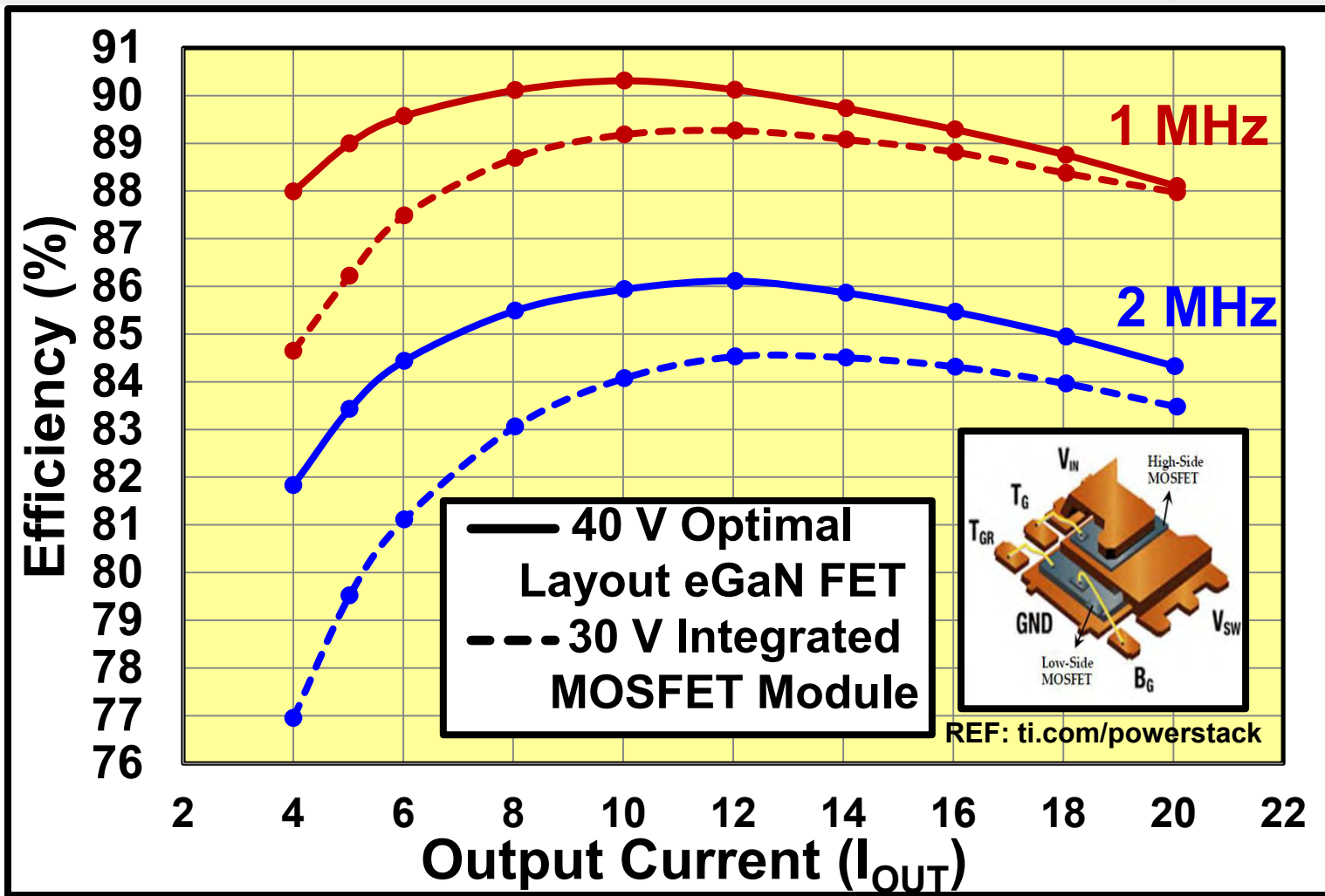
$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $I_{OUT}=20\text{ A}$ $F_S=1\text{ MHz}$ $L=300\text{ nH}$
 T/SR: EPC2015 Driver LM5113



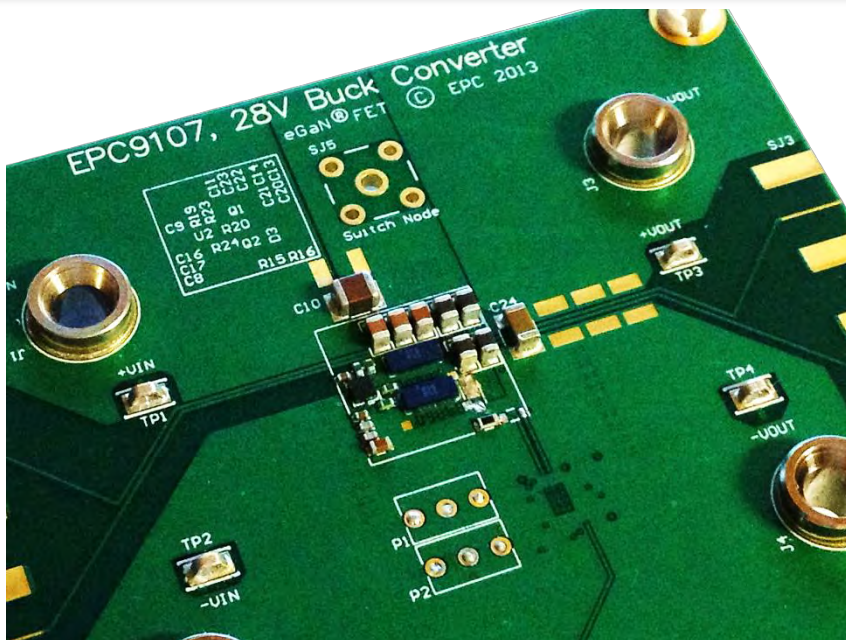
$V_{IN}=12\text{ V}$ $V_{OUT}=1.2\text{ V}$ $I_{OUT}=20\text{ A}$ $F_S=1\text{ MHz}$ $L=300\text{ nH}$ eGaN FET T/SR: EPC2015
MOSFET T:BSZ097N04 SR:BSZ040N04



$V_{IN}=12\text{ V } V_{OUT}=1.2\text{ V } F_S=1\text{ MHz } L=300\text{ nH}$



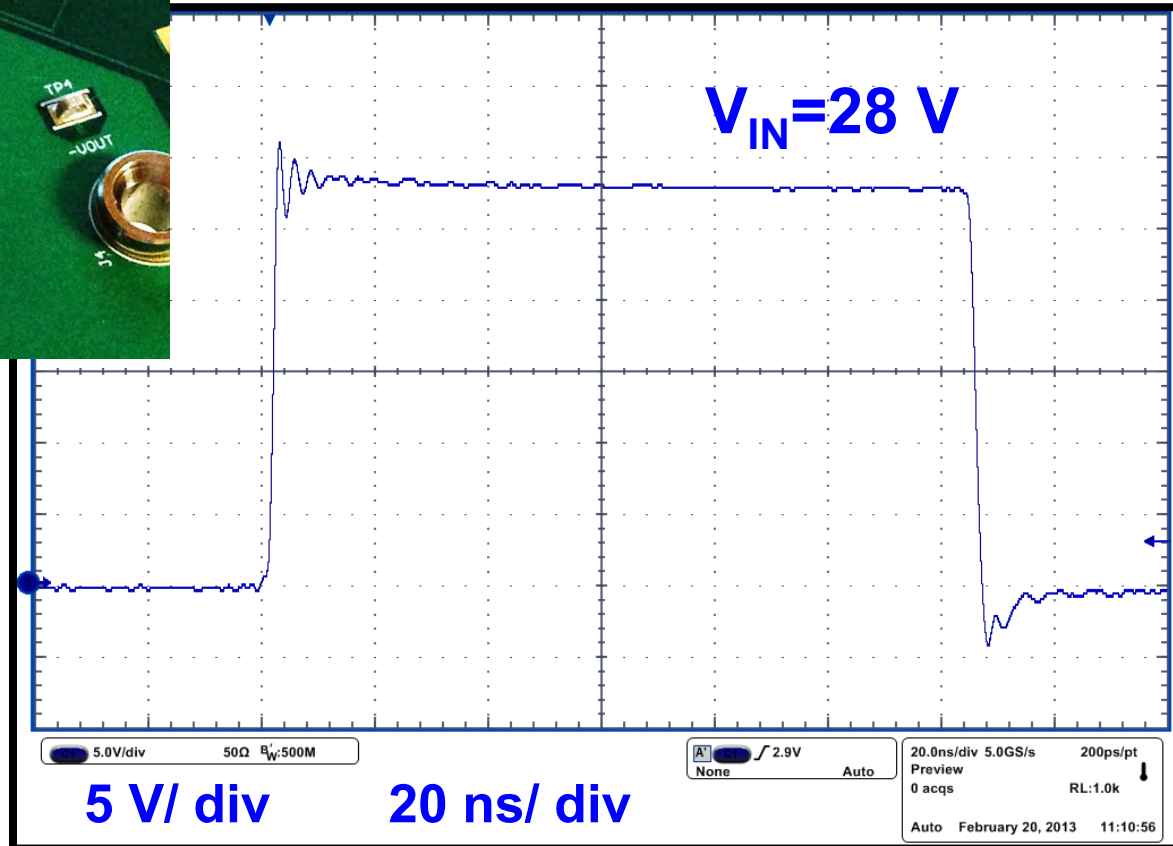
$V_{IN}=12\text{ V } V_{OUT}=1.2\text{ V } L=300\text{ nH}$



$V_{IN}=12-28\text{ V}$ $V_{OUT}=3.3\text{ V}$
 $I_{OUT}=15\text{ A}$ $F_S=1\text{ MHz}$
 2 x EPC2015

Switching Node Voltage

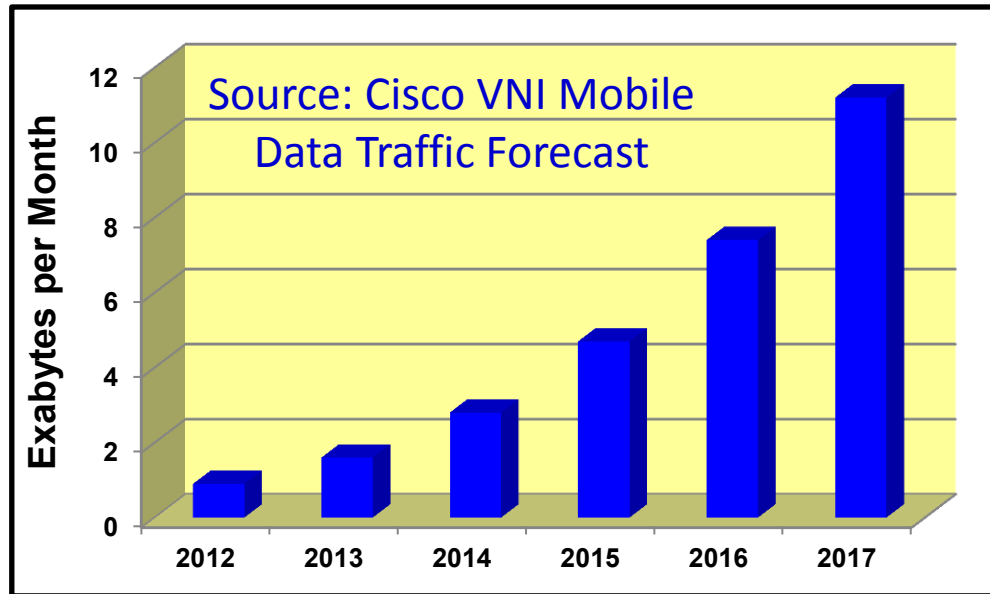
$V_{IN}=28\text{ V}$ $I_{OUT}=15\text{ A}$



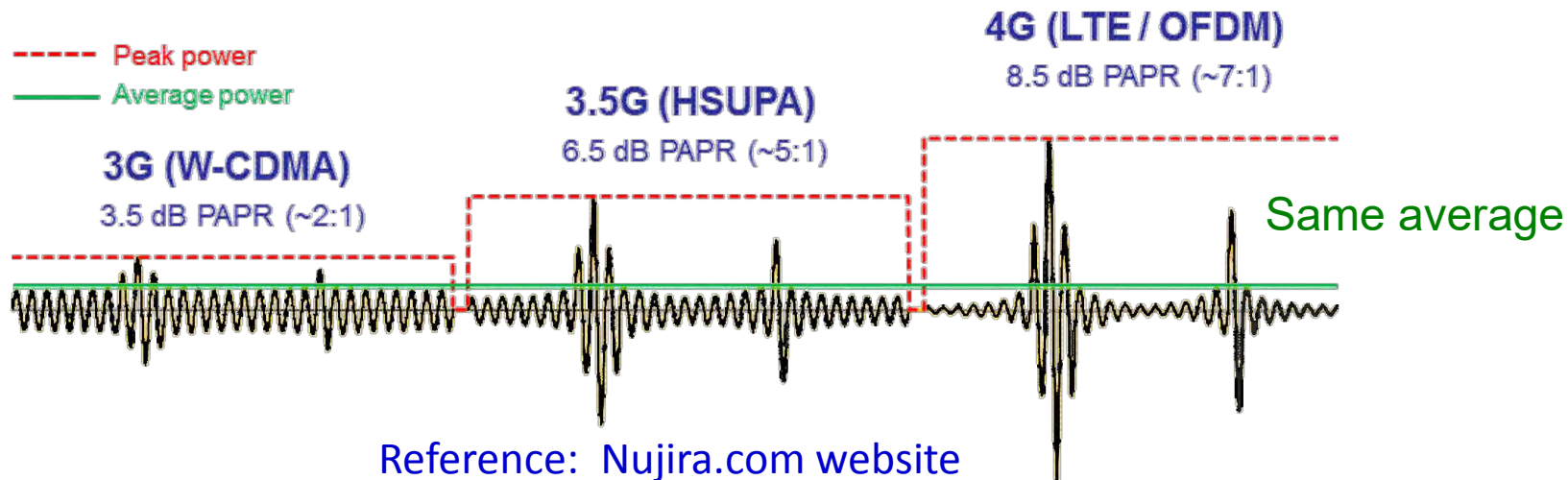
- Envelope Tracking
- 48 V- 12 V Power Conversion
 - Hard Switching Brick
 - Resonant Bus Converter
 - High Current Non-Isolated Buck
- Wireless Power

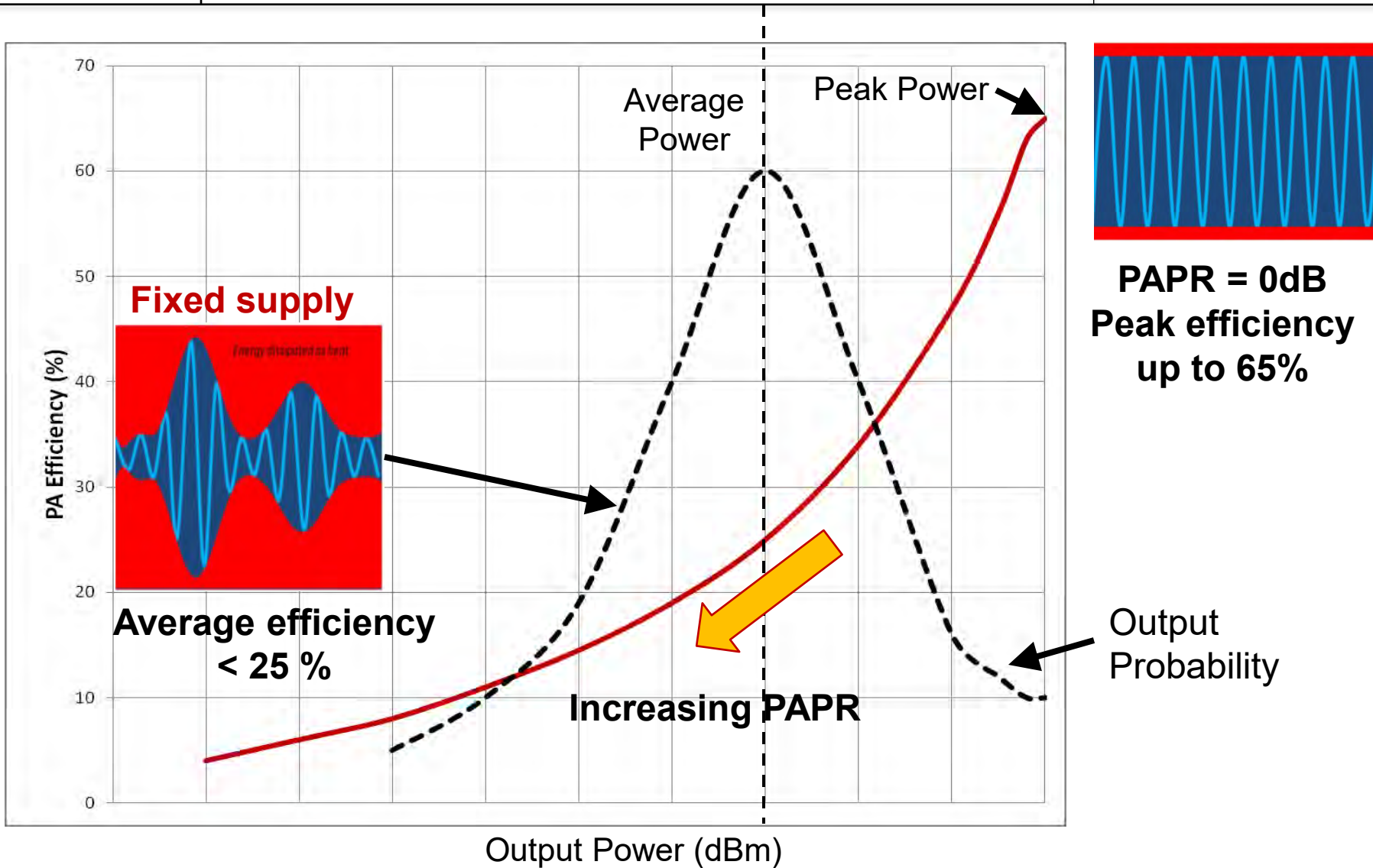
Envelope Tracking (ET)

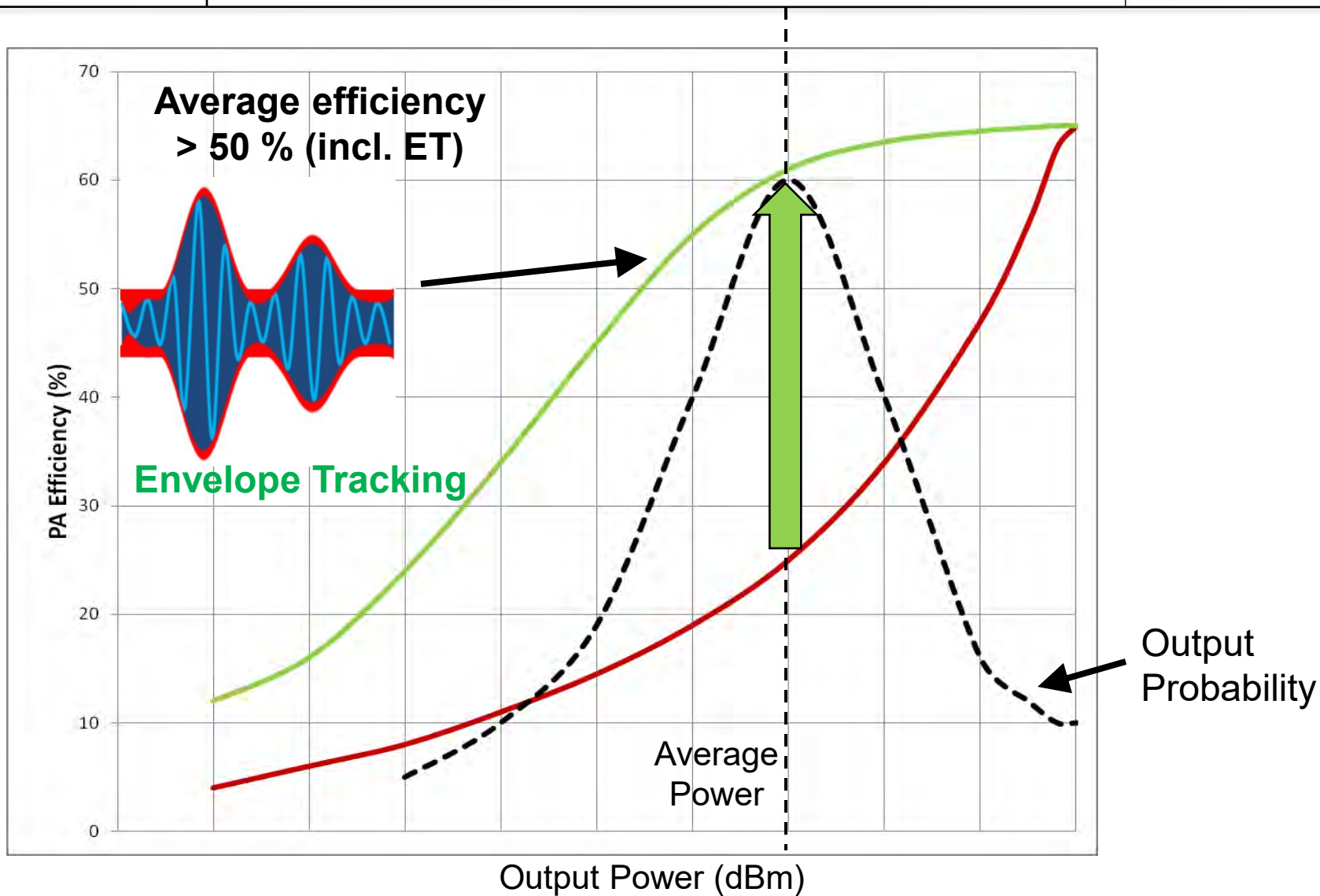
Why Envelope Tracking?

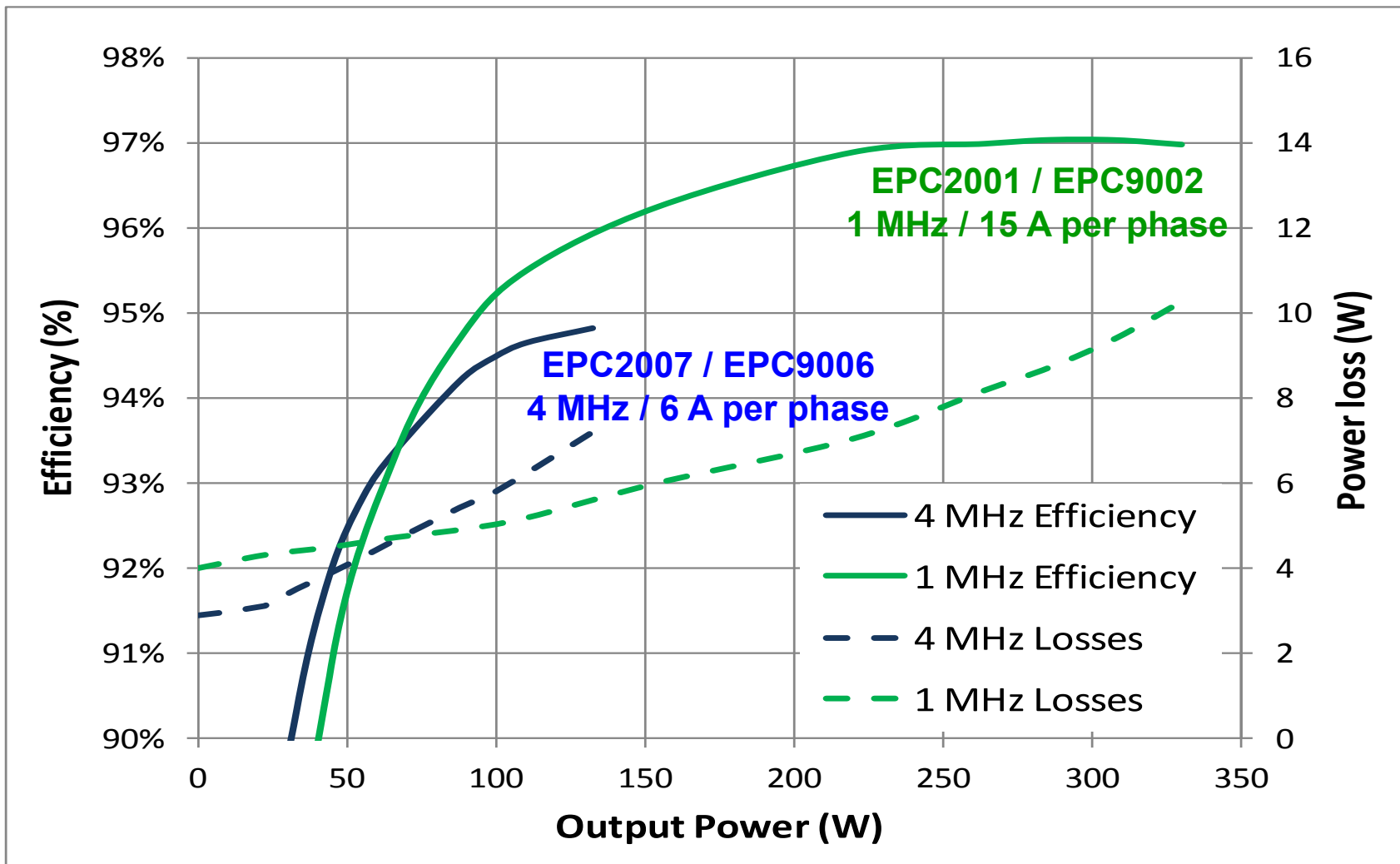


66% Compound annual growth rate (CAGR)

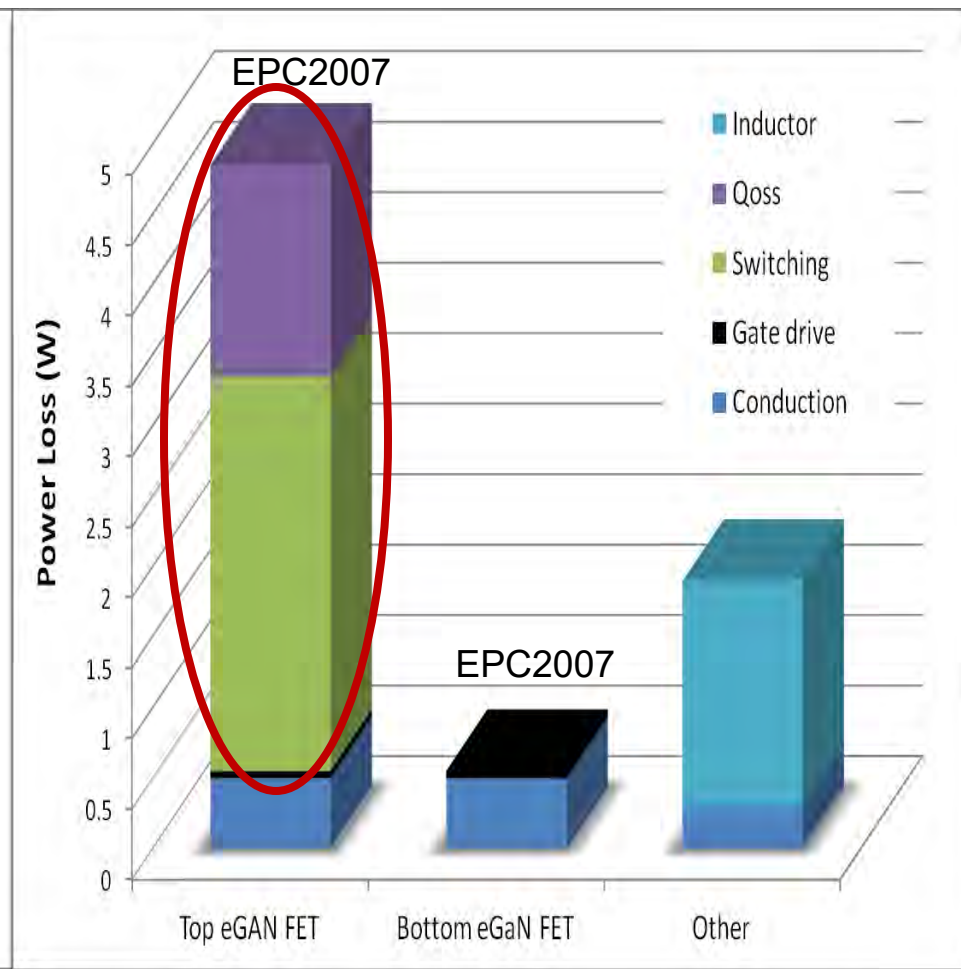
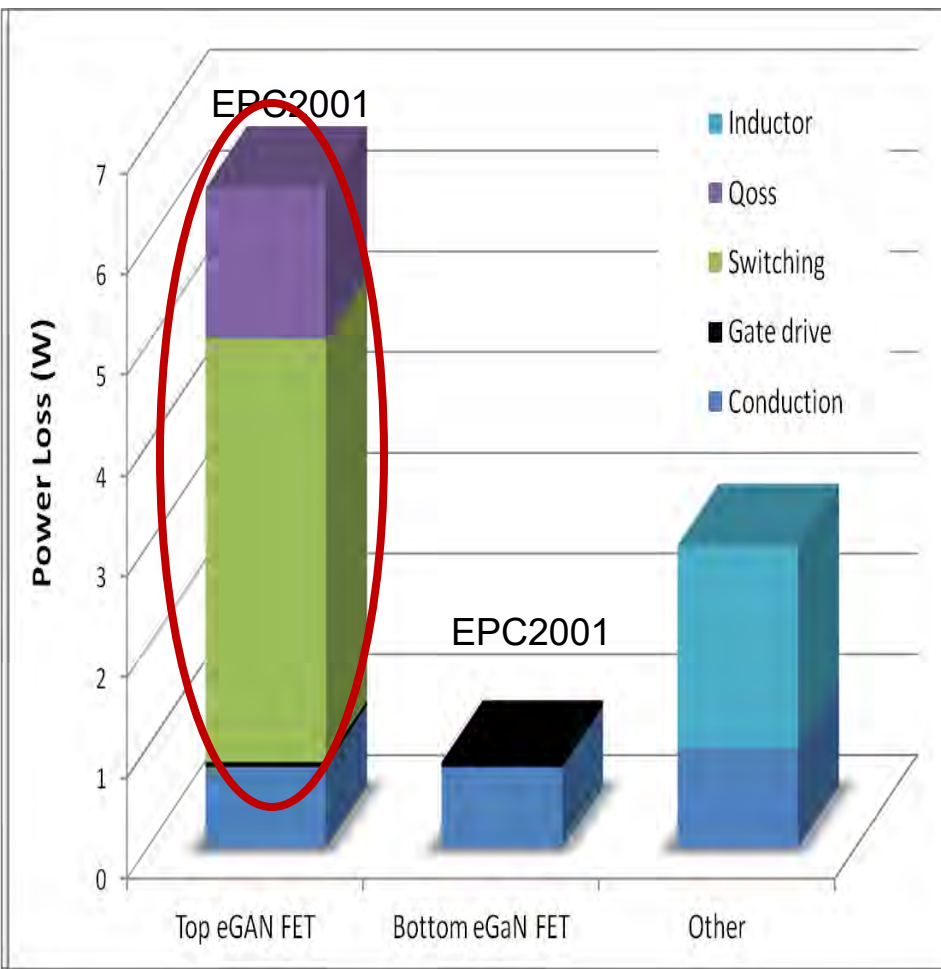






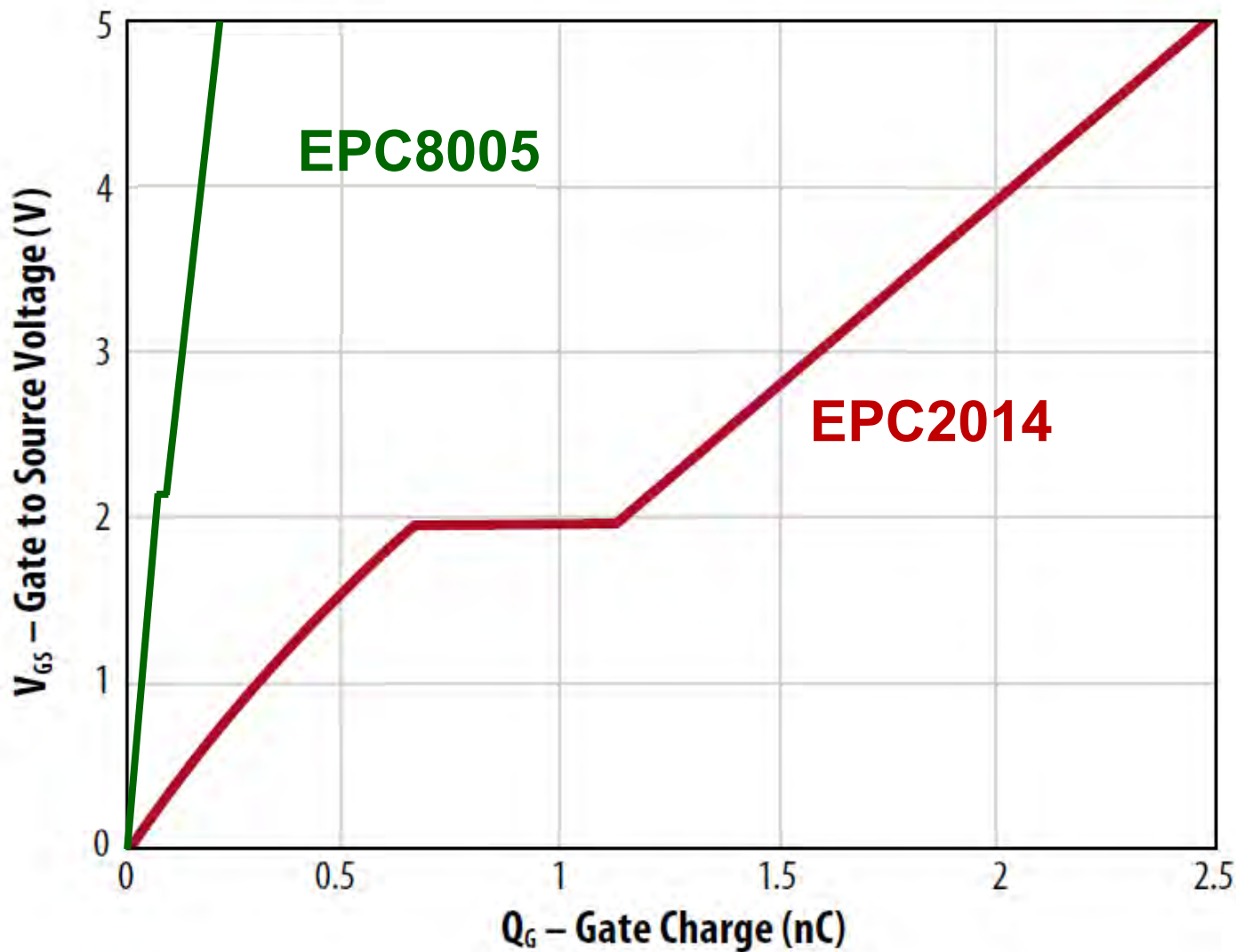


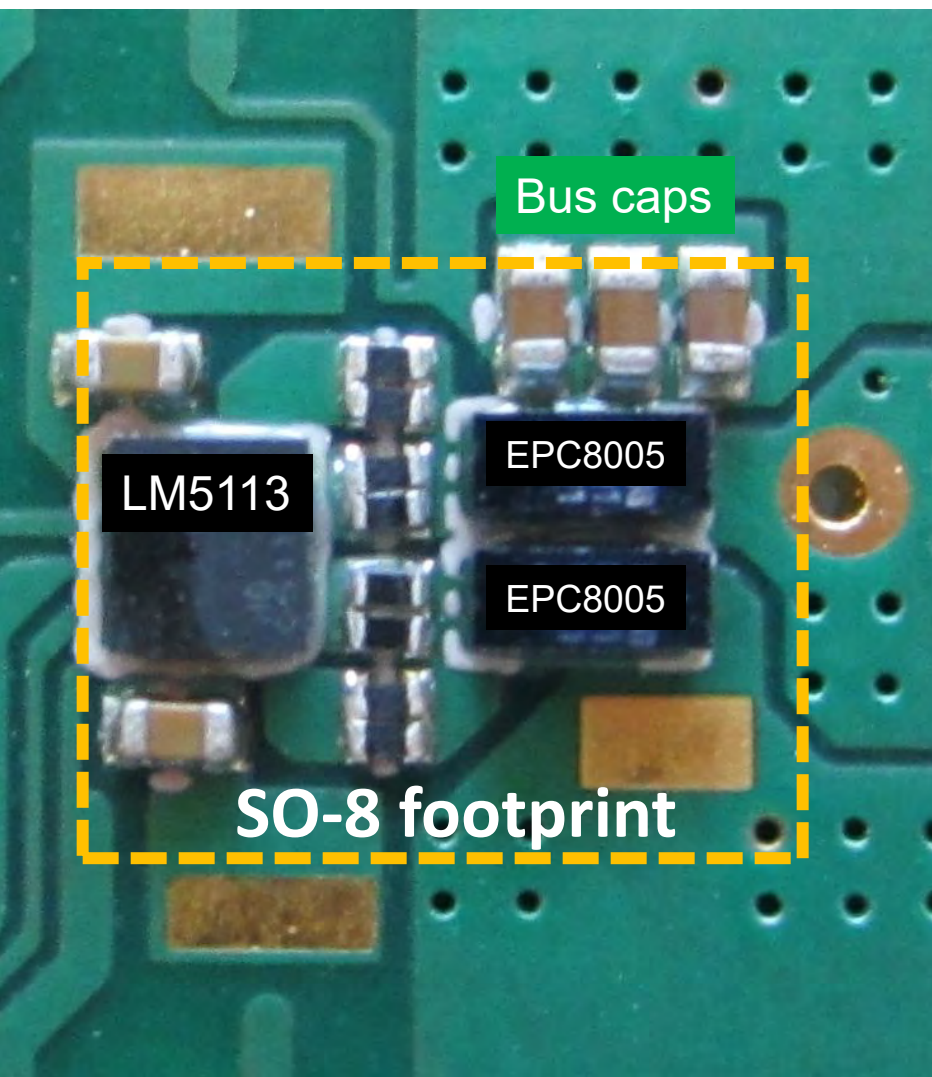
$V_{IN}=45\text{ V}, V_{OUT}=22\text{ V}$



1 MHz EPC9002

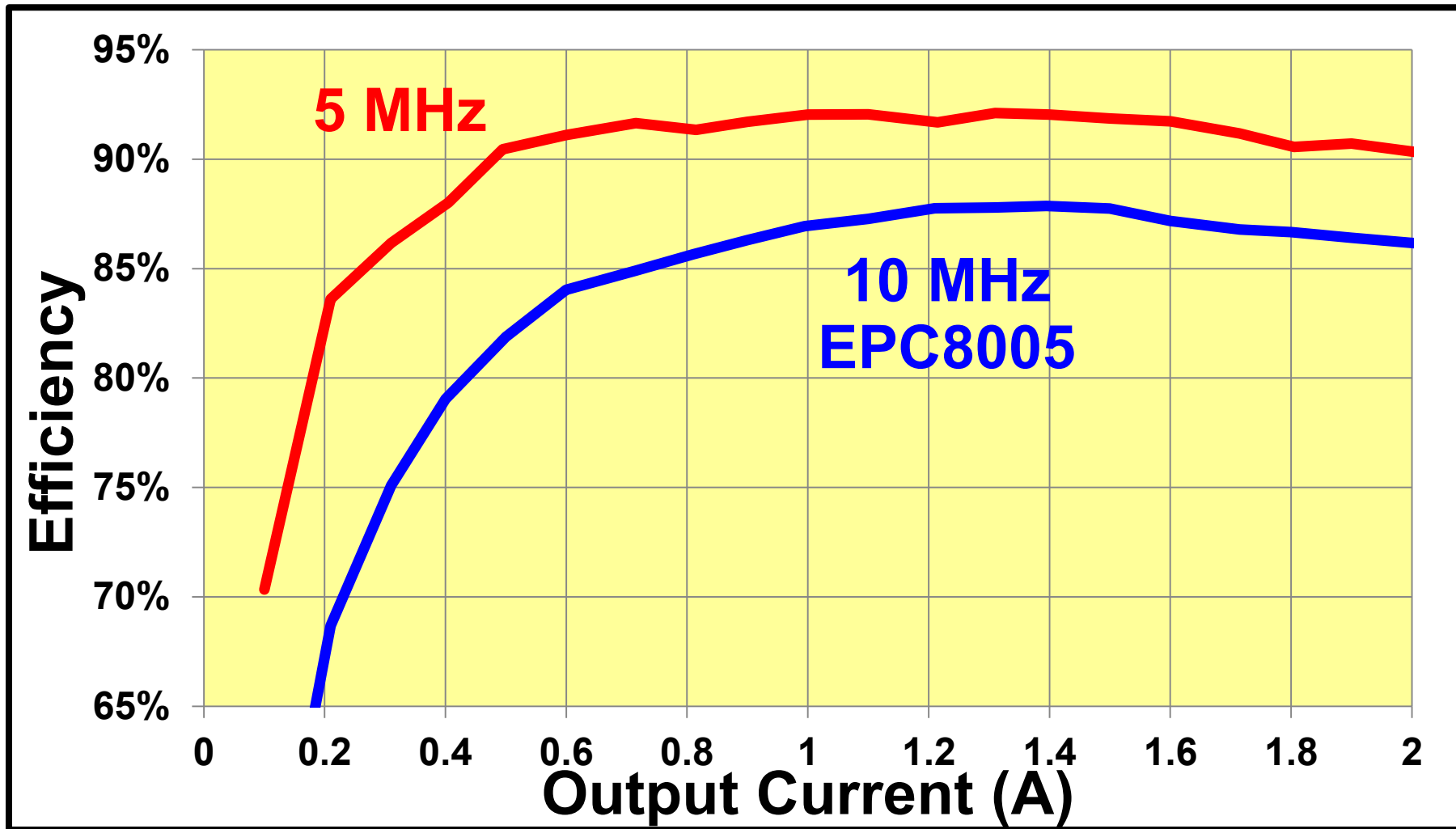
4 MHz EPC9006





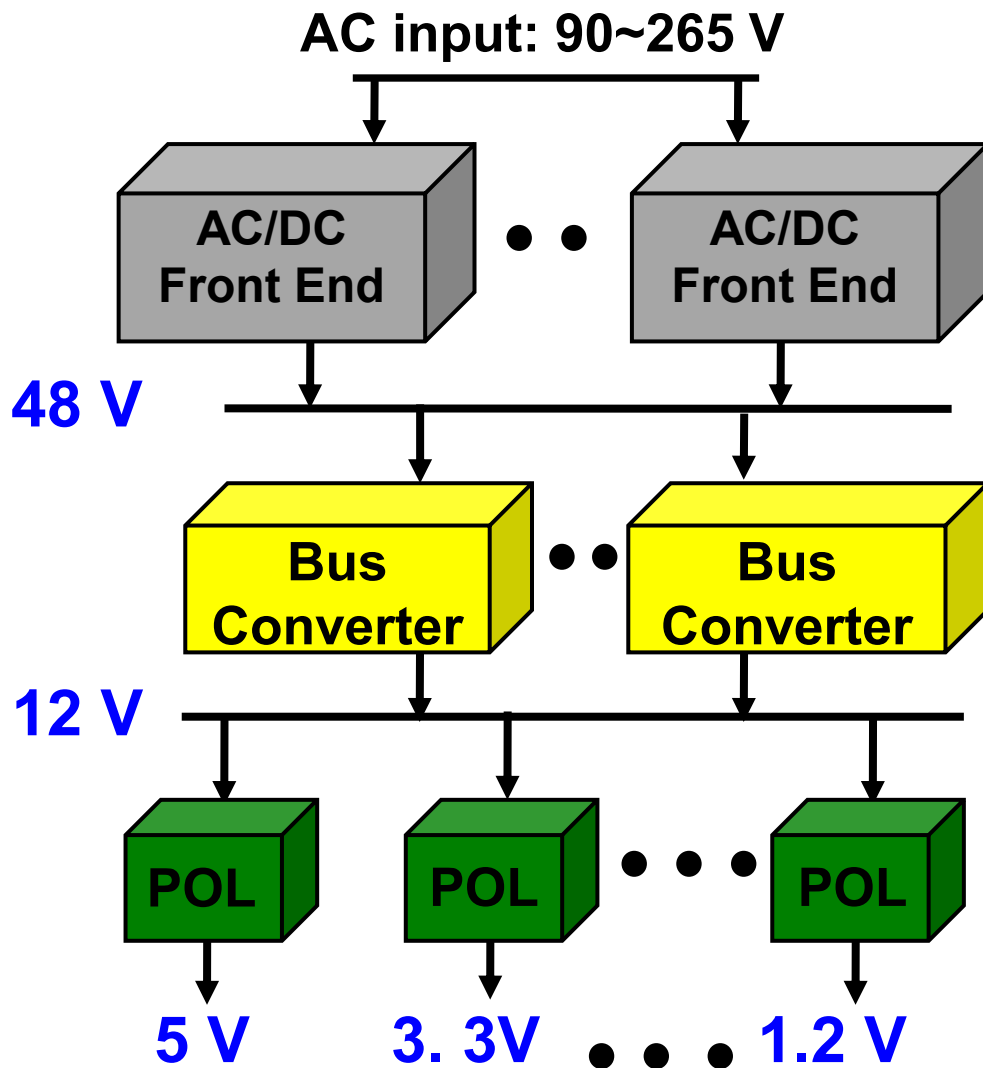
- LM5113 BGA driver
- 2x 0201 resistors in parallel to minimize gate inductance
- Optimum gate and power loops

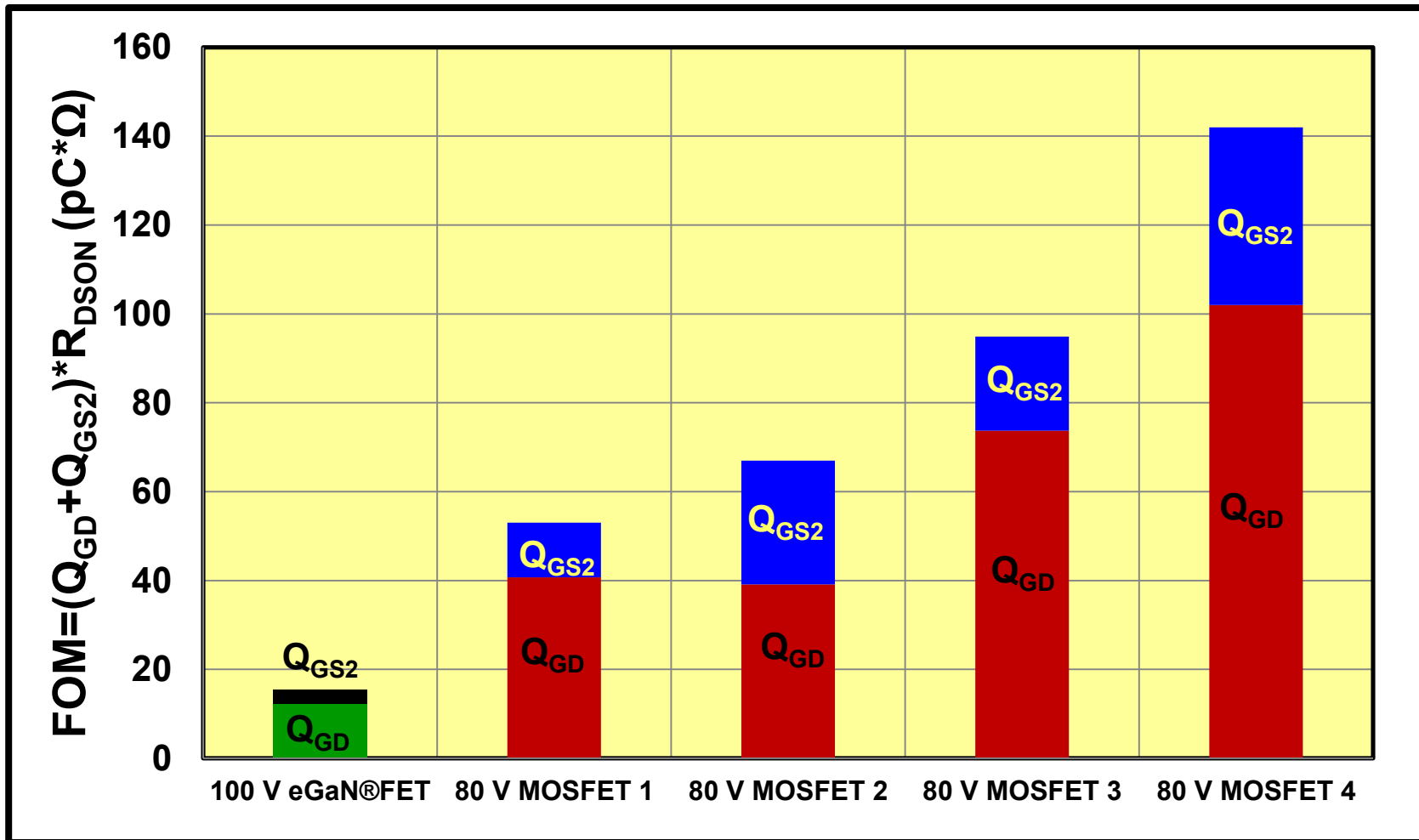
42 V to 20 V / 2 A buck



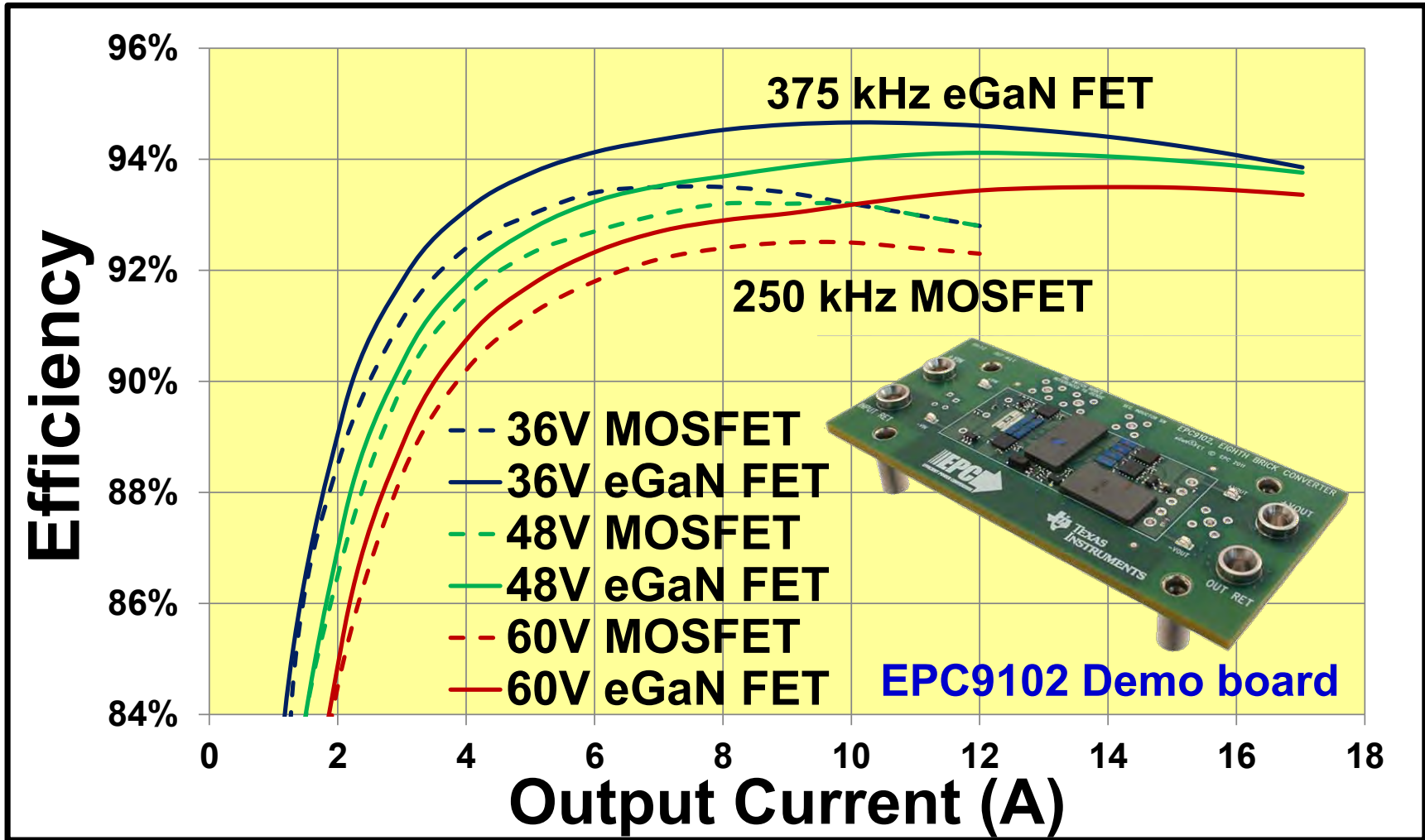
$V_{IN}=42\text{ V}$ $V_{OUT}=20\text{ V}$

48 V to 12 V Power Conversion





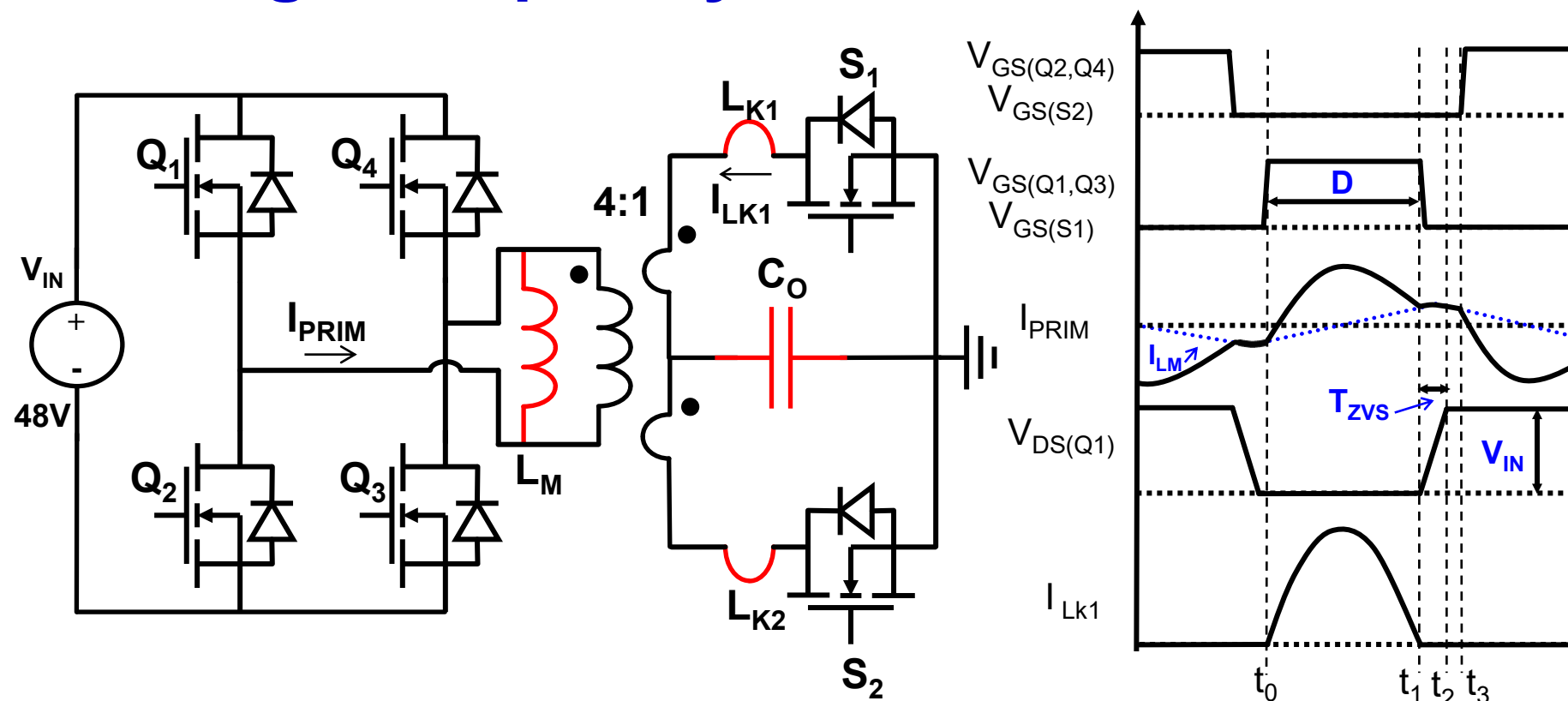
$V_{DS} = 0.5 * V_{DS} , I_{DS} = 15 A$



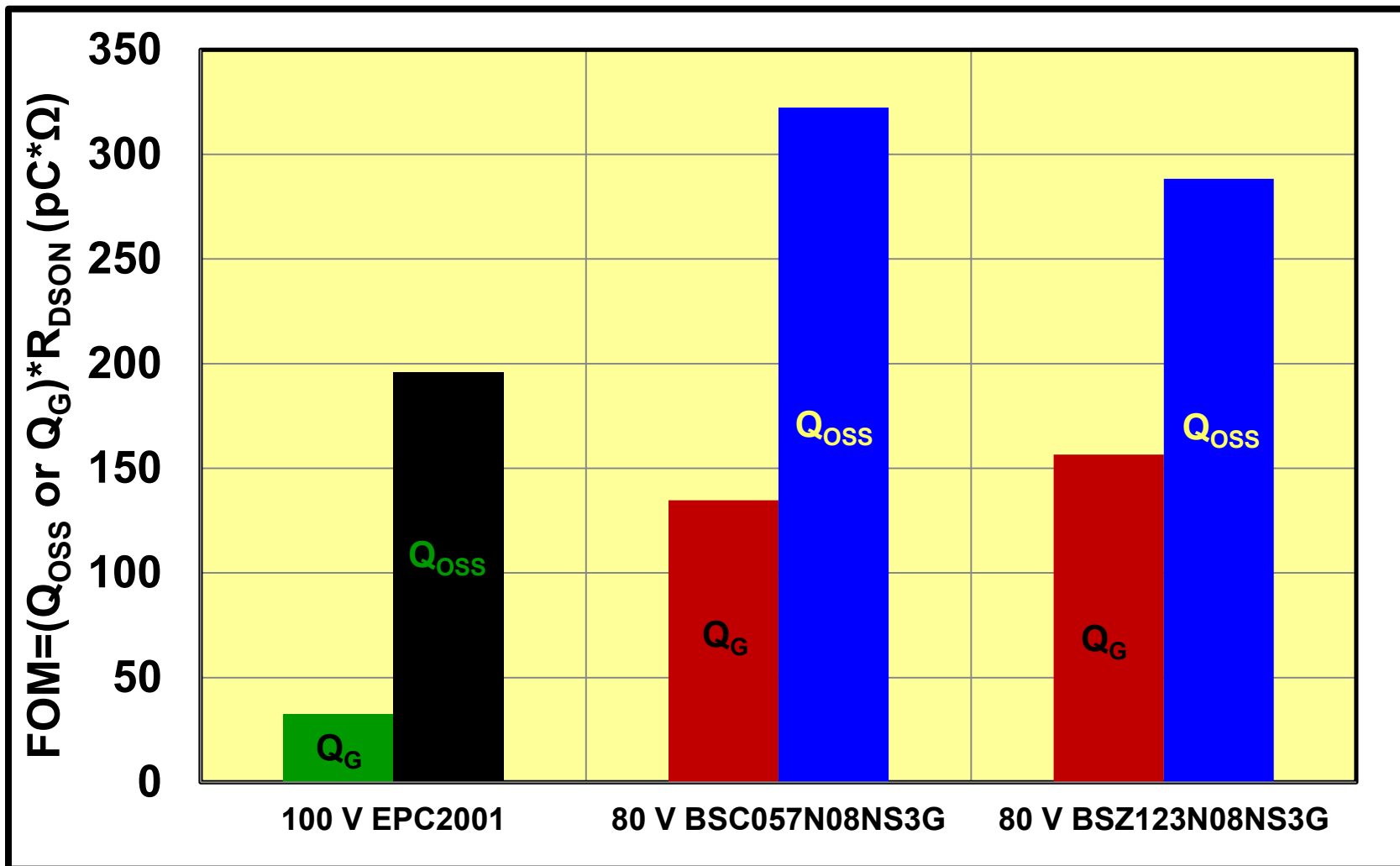
36 - 60 Vin, 12 Vout, 200 W, 375 kHz

Resonant Bus Converter

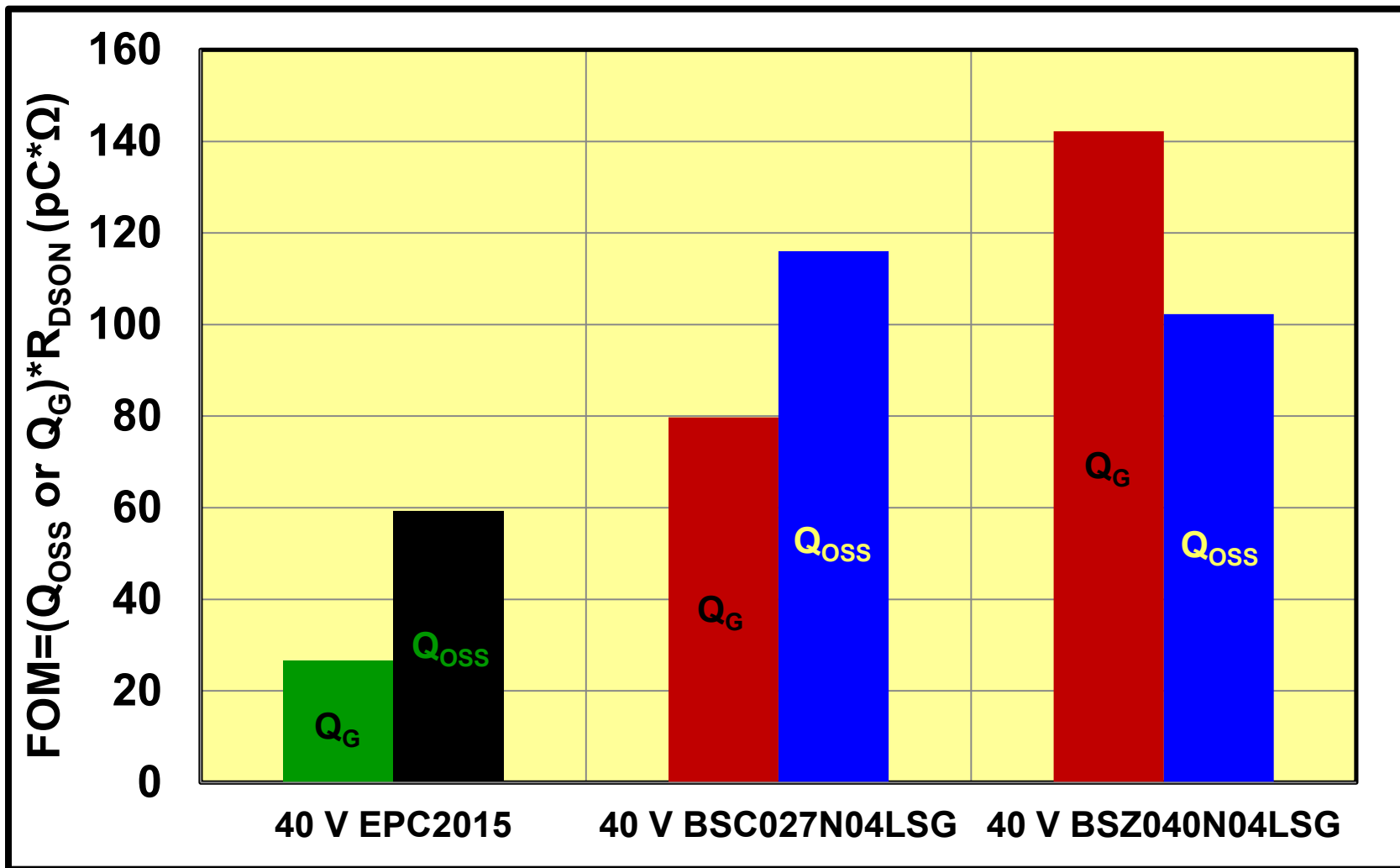
High Frequency DC/DC Transformer



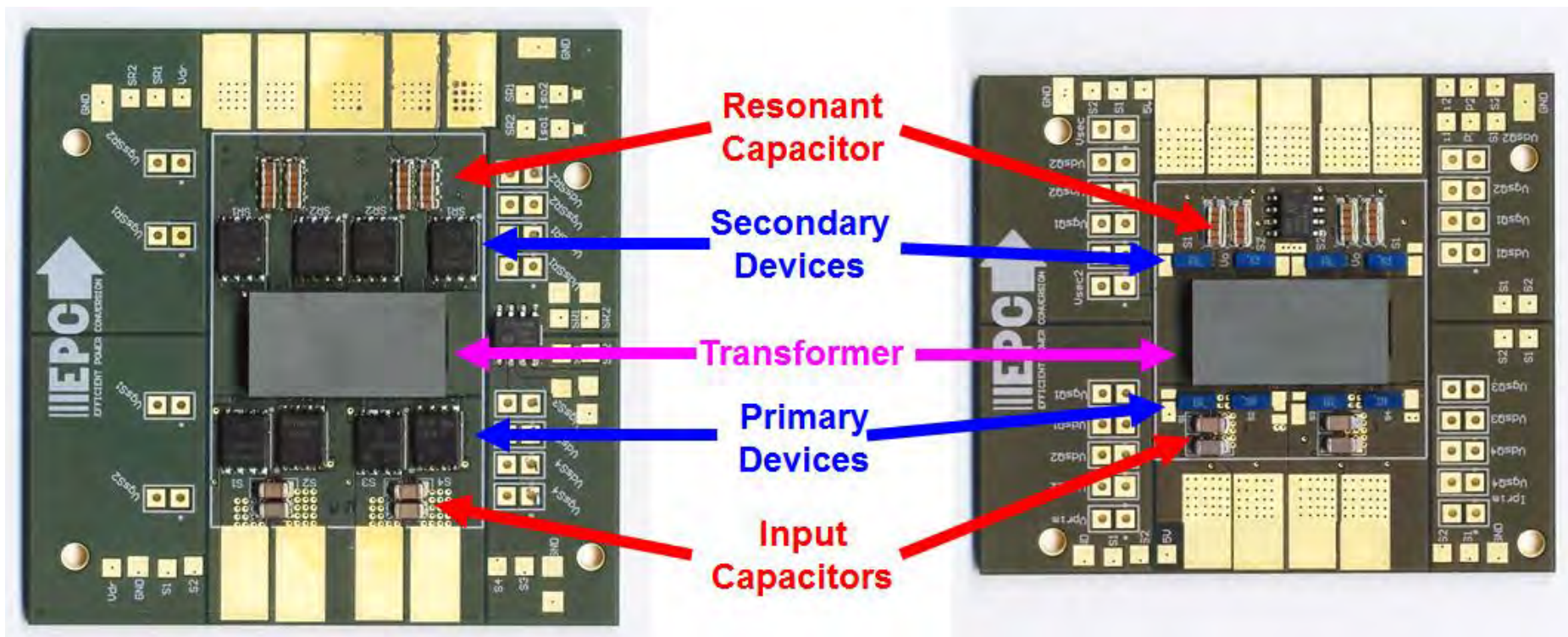
Ref: Y. Ren, M. Xu, J. Sun, and F. C. Lee, "A family of high power density unregulated bus converters," IEEE Trans. Power Electron., vol. 20, no. 5, pp. 1045–1054, Sep. 2005.



$V_{DS}=48\text{ V}$



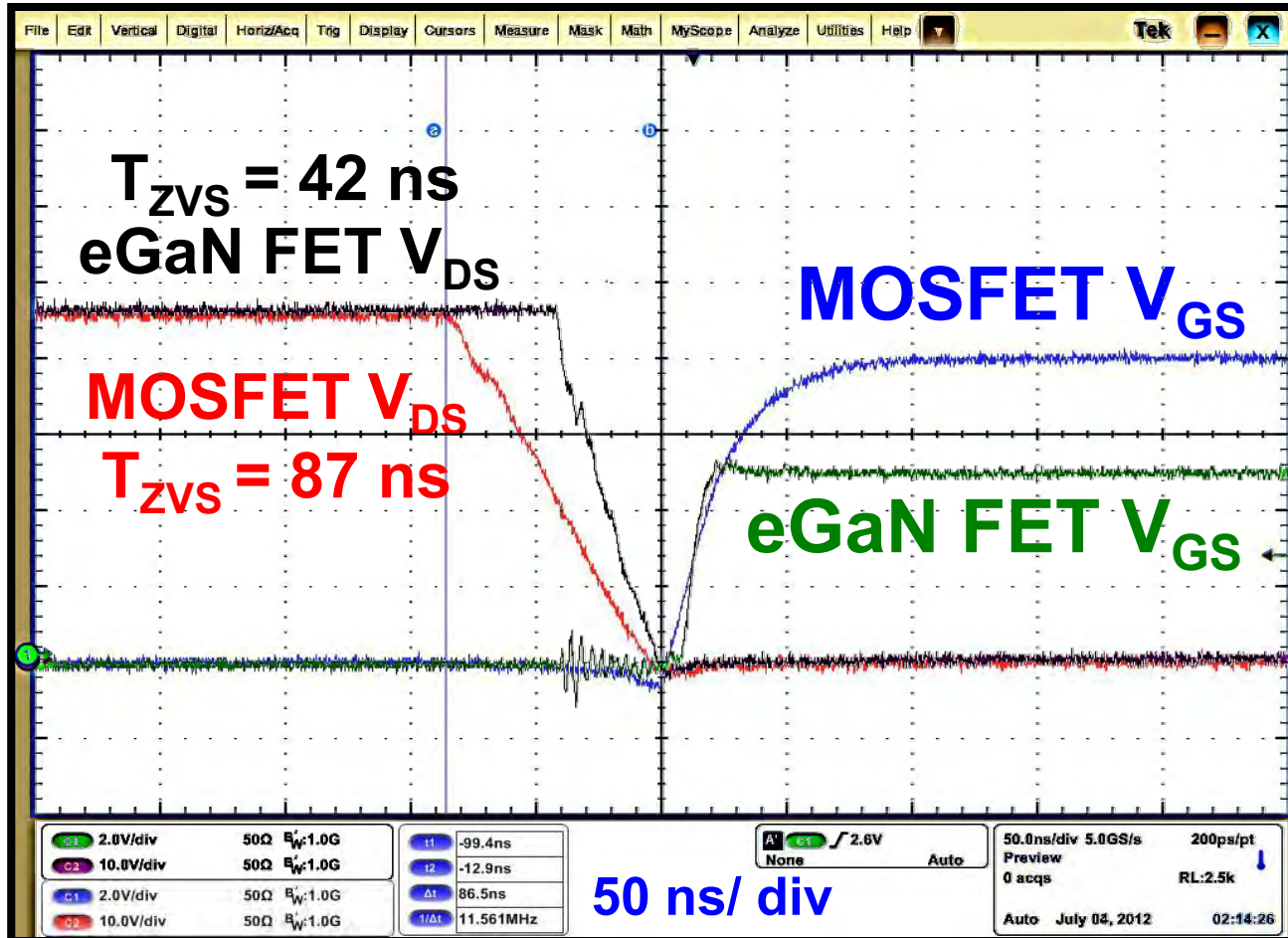
$V_{DS}=20\text{ V}$



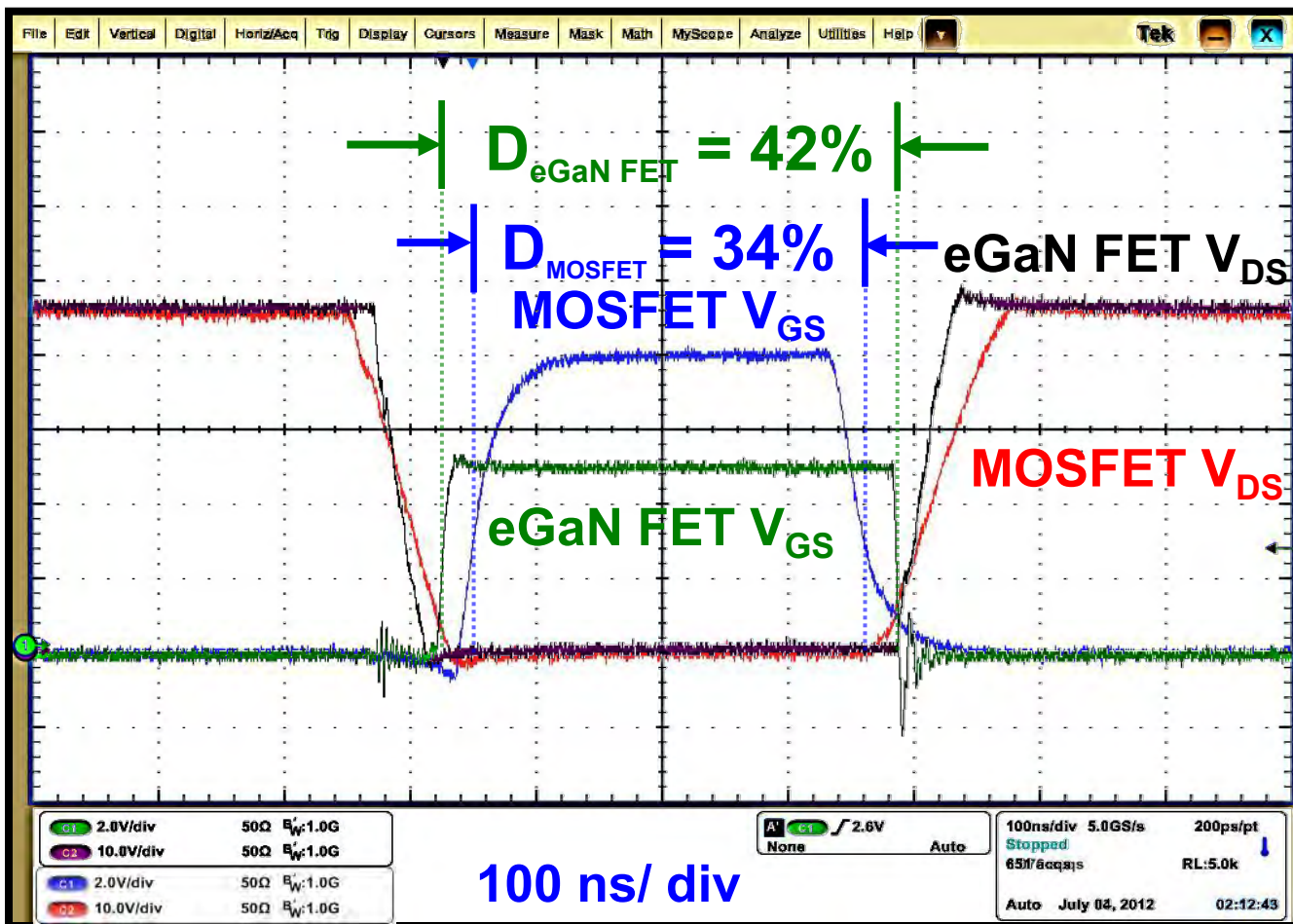
MOSFET

vs.

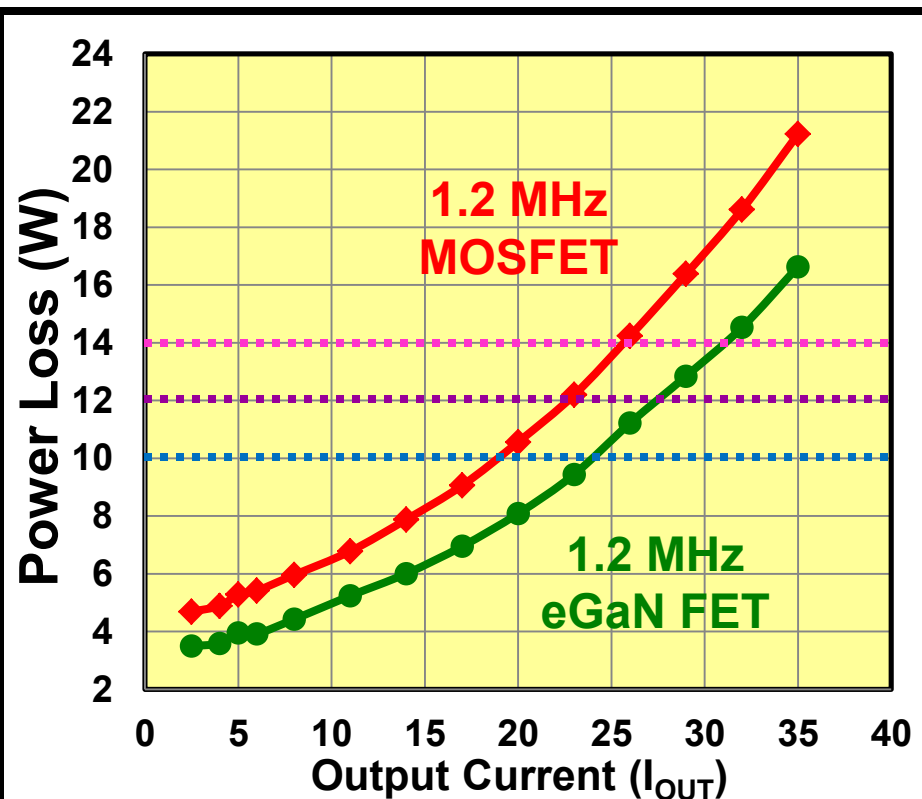
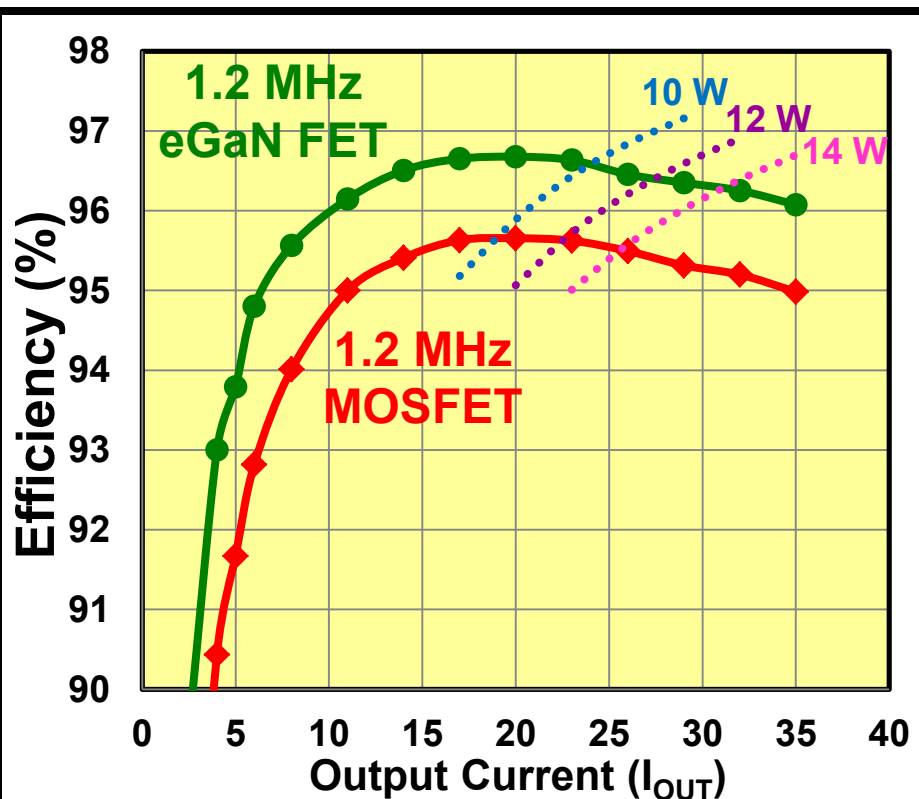
eGaN[®] FET



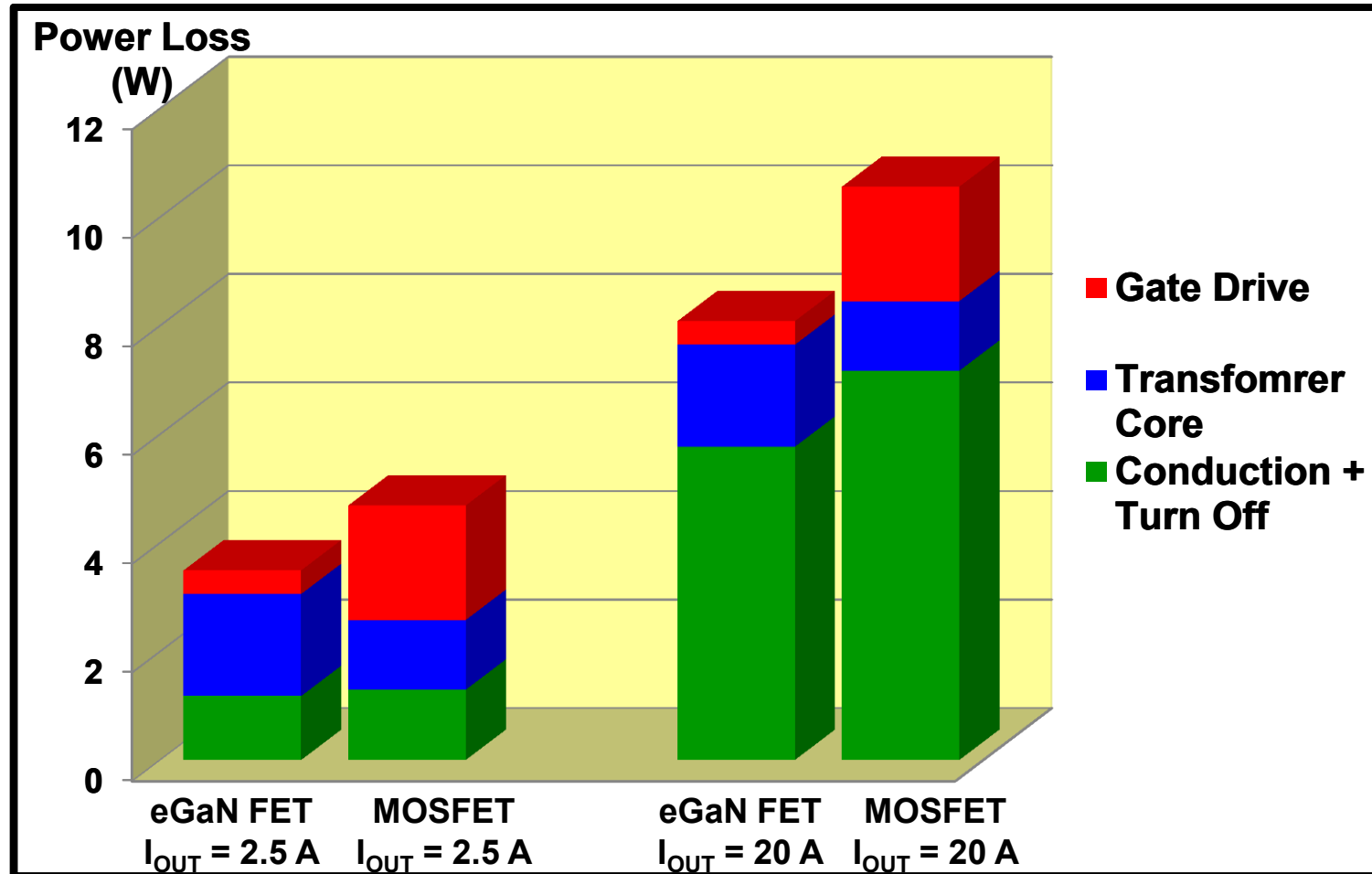
$F_S = 1.2 \text{ MHz}$, $V_{IN} = 48 \text{ V}$, and $V_{OUT} \approx 12 \text{ V}$



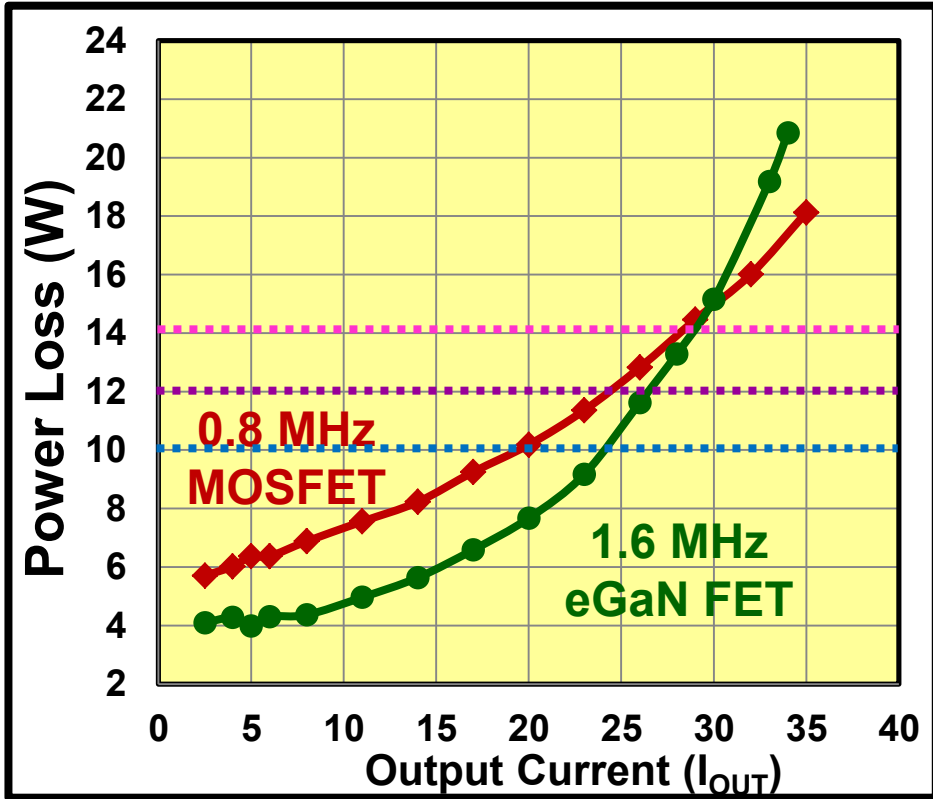
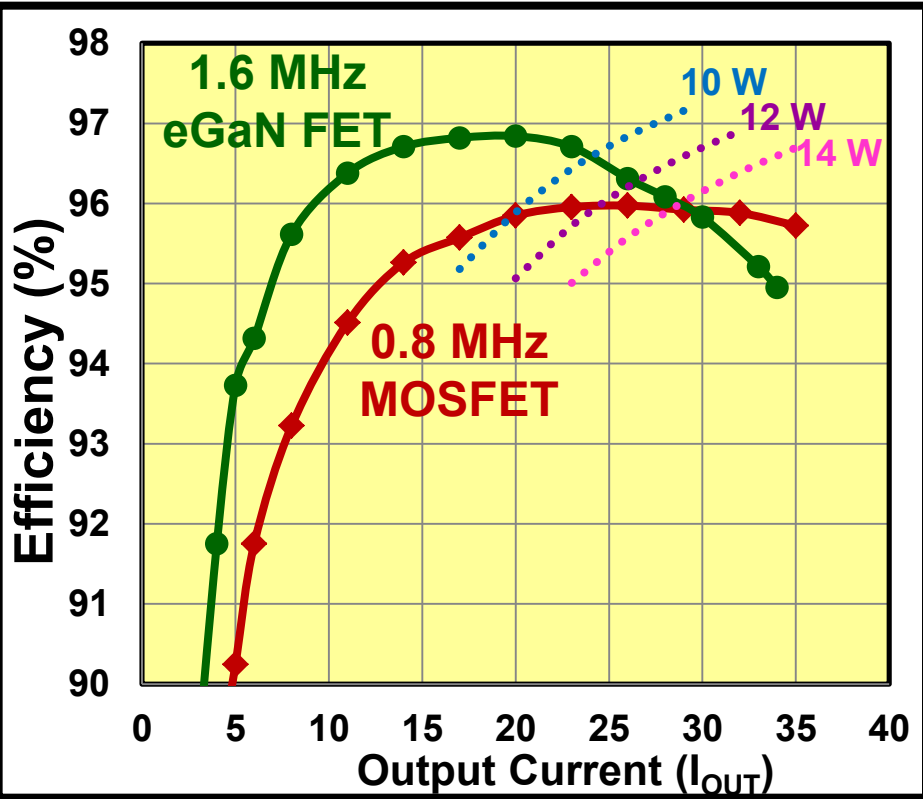
$F_S = 1.2\text{ MHz}$, $V_{IN} = 48\text{ V}$, and $V_{OUT} \approx 12\text{ V}$



$F_S = 1.2 \text{ MHz}$, $V_{IN} = 48 \text{ V}$, and $V_{OUT} \approx 12 \text{ V}$



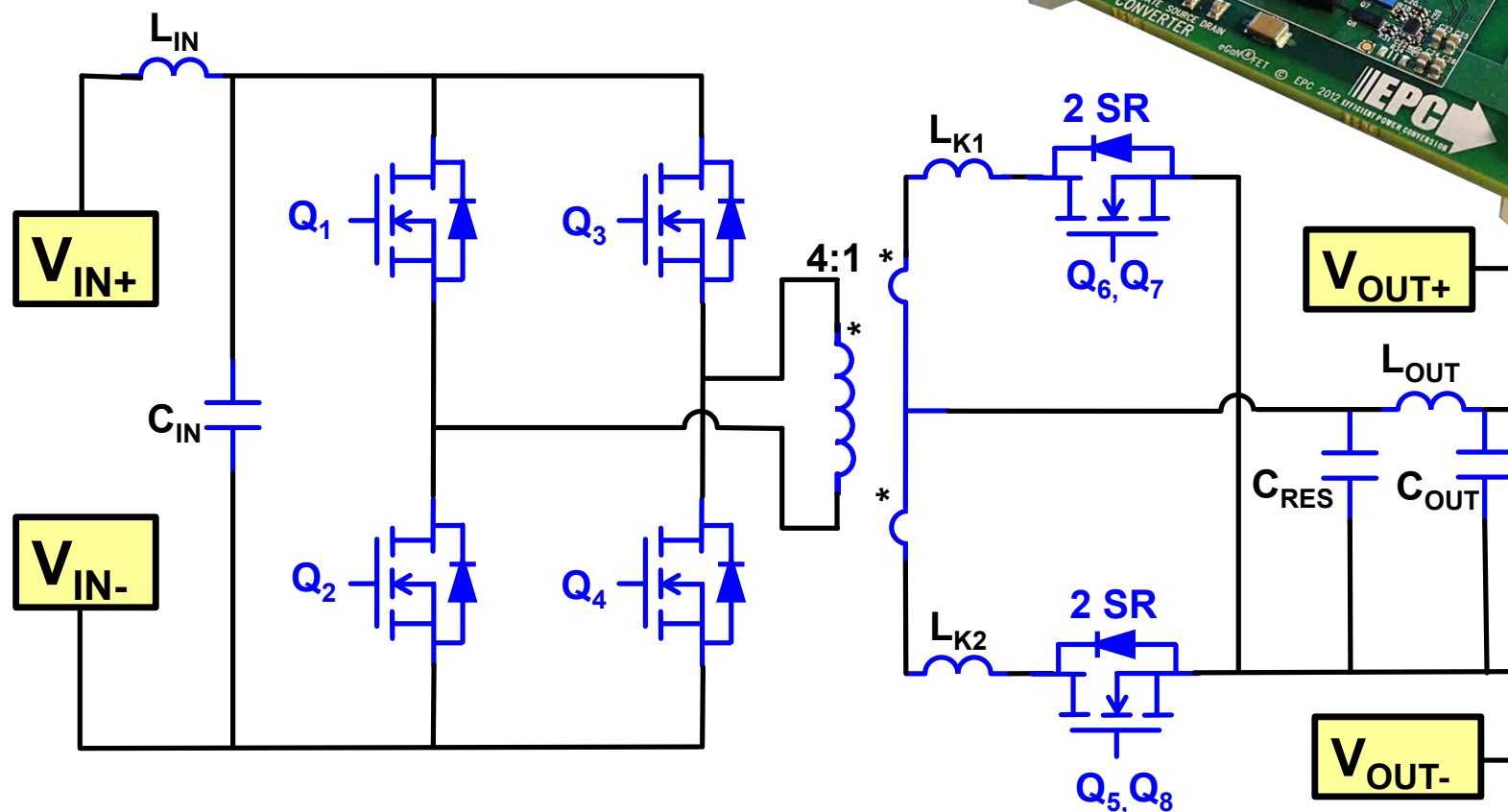
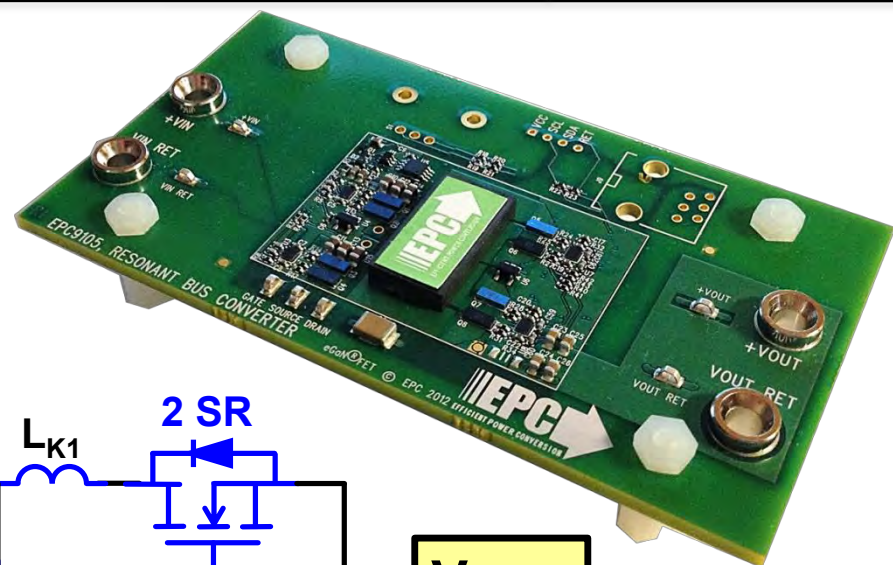
$F_s = 1.2 \text{ MHz}$, $V_{IN} = 48 \text{ V}$, and $V_{OUT} \approx 12 \text{ V}$

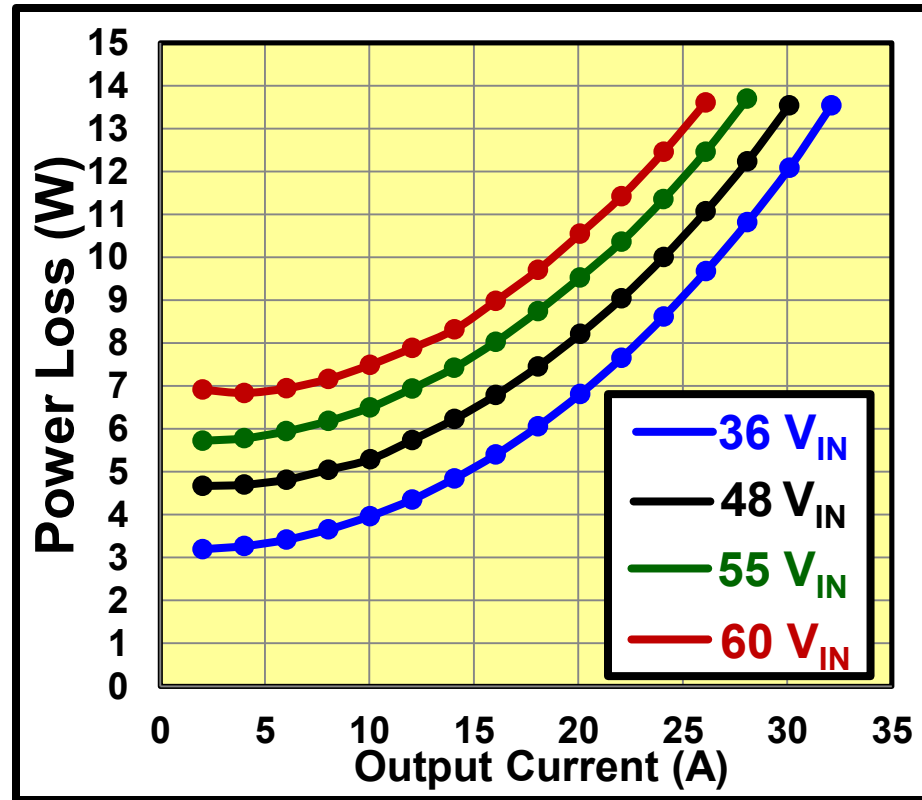
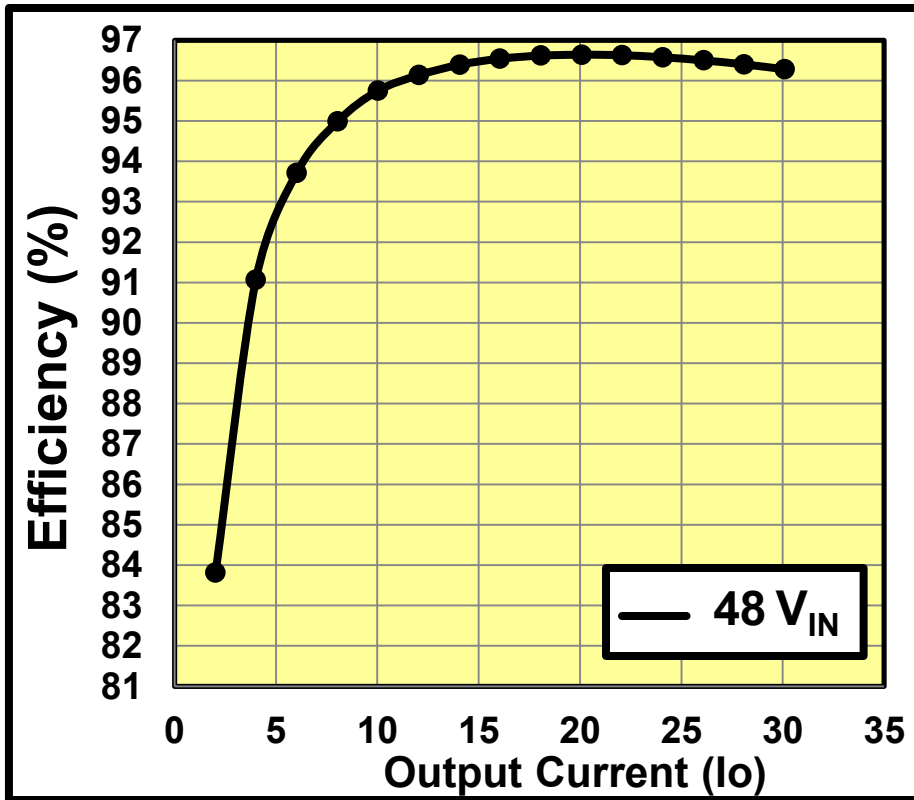


$V_{IN} = 48 \text{ V}$, and $V_{OUT} \approx 12 \text{ V}$

EPC9105 Demonstration Board

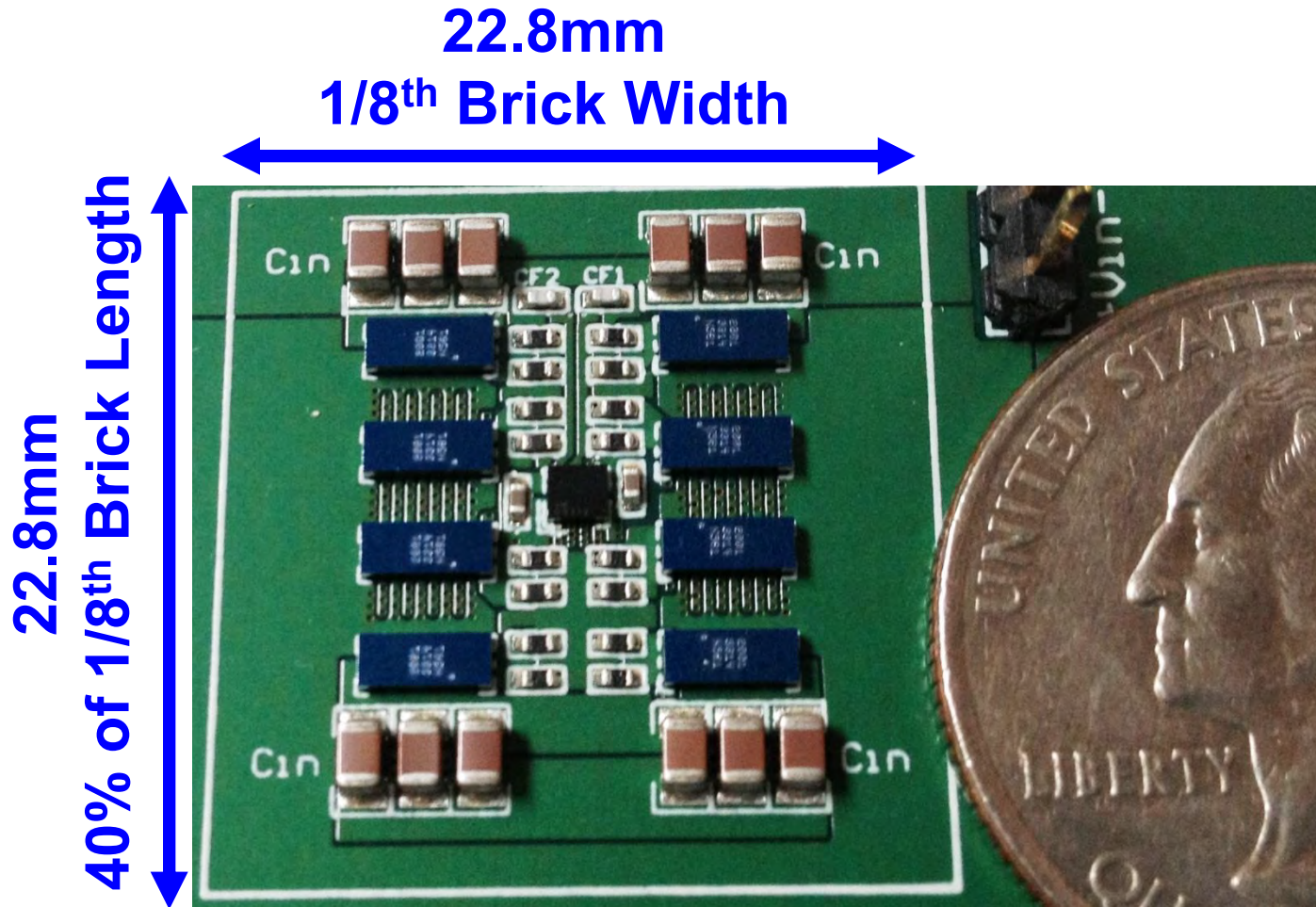
36 - 60 V_{IN}, 12 V_{OUT}, 350 W, 1.2 MHz



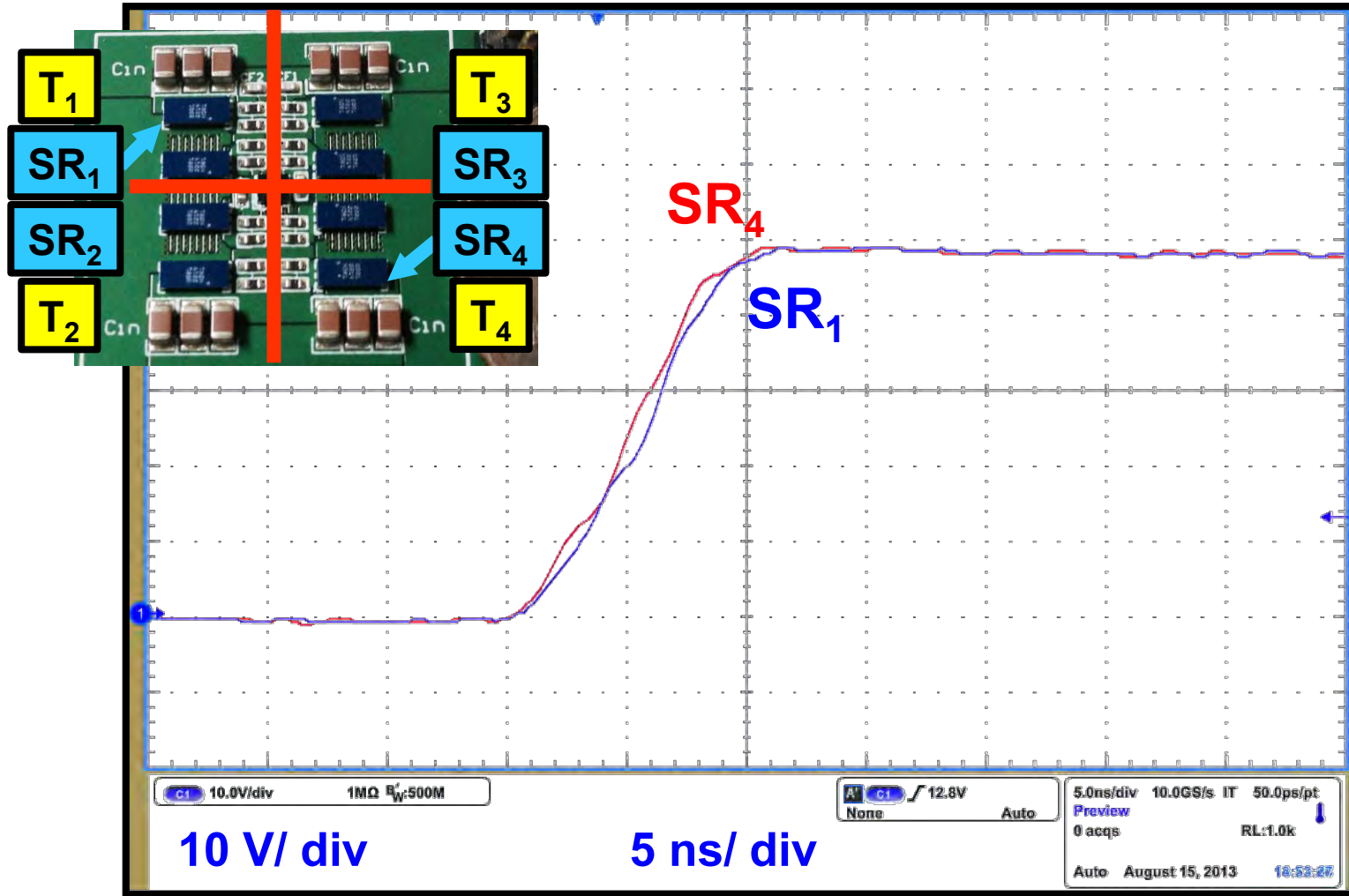


$F_s = 1.2 \text{ MHz}$, $V_{IN} = 36\text{-}60 \text{ V}$, and $V_{OUT} \approx V_{IN} / 4$

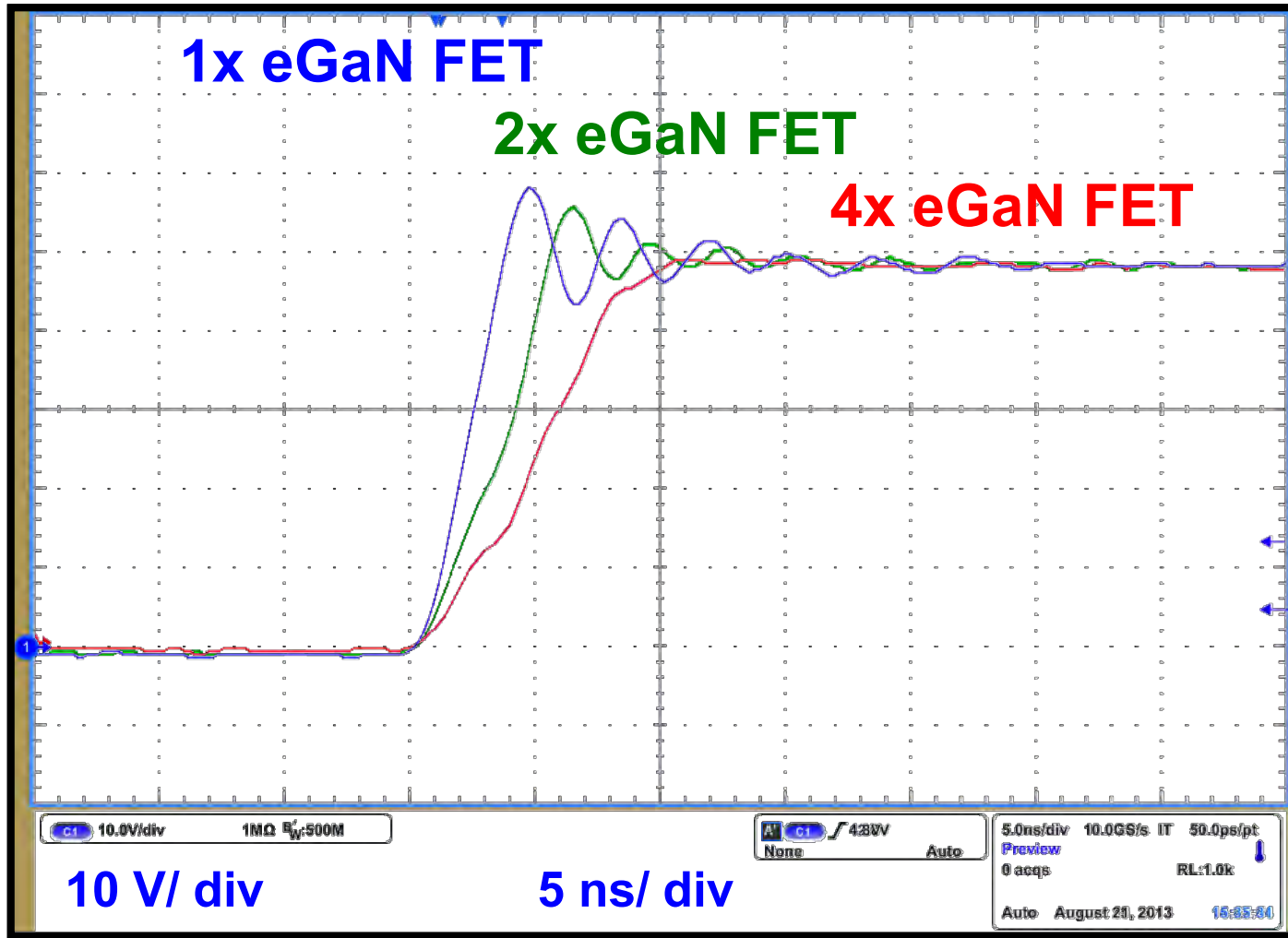
High Current Non-Isolated Buck Converter



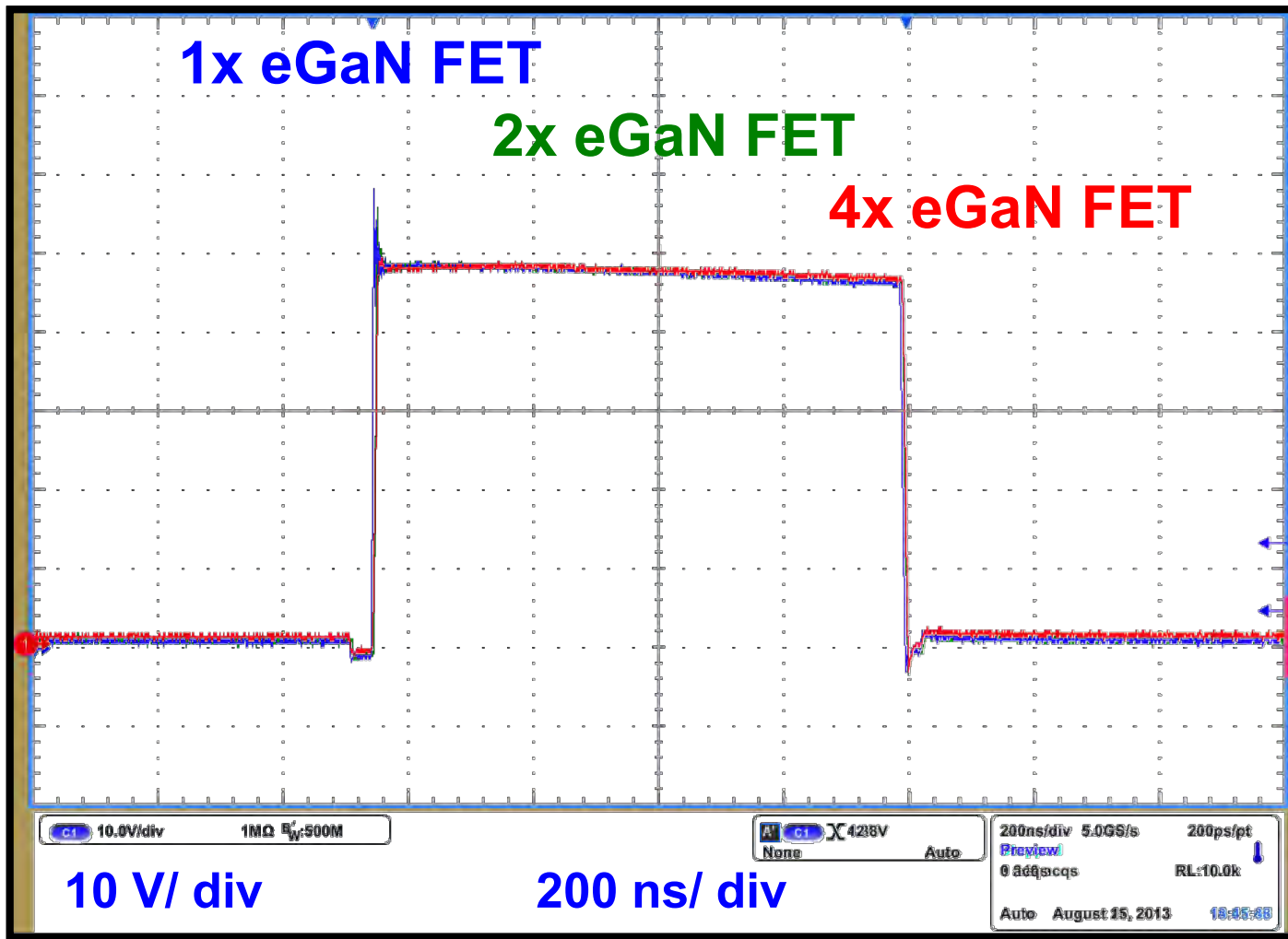
8 x EPC2001
4 Top Devices and 4 SR in parallel



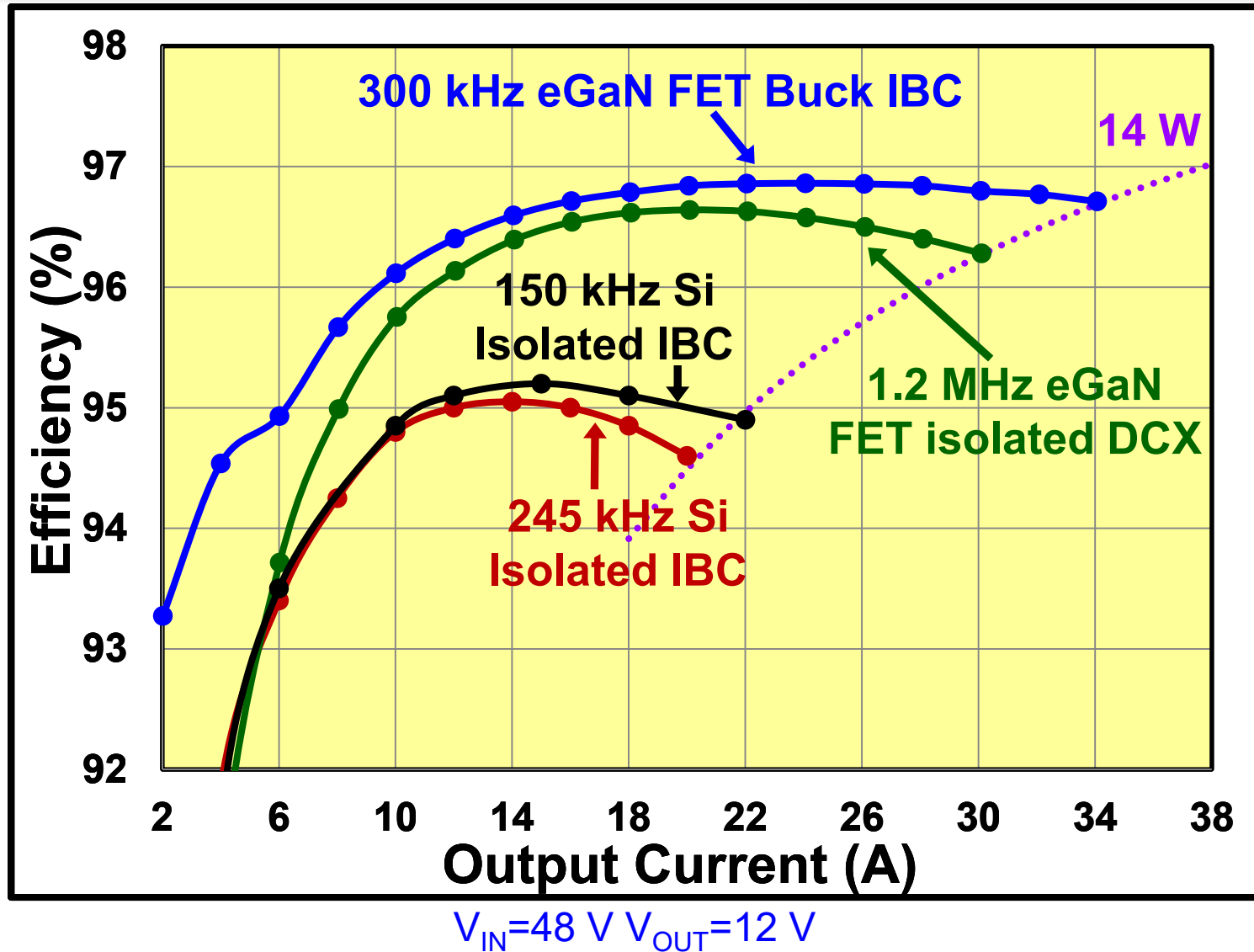
$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $I_{OUT}=30\text{ A}$ $F_S=300\text{ kHz}$ $L=3.3\text{ }\mu\text{H}$ GaN FET T/SR: 100 V EPC2001



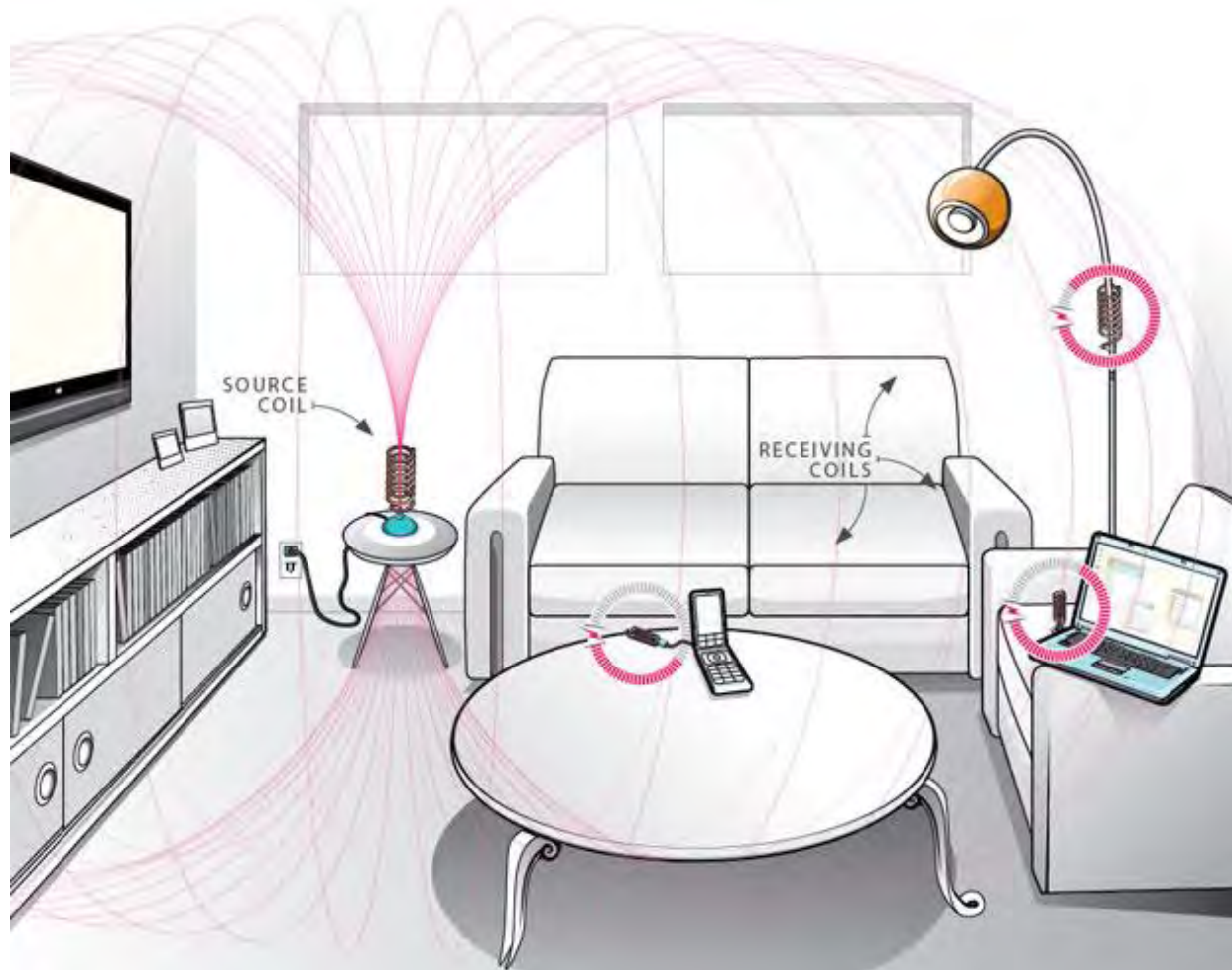
$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $I_{OUT}=30\text{ A}$ $F_S=300\text{ kHz}$ $L=10\text{ }\mu\text{H}$ GaN FET T/SR: 100 V EPC2001

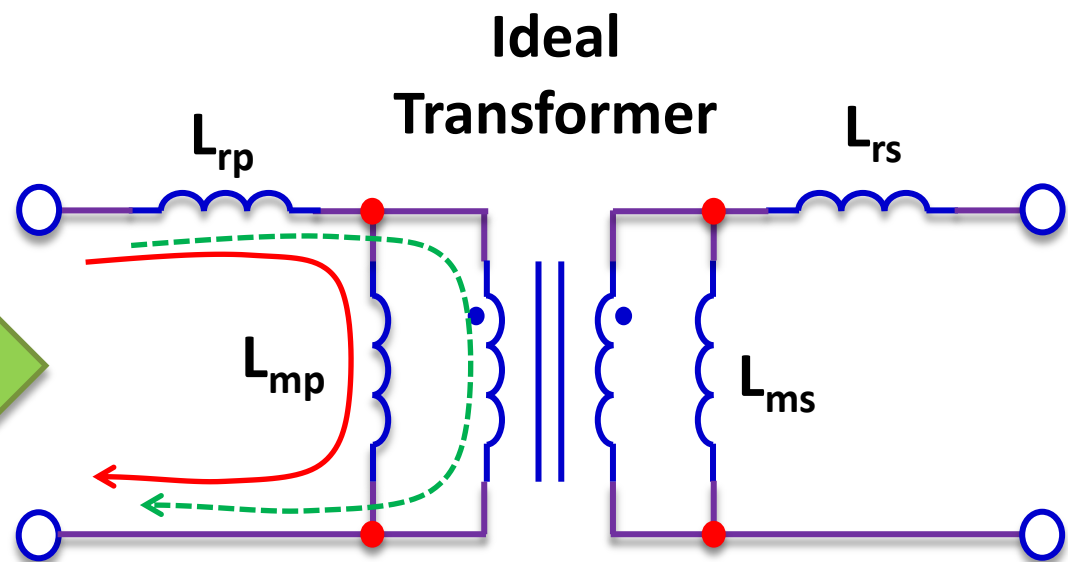
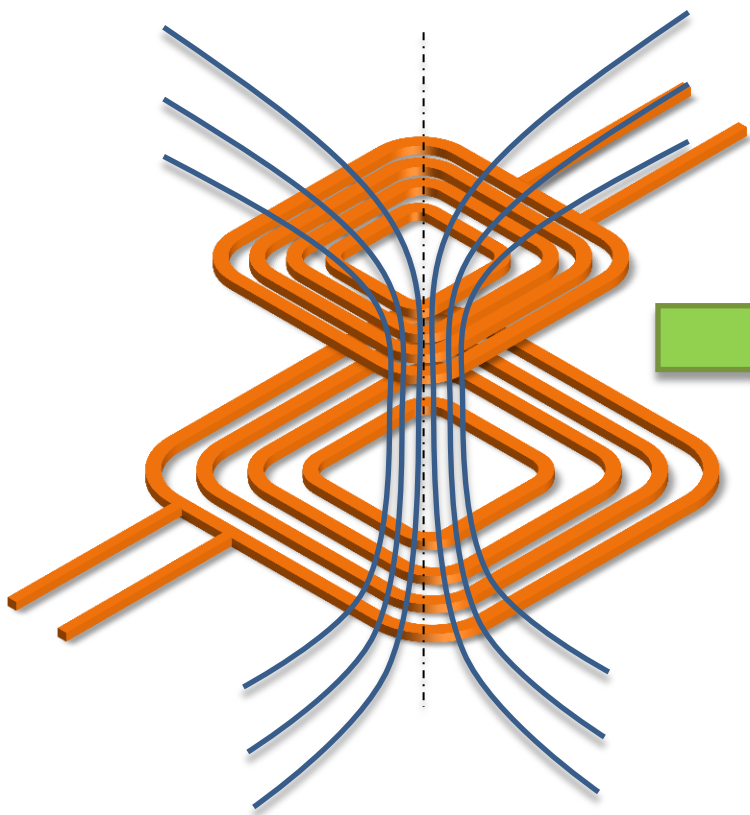


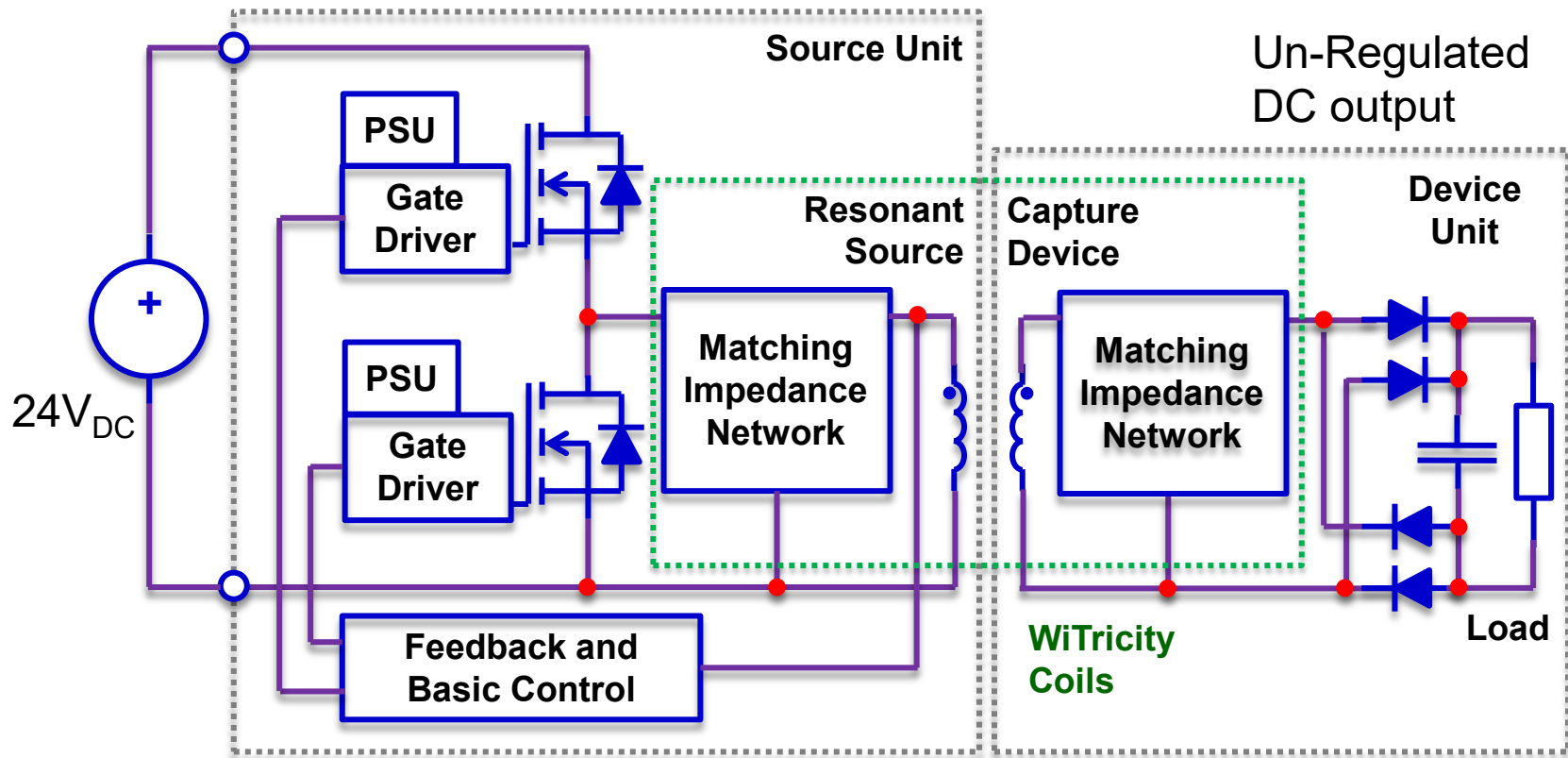
$V_{IN}=48\text{ V}$ $V_{OUT}=12\text{ V}$ $I_{OUT}=30\text{ A}$ $F_S=300\text{ kHz}$ $L=10\text{ }\mu\text{H}$ GaN FET T/SR: 100 V EPC2001

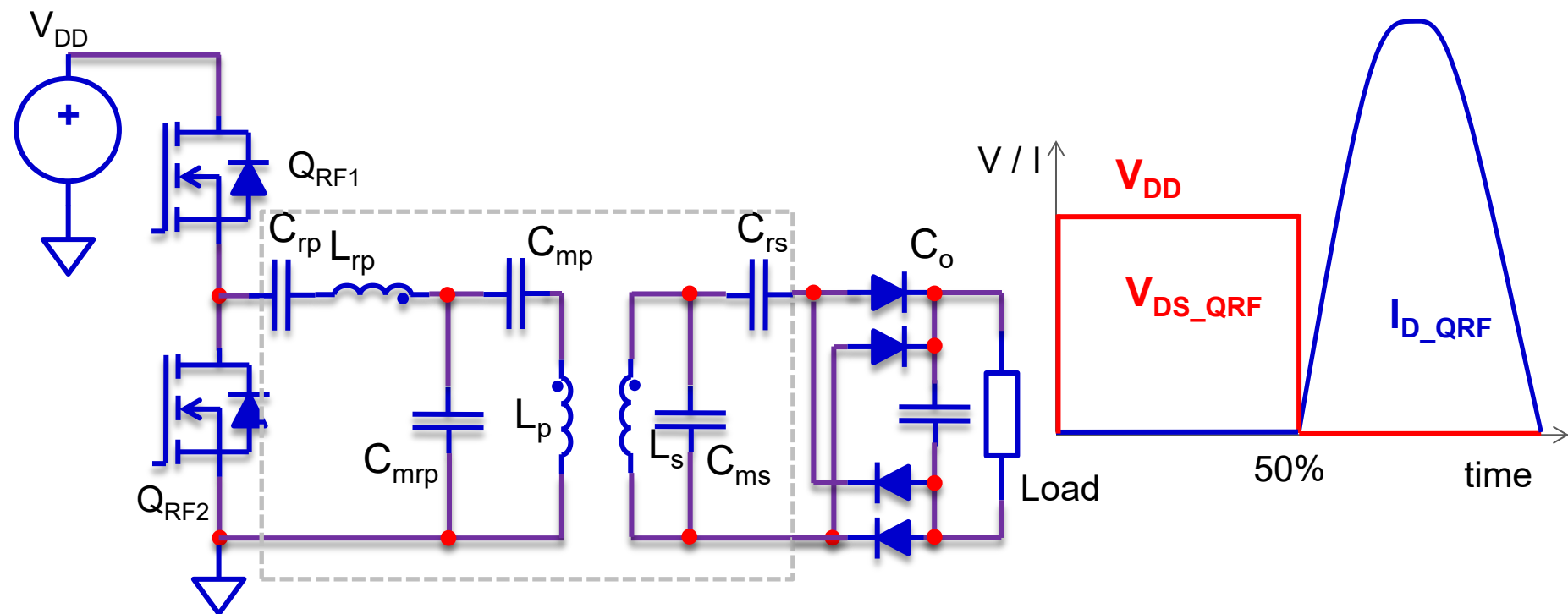


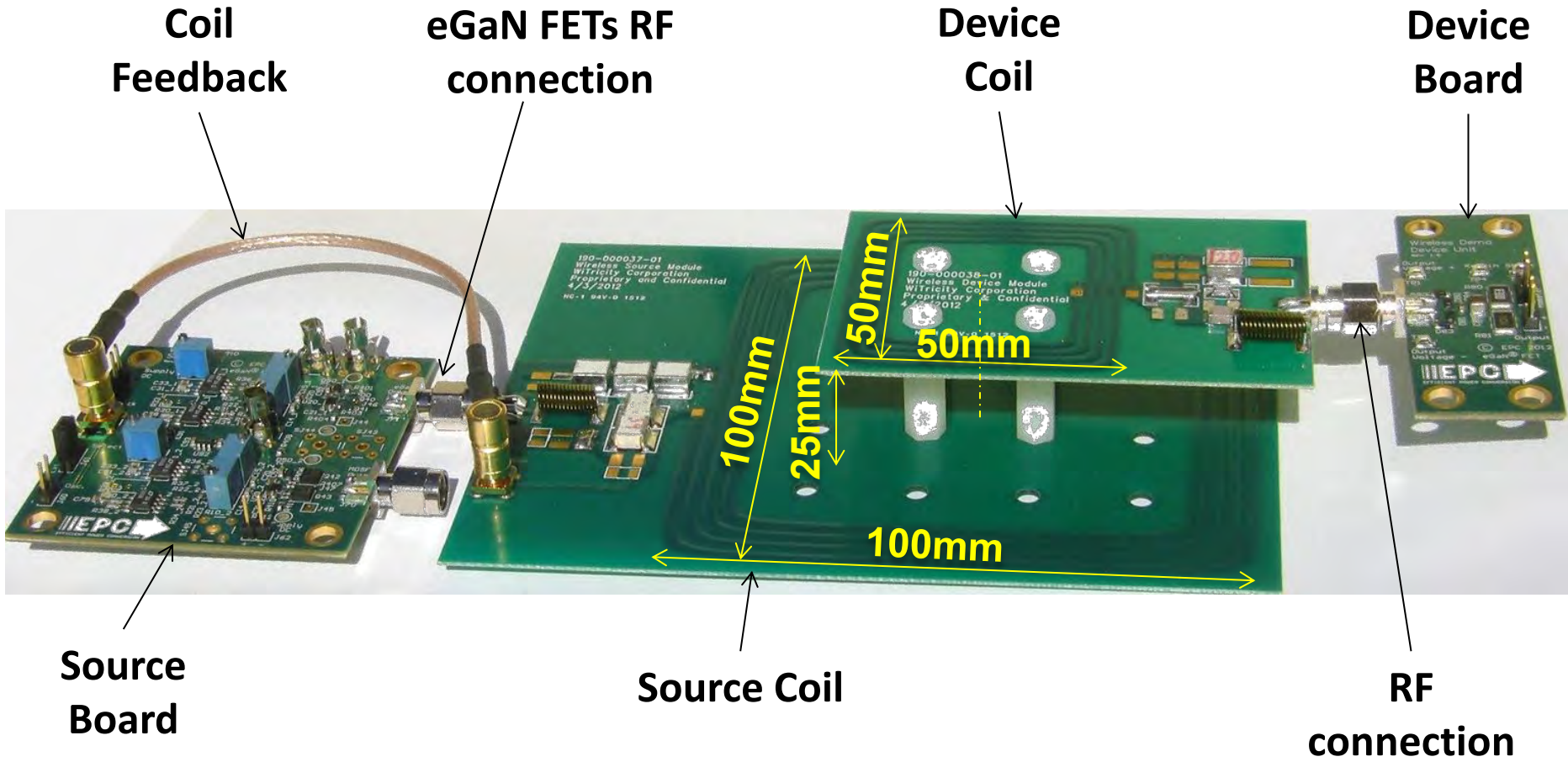
Wireless Power

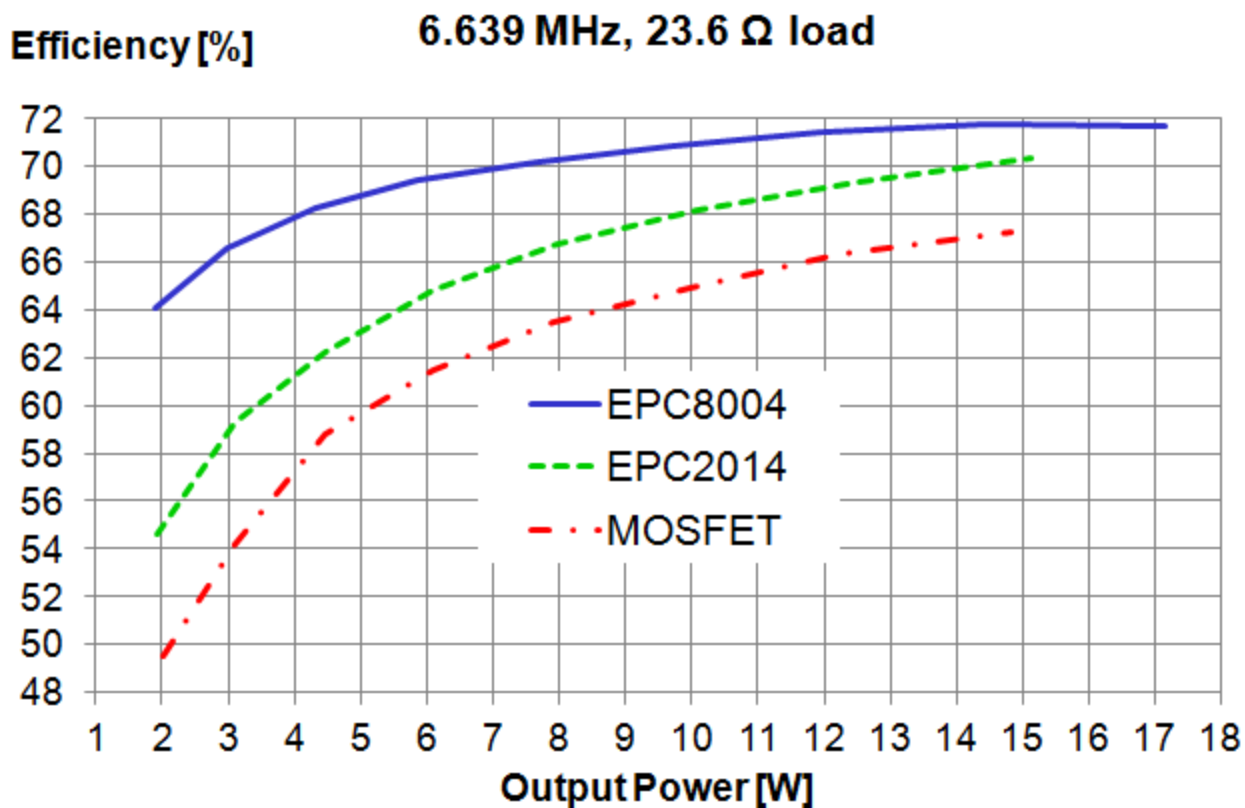












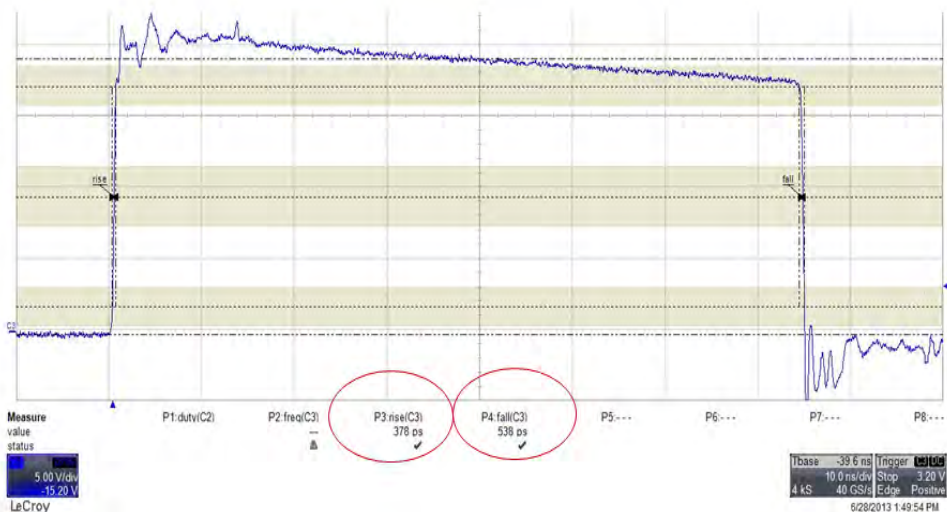
Voltage Mode Class D Operation

A Look into the Future

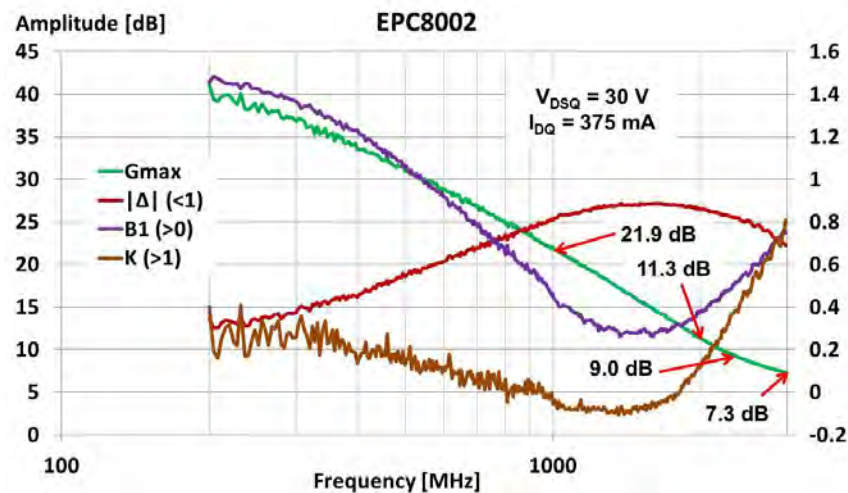
- Does it enable significant new capabilities?
- Is it easy to use?
- Is it VERY cost effective to the user?
- Is it reliable?

- Does it enable significant new capabilities?
- Is it easy to use?
- Is it VERY cost effective to the user?
- Is it reliable?

- 20 V
- 4 A load, 1 MHz
- 380 ps rise, 540 ps fall



EPC8007 driven by LM5113



Small signal Performance

- Does it enable significant new capabilities?
- Is it easy to use?
- Is it VERY cost effective to the user?
- Is it reliable?

It's just like a MOSFET

except

The high frequency capability makes circuits using eGaN FETs sensitive to layout

The lower $V_{G(MAX)}$ of 6 V makes it advisable to have V_{GS} regulation in your gate drive circuitry

Universities all over the world are graduating well-trained engineers experienced in the use of GaN Transistors

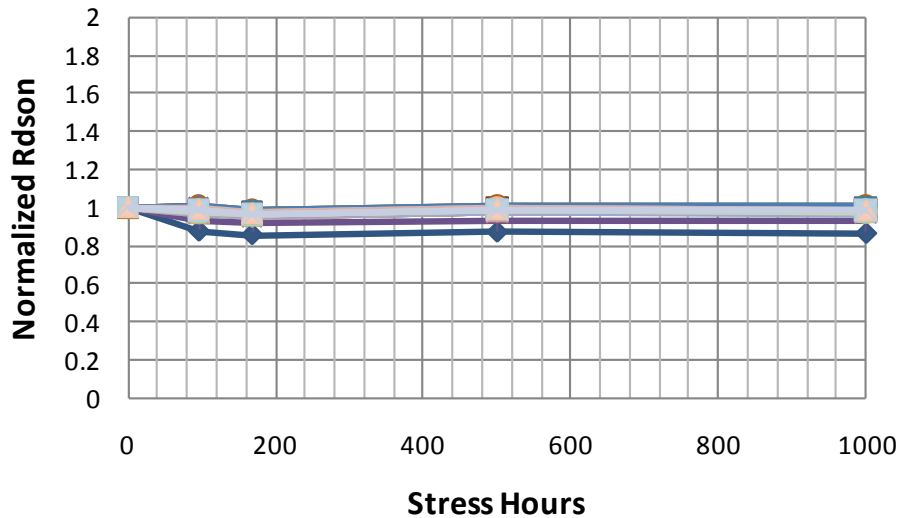
- Virginia Tech
- Ohio State University
- University of Tennessee
- Florida State University
- Auburn University
- University of California at Santa Barbara
- Rensselaer Polytechnic Institute
- Hong Kong University of Science and Technology
- Cornell University
- Katholieke Universiteit Leuven
- University of Bristol
- University of Glasgow
- University of Sheffield
- University of Warsaw
- University of Sydney
- Massachusetts Institute of Technology
- Cambridge University
- National Central University of Taiwan
- National Taiwan University
- Yale University
- Chang Gung University
- University of Florida
- Case Western University
- University of Toledo
- Kyushu Institute of Technology
- National Chiao Tung University
- University of Texas
- Yamaguchi University
- Universitat Kassel
- National Tsinghua University
- Mid Sweden University
- New Mexico State University
- University of Johannesburg
- University of Toronto
- Universita di Padova
- Delft University of Technology
- Missouri University of Science and Technology
- University of Maryland
- Insitituto Italiano di Technologia

- Does it enable significant new capabilities?
- Is it easy to use?
- Is it **VERY** cost effective to the user?
- Is it reliable?

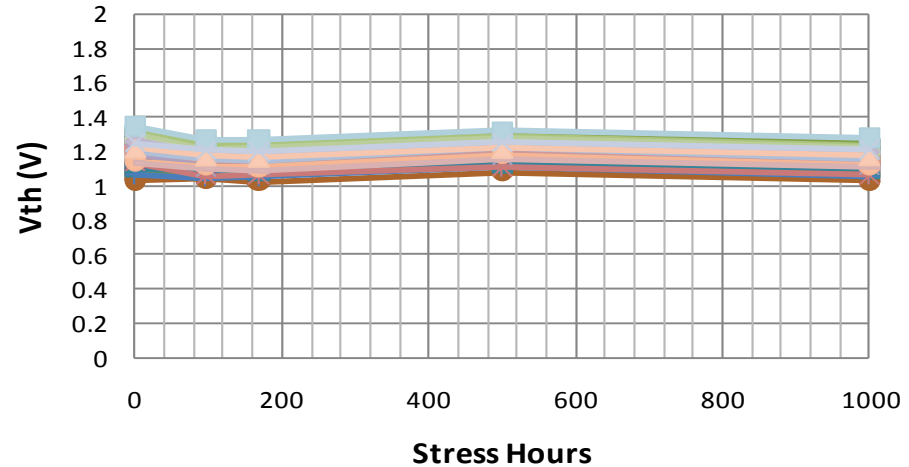
	2012	2015
Starting Material	same	same
Epi Growth	<i>higher</i>	<i>~same?</i>
Wafer Fab	same	lower
Test	same	same
Assembly	lower	lower
OVERALL	higher	<i>lower!</i>

- Does it enable significant new capabilities?
- Is it easy to use?
- Is it VERY cost effective to the user?
- **Is it reliable?**

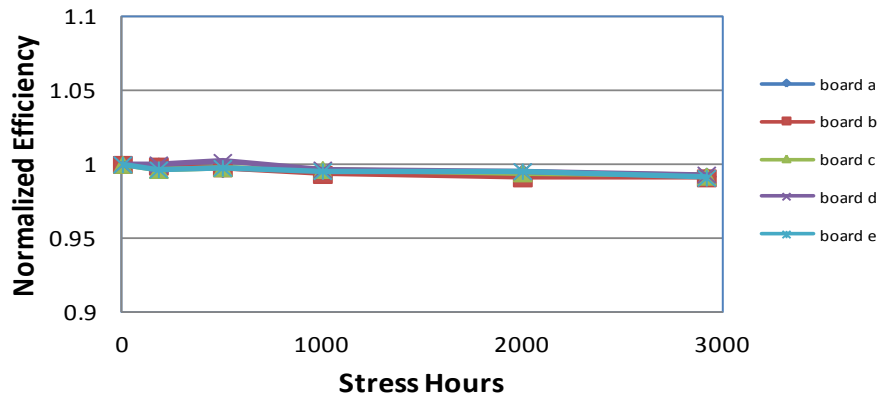
EPC2001 $R_{DS(ON)}$ after $100V_{DS}$ HTRB at $125^{\circ}C$



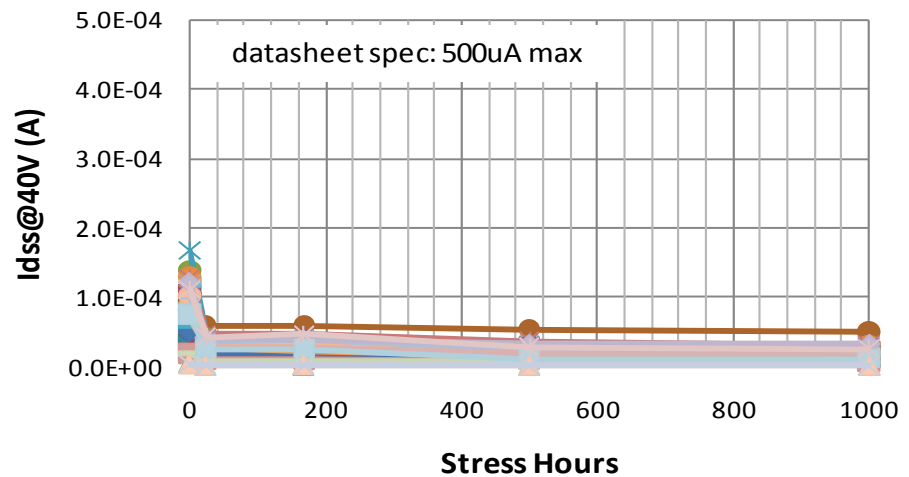
EPC2001 $V_{GS(TH)}$ after $100V_{DS}$ HTRB at $125^{\circ}C$



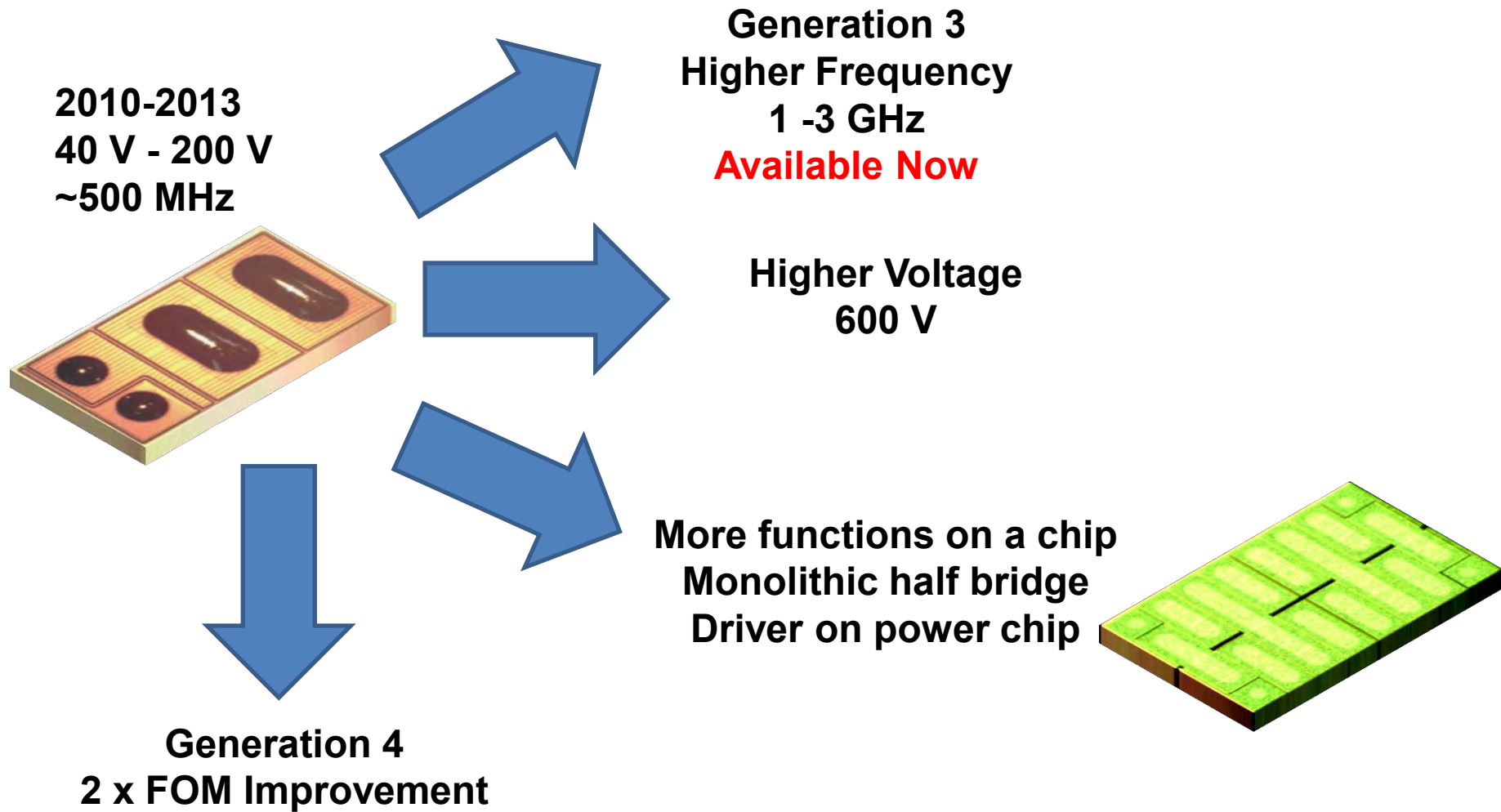
EPC9001 Efficiency after Op Life Test at $85^{\circ}C T_j$



EPC2015 I_{dss} after 40V H3TRB at $85^{\circ}C/85\%RH$



New Technology in the Future



- eGaN FETs enable exciting new applications such as RF Envelope Tracking and Wireless Power Transmission
- eGaN FETs have the potential to replace silicon power MOSFETs in power conversion applications with a low-cost and higher efficiency solution
- eGaN FETs are straightforward to use, but you can't just drop them into a MOSFET socket. Some R&D is needed – start today!